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LASER DIODE LABS INC NEW BRUNSWICK NJ

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INJECTION LASER DIODES FOR FIBER OPTIC COMMUNICATIONS.(U)

MAR 81 A GENNARD

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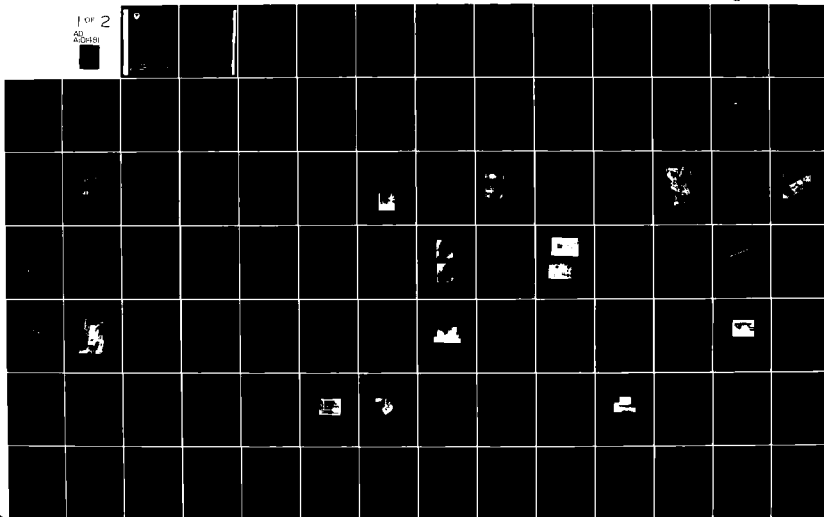
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**RESEARCH AND DEVELOPMENT TECHNICAL REPORT  
CORADCOM-76-0040-F**

MANUFACTURING METHODS AND TECHNOLOGY PROGRAM  
OF INJECTION LASER DIODES FOR USE IN FIBER  
OPTIC COMMUNICATIONS.

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This project has been accomplished as part of the U.S. Army Manufacturing Methods and Technology Program which has as its objective the timely establishment of manufacturing processes, techniques, or equipment to insure the efficient production of current or future defense programs.

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SECTION I  
INTRODUCTION

The primary objective of this Manufacturing Method and Technology Engineering Program is threefold. First, the Injection Laser Diode for use in Fiber Optic Communications as outlined in Specification SCS-516 must be transferred from a developmental device to a manufactured commercial product without adversely affecting the performance characteristics of the device. Secondly, the manufacturing methods and techniques necessary for the production of the laser diode be developed and implemented to insure the highest degree of device quality and reliability at a reasonable cost. Thirdly, verification of device performance and quality for injection lasers produced in a manufacturing environment must be carried out by means of rigorous testing and evaluation to demonstrate the technical adequacy of the manufacturing methods developed under this contract.

This report describes the techniques and methods used to attain the goals as described above. In particular laser chip concepts and design, package concepts and design and environmental and electrical testing were key areas and established the emphasis required to achieve the successful completion of the program.

## SECTION II

### DEVICE DESIGN REQUIREMENTS AND PERFORMANCE SPECIFICATIONS

#### 2.1 Electro-Optical Characteristics.

The performance characteristics of the Injection Laser for use in Fiber Optic Communications are described in detail in Technical Specification SCS-516. The device may be generally described as a double-hetero-junction (DH) GaAs - GaAlAs semiconductor laser capable of high data rate transmission at an emitting wavelength of 820 nm at room temperature. In addition, the device must be fiber optic compatible. An outline of the major electro-optical performance characteristics of the device is shown in Table 1. A more detailed description of the device, including environmental performance and parameter test methods can be found in SCS-516. In order to provide for a high degree of fiber optic system integrity through the use of redundancy, the injection laser diode has been designed to consist of a triad of discrete lasing elements contained within a single crystal of semiconductor material. This construction will be referred to as "monolithic triple stripe geometry" throughout this report.

#### 2.2 Device Structure.

To achieve the electro-optical characteristics outlined in Table 1, the narrow cavity ( $< .5\mu\text{m}$ ) GaAs-GaAlAs

Table 1

Electro-optical Performance Characteristics of the  
Injection Laser Diode for Fiber Optic Communications.

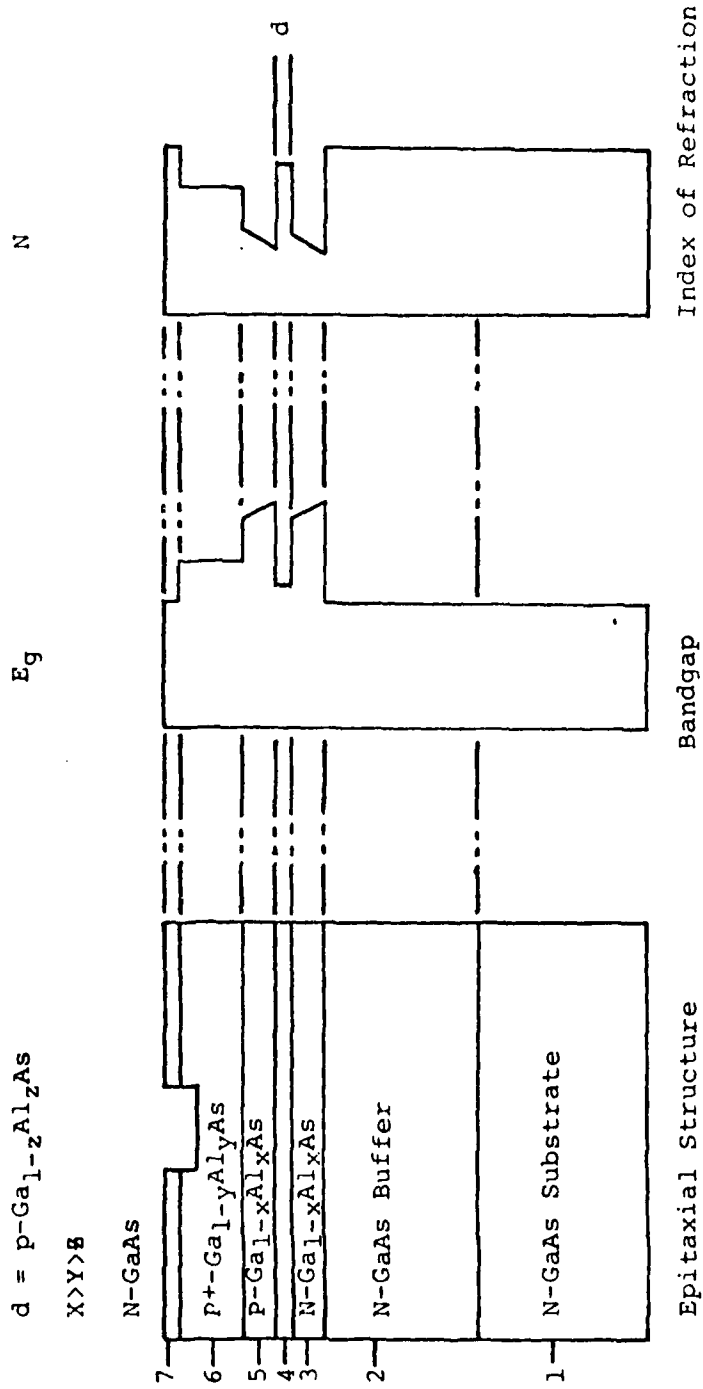
	<u>Min.</u>	<u>Max.</u>	<u>Units</u>
Optical Stripe Width	-	25	μm
Stripe Spacing	120	130	μm
Peak Output Power	200	-	mW
Average Output Power per Stripe	6.3	7.0	mW
Peak Wavelength	800	830	nm
Beam Divergence Parallel to Junction	-	15	degrees
Beam Divergence Perpendicular to Junction	-	40	degrees

Operating Conditions

$I_p = 3A$  max.  
 $V_f = 2.0V$  max. @ 3A.  
 $T_a = 25^\circ C$   
 $t_p = 10$  nsec  
 $DF = 10\%$

double heterojunction laser structure has been employed in conjunction with Laser Diode Laboratories' unique stripe geometry current isolation technique. Devices of this structure have demonstrated low threshold current density ( $<1\text{KA}/\text{cm}^2$ ), high differential quantum efficiency ( $>50\%$ ), fast rise time ( $<200\text{ psec}$ ), and sufficiently good beam characteristics to satisfy the requirements of most fiber optic systems applications. A schematic diagram of the structure is shown in Figure 1 along with the bandgap,  $E_g$ , and index of refraction,  $n$ , profiles perpendicular to the plane of the P/N junction.

The substrate, region 1, is n-type GaAs doped with Si to  $2 \times 10^{18}$ , with EPD  $<1\text{K}/\text{cm}^2$ . Existing dislocation networks and substrate surface imperfections are terminated by the growth of at least one n-type GaAs buffer layer, region 2, doped with Te to  $2 \times 10^{18}$ . Regions 3 and 5 are n-type and p-type GaAlAs respectively. These two layers confine light generated by the injection and recombination of carriers in the active region 3, a p-type GaAlAs layer (Si,  $1 \times 10^{18}$ ). Light is confined to the waveguide formed by regions 3 and 5 by virtue of the slight decrease in index of refraction at their boundaries with the lower bandgap active layer. The peak emission wavelength of the laser is controlled by the bandgap of the active region, which in turn is a function of the aluminum



Schematic Representation of the Epitaxial Structure for  
 Fabrication of Stripe Geometry Double Heterojunction  
 Injection Laser Diodes.



concentration of this layer. In this case, 8% aluminum in the active region corresponds to approximately 820 nm peak emission wavelength. In order to obtain the low threshold current densities required for high duty cycle operation and for satisfactory high temperature performance, the recombination volume, hence the active region thickness must be kept small. In the case of CW injection lasers with  $J_{th}$  typically  $< 1.5 \text{ KA/cm}^2$ , 'd' is normally 0.3 to 0.4  $\mu\text{m}$ .

Region 6 functions as a contact cap with aluminum incorporated in this p-type Ge doped layer to minimize lateral current flow by increasing its resistivity. Stripe geometry fabrication permits high duty cycle and room temperature CW operation by limiting the lasing region of the active layer to only a small portion of the junction width. This allows heat generated in the 25  $\mu\text{m}$  lasing region beneath the contact stripe to be dissipated throughout the entire bulk of the laser diode pellet. The topmost region 7 consists of lightly doped n-type GaAs. Following photolithographic definition of the contact stripe, 15 to 20  $\mu\text{m}$  wide channels are etched through this current blocking layer. Under conditions of forward bias, current is restricted to flow through the active region only beneath the etched channel. Elsewhere, because the p/n junction formed by interface between regions 6 and 7 is back-biased, the cavity remains unpumped.

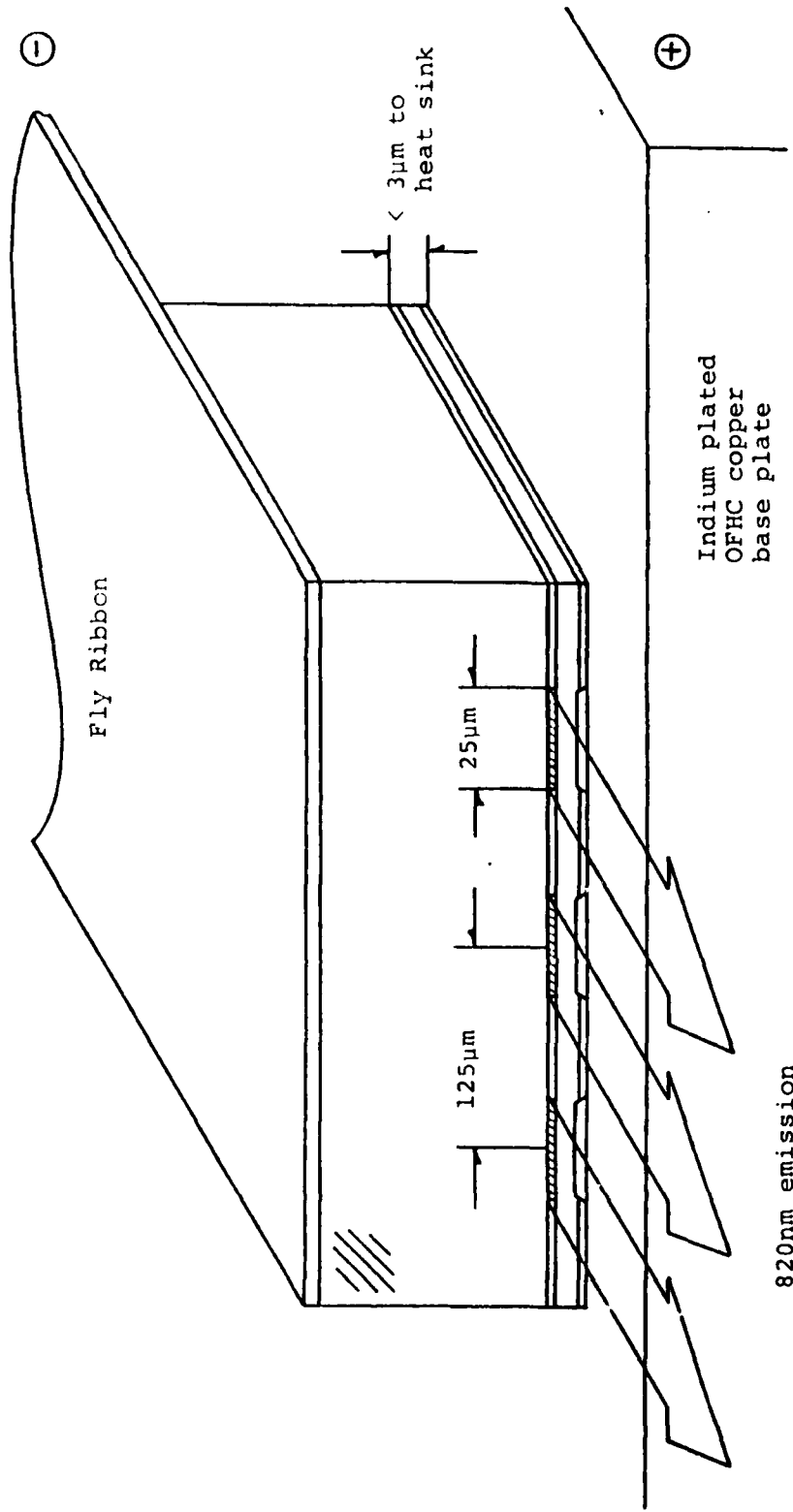
Details of the epitaxial synthesis and wafer processing for monolithic stripe geometry fabrication will be discussed in Section III.

### 2.3 Array Configuration.

The requirements of SCS-516 dictate the array configuration for the monolithic triple stripe geometry injection laser diode. Figure 2 illustrates the main features of the diode chip. The diode essentially consists of a triad of discrete lasing elements embedded in a single chip of epitaxial GaAs-GaAlAs material. Each element has a maximum optical source size of 25  $\mu\text{m}$  and the elements are spaced at 125  $\mu\text{m}$  intervals to facilitate coupling of each individual element to a triple fiber optic ribbon cable. Monolithic construction is preferred because the high degree of dimensional and compositional uniformity inherent in the hetero-epitaxial process guarantees optimum uniformity of electro-optical parameters among the three discrete lasing elements. In addition, the high degree of uniformity provides perfect geometrical alignment of the elements relative to each other. Fabrication of the monolithic triple stripe geometry array from epitaxially synthesized wafers is discussed in detail in Section III.

### 2.4 Package Requirements.

During the first quarter of the program, several modifications to the package outline were requested



Monolithic Triple Stripe Geometry Laser Diode  
Module Configuration

by ECOM for incorporation into the device design. These modifications to the proposed package configuration involved increasing the height of the pill package base to better facilitate coupling to the fiber cable end ferrule. Also, the overall height was adjusted to allow the use of square optical windows in production. Figure 3 shows the modified package outline drawing with tolerances. A detail drawing showing the laser module mounting position and orientation within the pill package is given in Figure 4. Final configuration of the package parts and a detailed description of their assembly is given in Section III.

### SECTION III

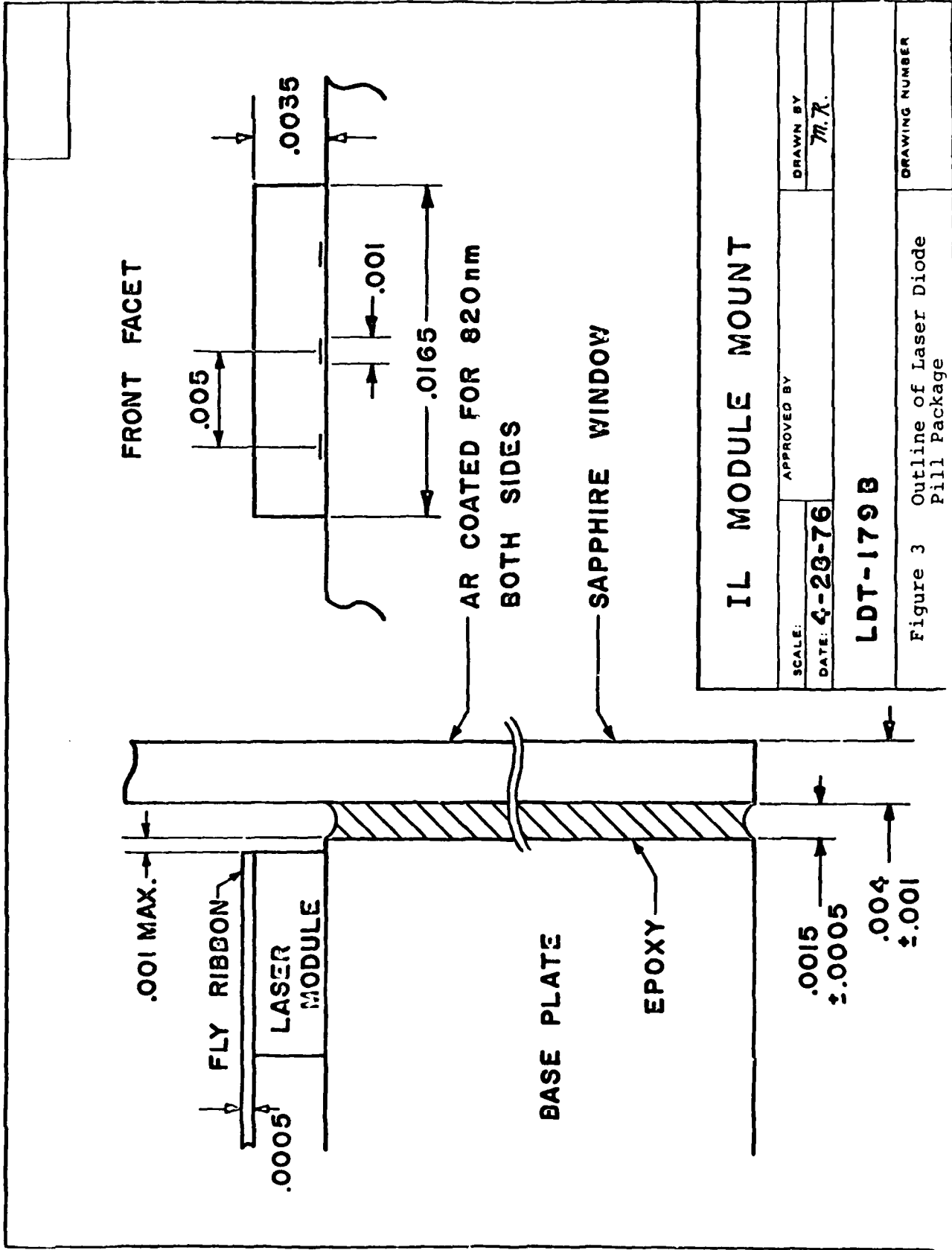
#### MANUFACTURING METHODS AND TECHNOLOGY ENGINEERING

#### 3.1 Materials Technology.

##### 3.1.1 Synthesis of Device Structure via LPE.

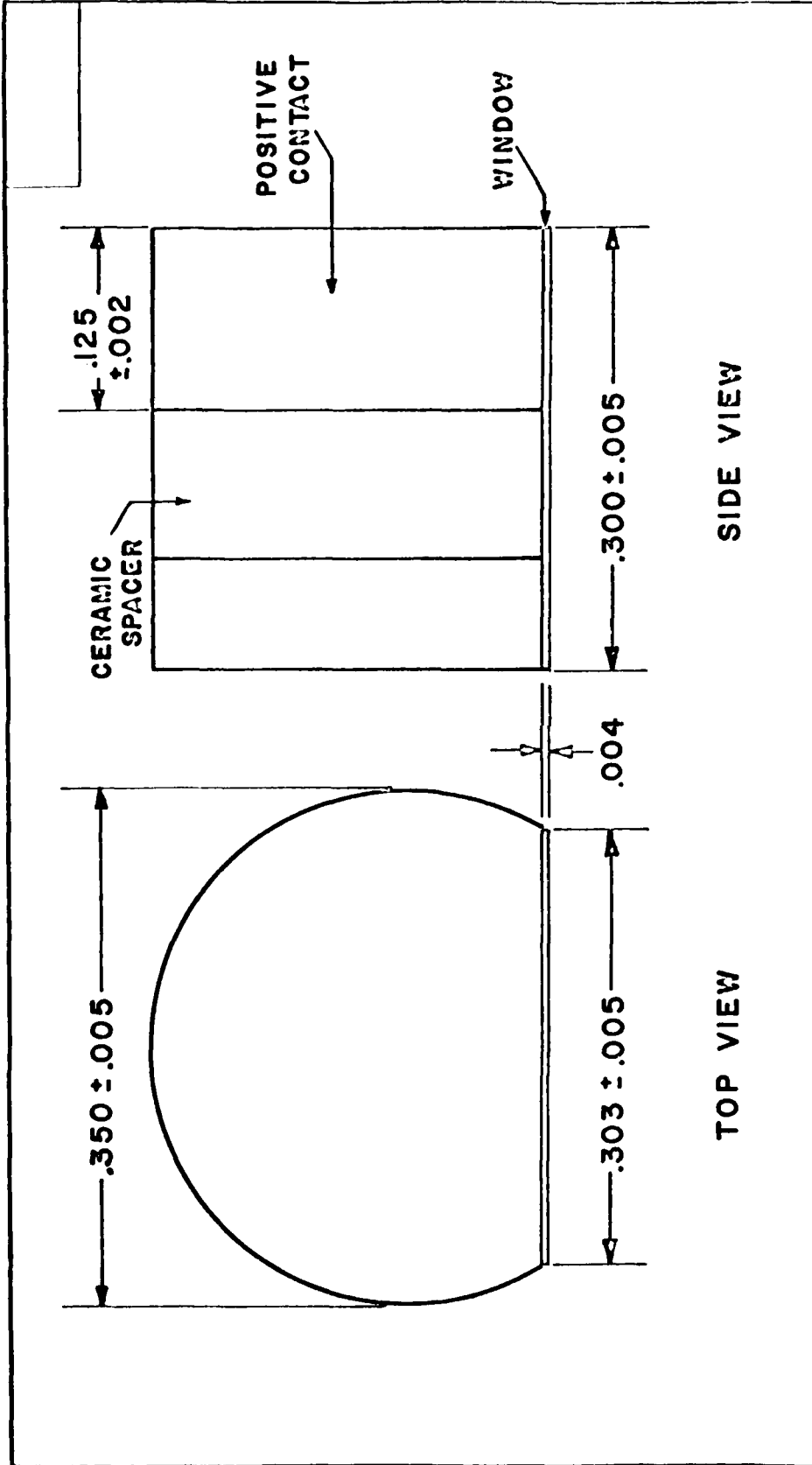
##### 3.1.1.1 Liquid Phase Epitaxial System.

Liquid phase epitaxy is a complex process in which single crystal layers of semiconductor material are deposited on a single crystal substrate of lattice matched material by precisely controlled cooling of a saturated solution in contact with the substrate. In the case of hetero-epitaxial synthesis of GaAs and GaAlAs layers for laser fabrication, gallium (Ga) is the preferred solvent and the substrate is normally high quality, low Etch Pit Density, (100)GaAs.



**IL MODULE MOUNT**

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Figure 3 Outline of Laser Diode Pill Package		DRAWING NUMBER



TOP VIEW

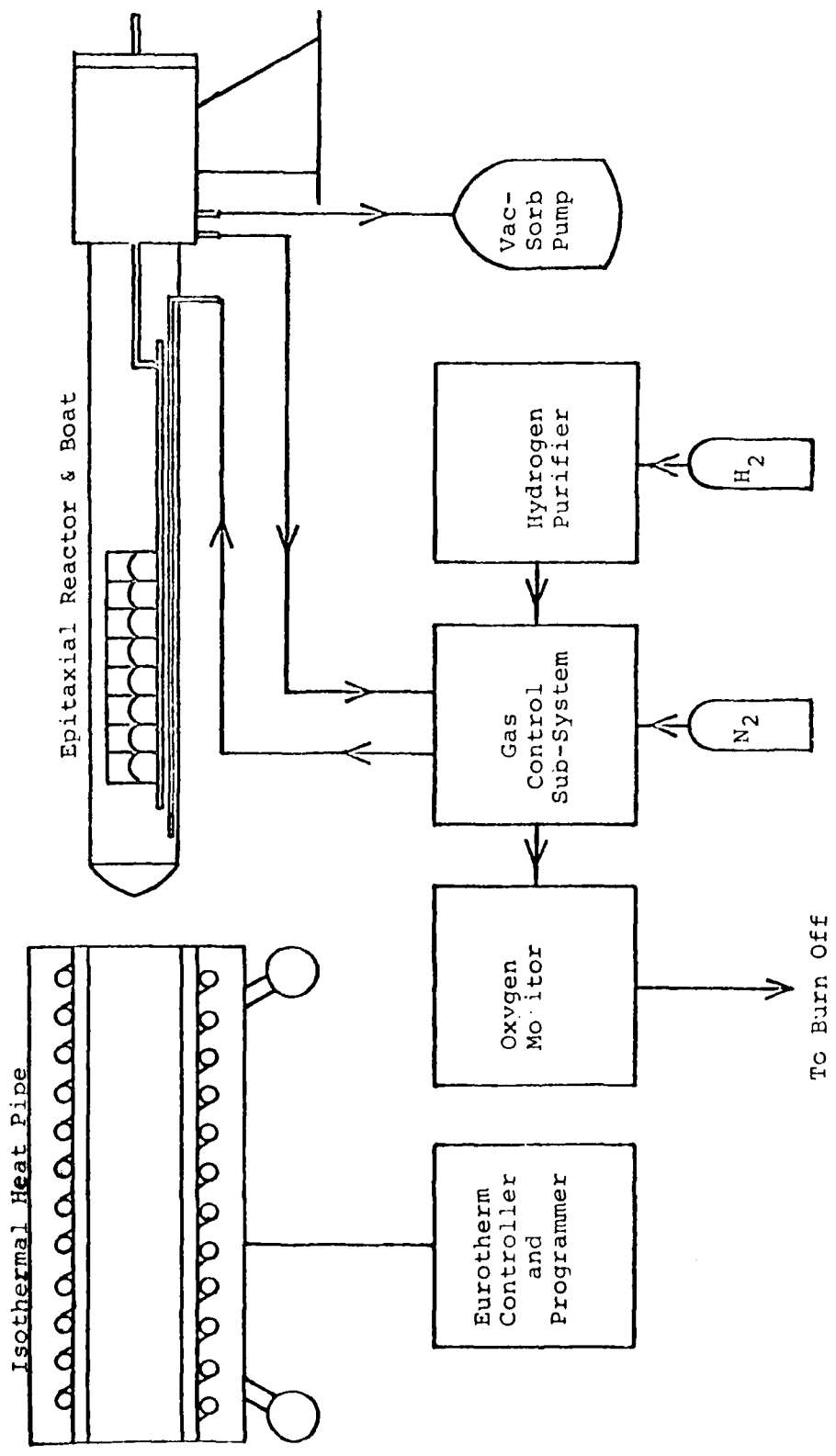
SIDE VIEW

ALL PURCHASED PARTS WILL BE MADE TO  $\pm .002$ " TOLERANCE. ASSEMBLY TOLERANCE AS SHOWN ABOVE.

<b>LDT-179 PILL PACKAGE</b>	
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Figure 4 Detail of Injection Laser Module Mount	
DRAWING NUMBER	

Crystal growth of these structures takes place at temperatures ranging between 750°C and 900°C and must be performed in an inert or reducing atmosphere to avoid the highly detrimental effects of oxygen contamination. The properly designed LPE reactor and support systems must satisfy several criteria in order to yield epitaxial wafers suitable for fabricating monolithic triple stripe geometry laser structures. These criteria are dictated by the uniformity, reliability, and produceability requirements of semiconductor optoelectronic components for volume commercial manufacture. Maximum surface area, layer thickness uniformity, compositional uniformity, and minimum defect density are required. In addition, the as-grown surface morphology of the terminal layer must be compatible with photolithographic processing for the definition and patterning of stripe geometry contacts. Figure 5 shows a block diagram of the epitaxial system in use at Laser Diode Laboratories. This system incorporates several features which have resulted in the optimization of the liquid phase process:

Isothermal Heat Pipe Furnace - The sodium filled isothermal liner eliminates all vertical and horizontal temperature gradients and, hence provides uniform deposition rates over the entire surface of the substrate. The isothermal liner also allows the use of larger epitaxial boats, therefore, larger epitaxial



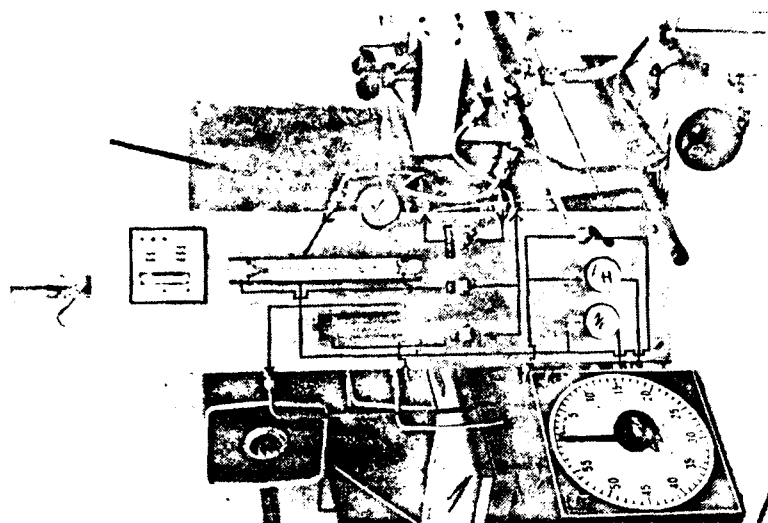
Block Diagram of Liquid Phase Epitaxial Systems  
Currently in Use at Laser Diode Laboratories.



wafers can be synthesized or more complex structures grown. Vac Sorb Pump - The use of a molecular sieve prior to the start of the run completely removes all traces of oxygen from the growth ambient without the risk of organic contamination.

Oxygen Monitor - The use of a fuel cell apparatus in the output stream of the system allows continuous monitoring of the O<sub>2</sub> content of the system both prior to and during epitaxial synthesis. The apparatus assures system integrity resulting in reproducible growth rates, alloy composition, and defect free growth by preventing the formation of Al<sub>2</sub>O<sub>3</sub> in the melt.

During the first quarter of the MMTE program, several improvements were made in the design of the epitaxial reactor. Notable among these improvements were the design and construction of new end cap apparatus shown in the photograph of Figure 6a. The new design can support higher vacuum, and operates with lower background O<sub>2</sub> levels than could be obtained previously. The optimized design now permits evacuation of the growth tube down to 80 microns and a steady state O<sub>2</sub> concentration of 0.1 ppm in the H<sub>2</sub> carrier gas. In addition, an improved gas supply sub-system has been designed for easier use by production personnel and is shown in the photograph of Figure 6b. A schematic indicating its operation is shown in Figure 7. In addition to obtaining optimum system performance through improved design concepts, the design and construction of



a.

b.

Figure 6 Photograph of Liquid Phase Epitaxial Reactors at Laser Diode Laboratories.

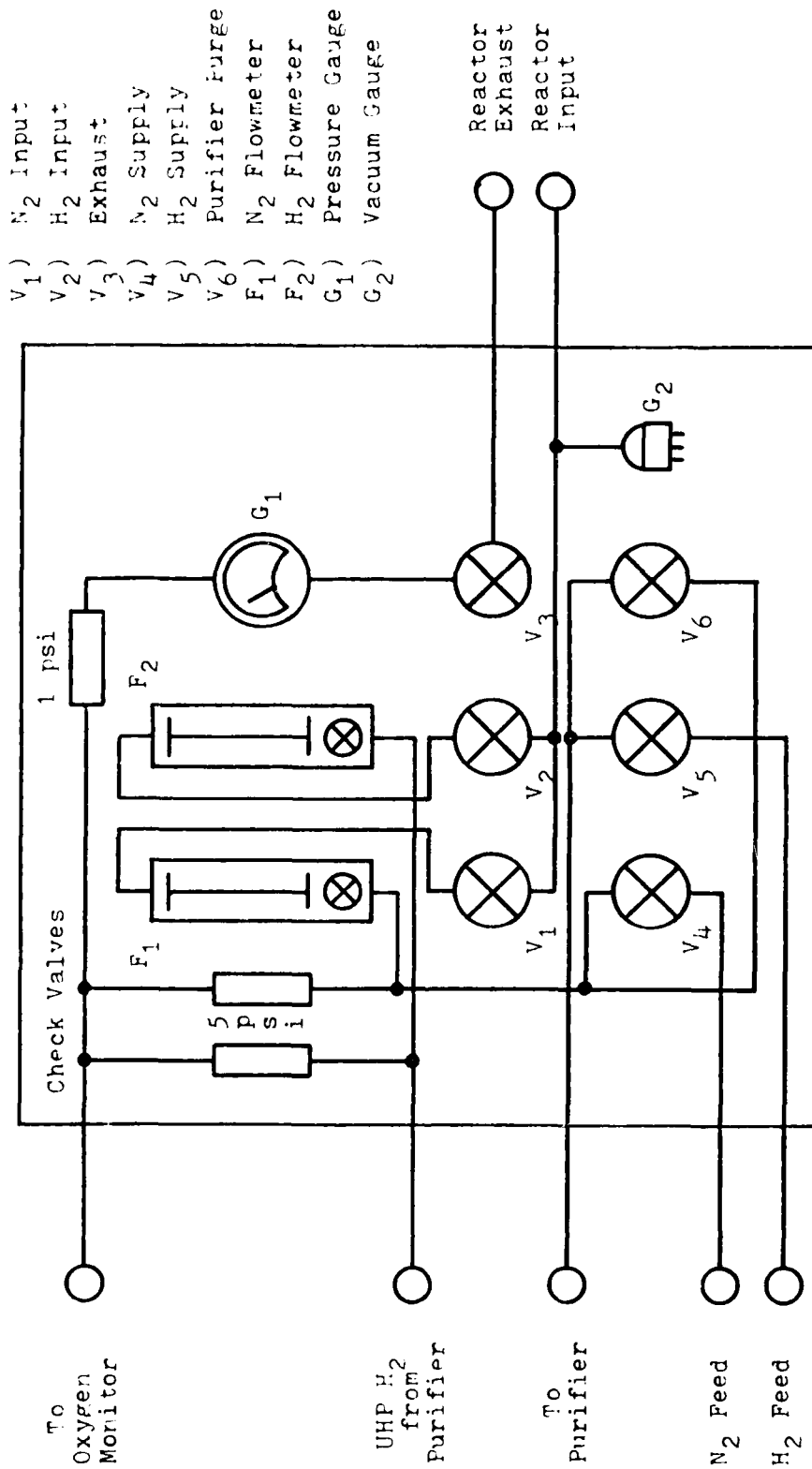


Figure 7 Schematic Diagram of Gas Control Subsystem

the epitaxial boat is crucial to obtaining high quality hetero-epitaxial material. The ultra high purity, high density graphite boat is shown in the photograph of Figure 8. The eight bin boat utilizes a built-in indexing mechanism for accurate positioning of the substrate in each bin. Also an extra bin is employed to remove excess gallium which may adhere to the surface of the wafer as it is removed from the final melt.

Together, the modified epitaxial reactor and epitaxial boat allow the generation of double heterojunction structures in a manufacturing environment for the volume production of monolithic triple stripe geometry injection lasers.

#### 3.1.1.2 Growth Process for the Synthesis of the Double Hetero-junction Structure.

Epitaxial synthesis of the double heterojunction structure is accomplished according to the sequence of events outlined in the flow chart of Figure 9. Table 2 lists the melt compositions for the growth of the double heterojunction structure used in the fabrication of the monolithic triple stripe geometry laser diode. After the appropriate melt ingredients, gallium (Ga) charges, and polycrystalline source wafers, have been loaded into consecutive growth bins, the single crystal (100) GaAs substrate is placed into the slider well of the high purity graphite boat (refer to Figure 8 ). A graphite cover plate is employed to eliminate surface

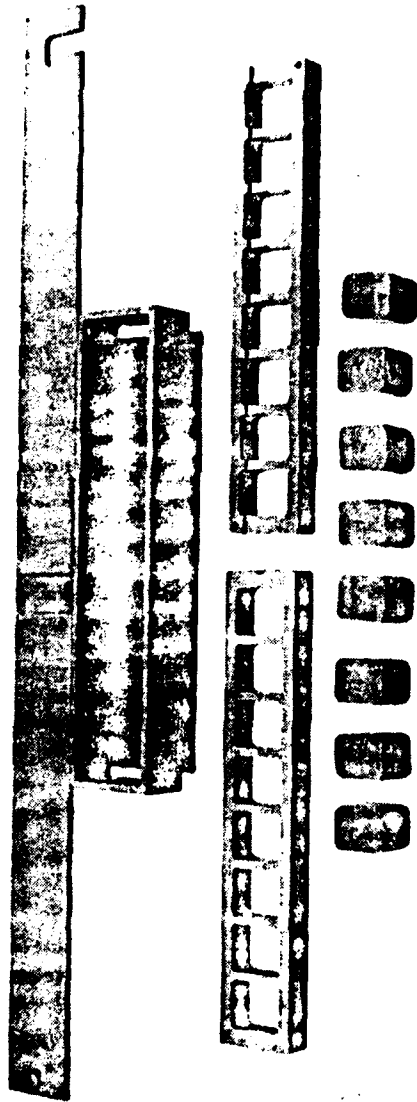


Figure 8 Photograph of Eight Bin Ultra High Purity Graphite Epitaxial Boat.

Figure 9 Sequence of Operations for Liquid Phase Epitaxial Synthesis.

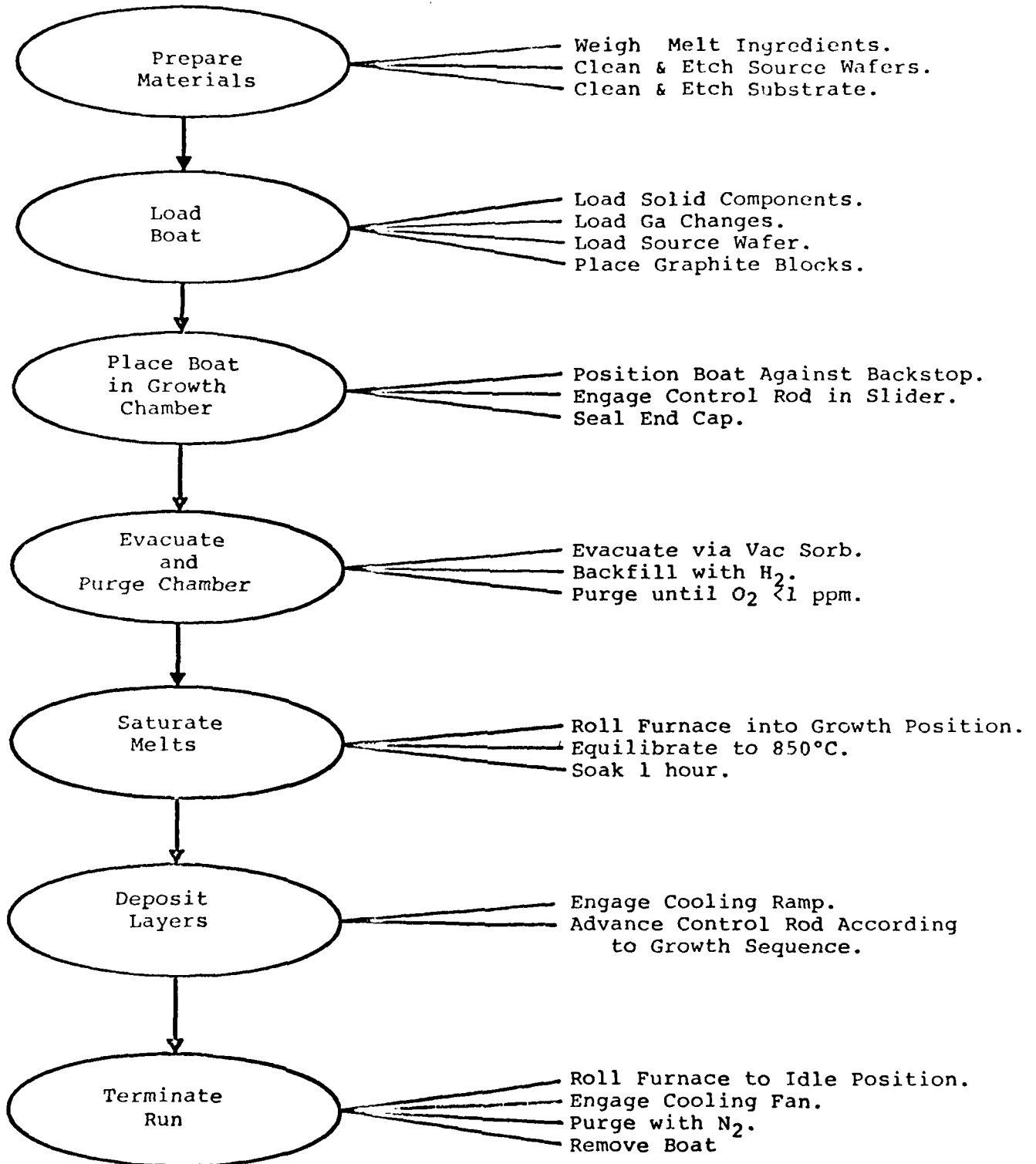


Table 2

Melt Compositions for Double Heterojunction Epitaxial Synthesis.

<u>Layer</u>	<u>*GaAs</u>	<u>Ga</u>	<u>Al</u>	<u>Te</u>	<u>Si</u>	<u>Ge</u>
1	0.6K	5.0K	-	1.0	-	-
2	0.6K	5.0K	6.0	1.0	-	-
3	0.6K	5.0K	1.0	-	15.0	-
4	0.6K	5.0K	6.0	-	-	0.1K
5	0.6K	5.0K	0.2	-	-	0.5K
6	0.6K	5.0K	-	-	-	-

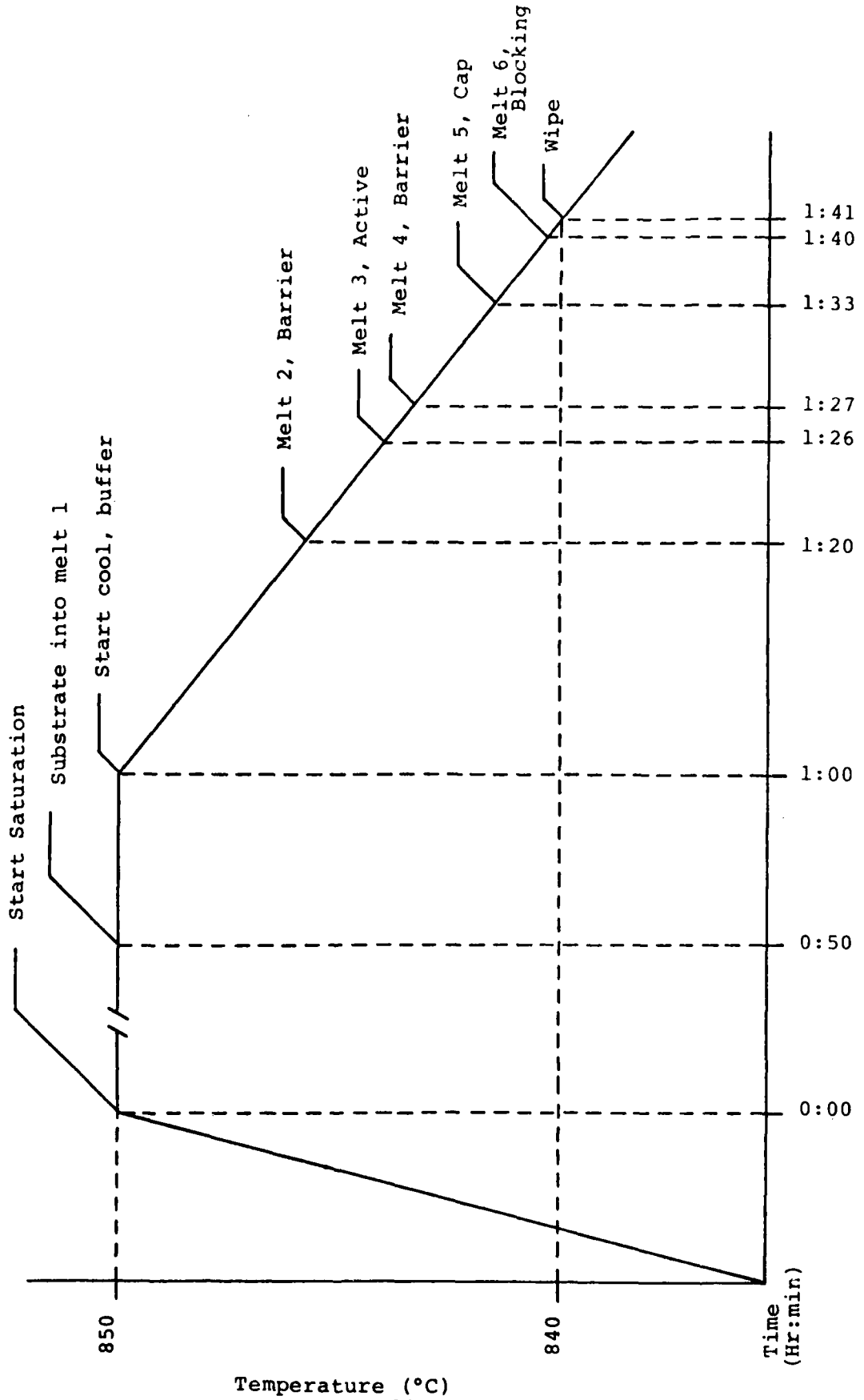
\* Polycrystalline source wafers.

\*\* Weights in mg.

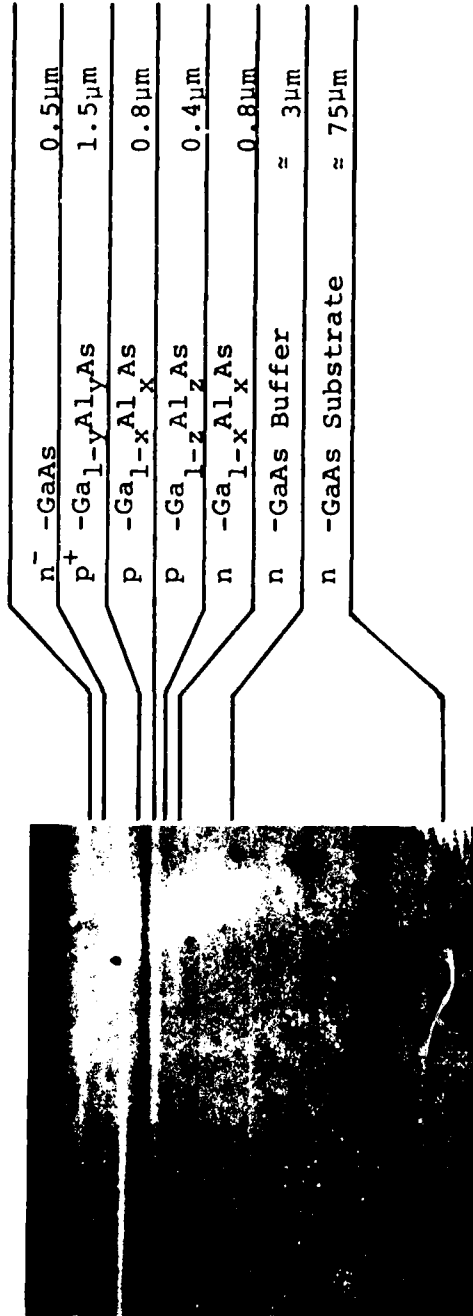
dissociation of the substrate during equilibration. The boat is then loaded into the quartz growth tube and the system is evacuated by means of the Vac-Sorb pump. Following a short H<sub>2</sub> purge, the system is brought up to the starting temperature of 850°C by rolling the isothermal liner into the growth position. Melt saturation is accomplished during a one hour soak at 850°C during which time enough GaAs is dissolved from the source wafers in order to exactly saturate each melt. This recently developed self-saturation scheme has simplified the growth procedure by eliminating the need for careful preweighing of GaAs for each melt. In addition, higher quality layers and increased run to run layer thickness reproducibility have been achieved with this technique. Once saturation has been achieved, epitaxial synthesis proceeds according to the time temperature program shown in Figure 10. Individual layers are epitaxially deposited by advancing the substrate through the consecutive growth bins for a precisely controlled time interval. Because growth rates for the various melts are well defined for a fixed starting temperature and cooling rate, layer thickness can be accurately and reproducibly controlled using this technique. A cleaved and etched cross section of a typical wafer synthesized for use in the fabrication of the monolithic triple geometry laser diodes is shown in Figure 11. In addition to the excellent dimensional and compositional uniformity of the layers, the surface



Temperature program used in the liquid phase epitaxial growth of double heterojunction structures for monolithic stripe geometry laser diodes.



Photograph of typical double heterojunction structure required for the manufacture of monolithic stripe geometry injection laser diodes.



morphology of the heteroepitaxial wafer is characterized by freedom from pit type defects and exhibits a high degree of flatness compatible with the photolithographic processing steps required for the application of stripe geometry to the wafer surface. Photomicrographs of the surface are shown in Figure 12.

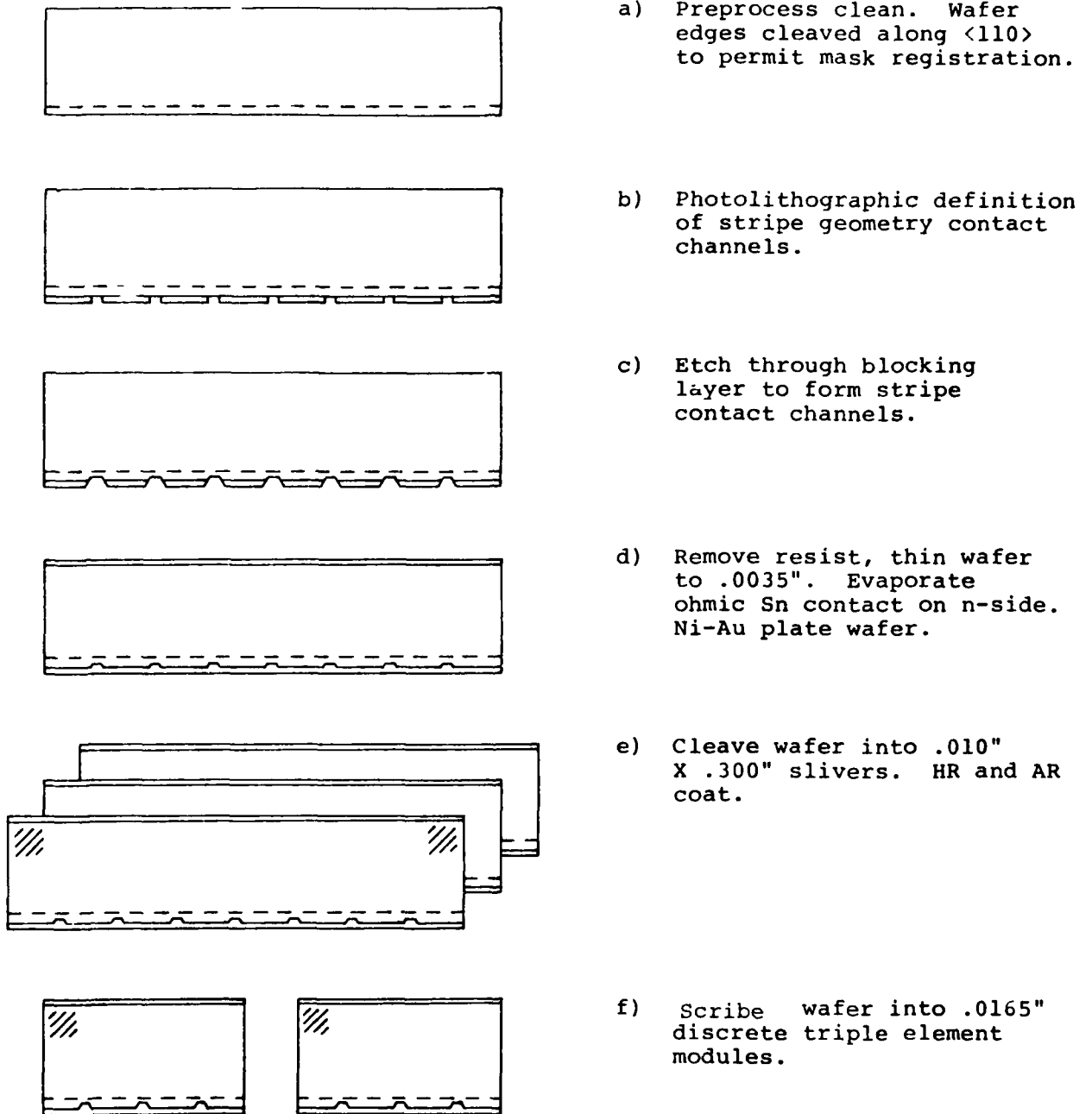
### 3.1.2 Wafer Processing for Monolithic Triple Stripe Geometry Module Fabrication.

Following liquid phase epitaxial synthesis, the wafer must be processed into individual triple stripe geometry modules. The processing steps required for the fabrication of the modules, are illustrated schematically in the process flow chart, Figure 13. After epitaxial synthesis of the multiheterojunction structure, the wafer undergoes a preprocess cleaning to remove residual Ga from the surface, Figure 13 (a). Approximately .050" of material is cleaved from all four edges creating mutually perpendicular  $\langle 110 \rangle$  reference planes to be used for channel stripe alignment. The proper  $\langle 110 \rangle$  alignment plane must be identified prior to epitaxial growth since a V-shaped channel cross section is desired. This is normally accomplished by defining channels on a sample substrate and observing the channels' cross section. Once identification of the  $\langle 1\bar{1}0 \rangle$  has been accomplished, the proper alignment plane is known for all substrates cut from a given ingot. Photolithographic definition of the stripe contact



Figure 12 Surface Morphology of the As-Grown Hetero-epitaxial Wafer.

Process flow diagram for the fabrication of monolithic stripe geometry injection laser arrays.



channels is accomplished by aligning the mask reference with the proper  $\langle 110 \rangle$  direction as indicated schematically in Figure 13 (b).

Photolithographic definition is followed by a 3:1:1, Methanol:Phosphoric: Hydrogen Peroxide etch which removes the n-GaAs blocking layer forming an array of etched 20  $\mu\text{m}$  wide contact channels in the p-GaAlAs contact cap. Parallel contact channels are spaced on .005" centers over the entire surface of the epitaxial wafer as shown in Figure 13 (c).

After removal of the masking resist, the epitaxial wafer is thinned to .0035" and Sn ohmic contacts are evaporated over the n-side of the thinned wafer, Figure 13 (d).

Ni-Au electroplated contacts are applied to both sides of the wafer forming ohmic contact to the exposed p-GaAlAs contact cap in the stripe channels.

Mirror facets are formed by cleaving the epitaxial wafer in the slivers approximately .010" by .300" as indicated schematically in Figure 13 (e).

Cleaving is accomplished with the aid of a diamond scribing apparatus shown in the photograph of Figure 14. The cavity length is accurately and reproducibly controlled by the micro-index control on the vacuum chuck of the scriber.

Reflective coating of the back facet of each sliver is accomplished by vacuum deposition of successive films of  $\text{SiO}$  (2000 $\text{\AA}$ ), Cr (50 $\text{\AA}$ ), Au (4000 $\text{\AA}$ ), Cr (100 $\text{\AA}$ ), and

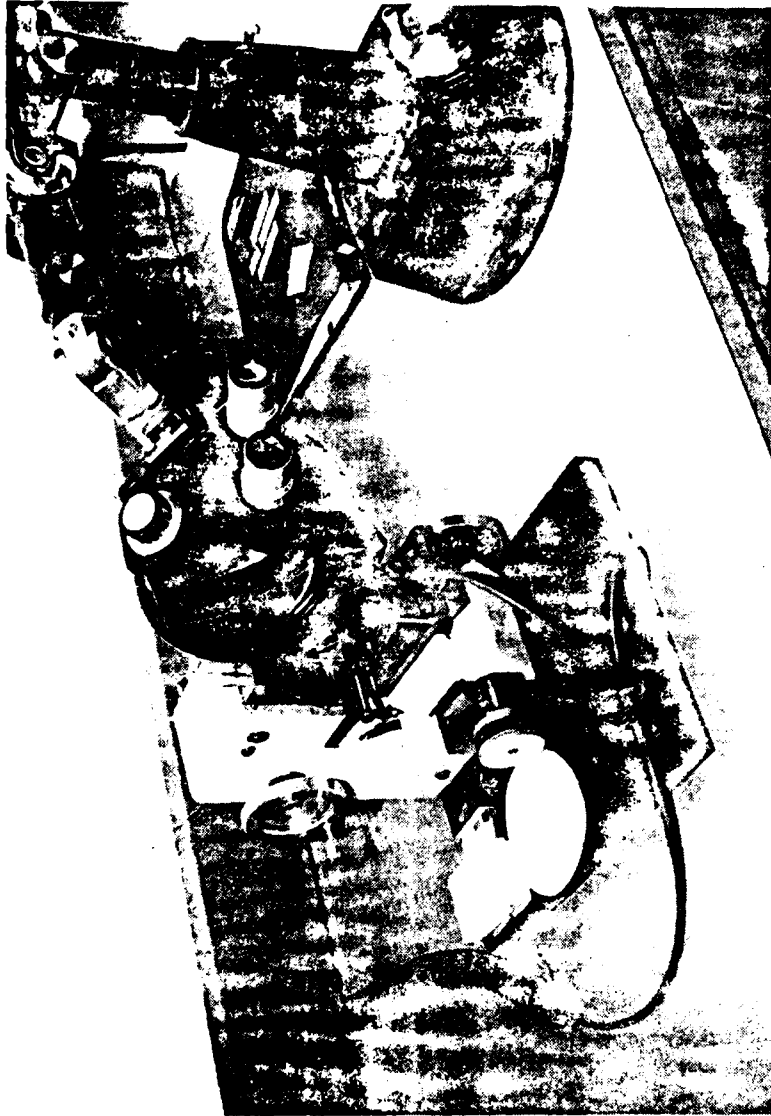


Figure 14 Scribing Apparatus for Cleaving Epitaxial Wafer into Slivers.

SiO (300Å).

Finally, in Figure 13 (f), the individual slivers are cut on .025" centers with a ganged wire saw having a .0035" kerf.

Figure 15 shows an epitaxial wafer to which triple stripe geometry contacts have been applied. Figure 16 shows individual modules after they have been cleaved, coated, and cut to size ready for assembly onto the pill package.

### 3.2 Packaging Technology.

#### 3.2.1 Package Design.

During the first quarter of the program, finalization of the package design and procurement of pill package blanks for fabrication of the first engineering samples was carried out. The pill package blank consists of a brass negative electrode, an Al<sub>2</sub>O<sub>3</sub> ceramic spacer, and an OFHC copper positive electrode which serves as the primary heat sink for the monolithic triple stripe geometry injection laser diode module. These three major components are bonded together through the use of a high temperature alloying technique and are purchased from the supplier as a complete assembly. Engineering drawings for the piece parts are given in Figures 17, 18, and 19. In addition to the package blank, the optical window along with its epoxy preform for attachment make up the remainder of the package parts. Parts drawings for these two components



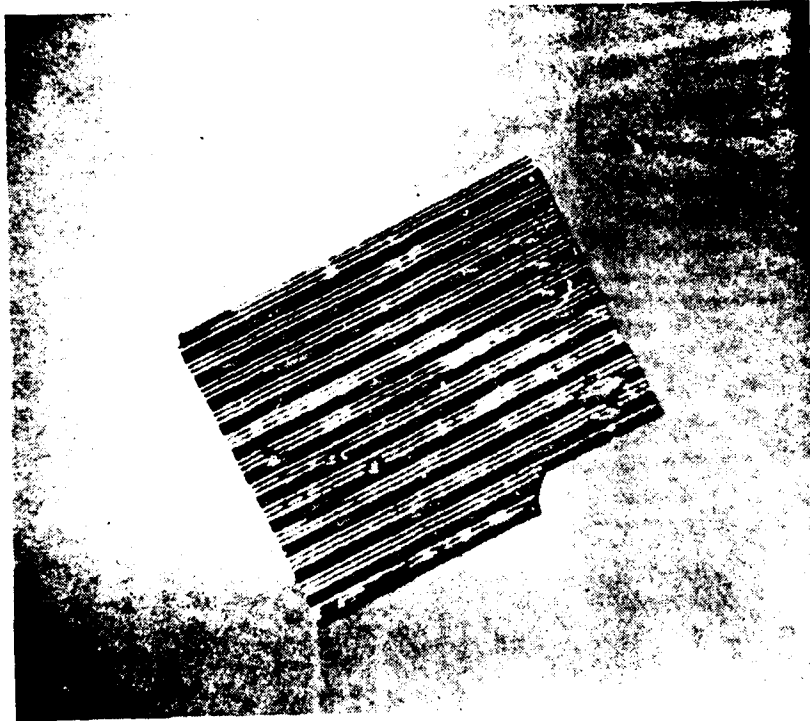
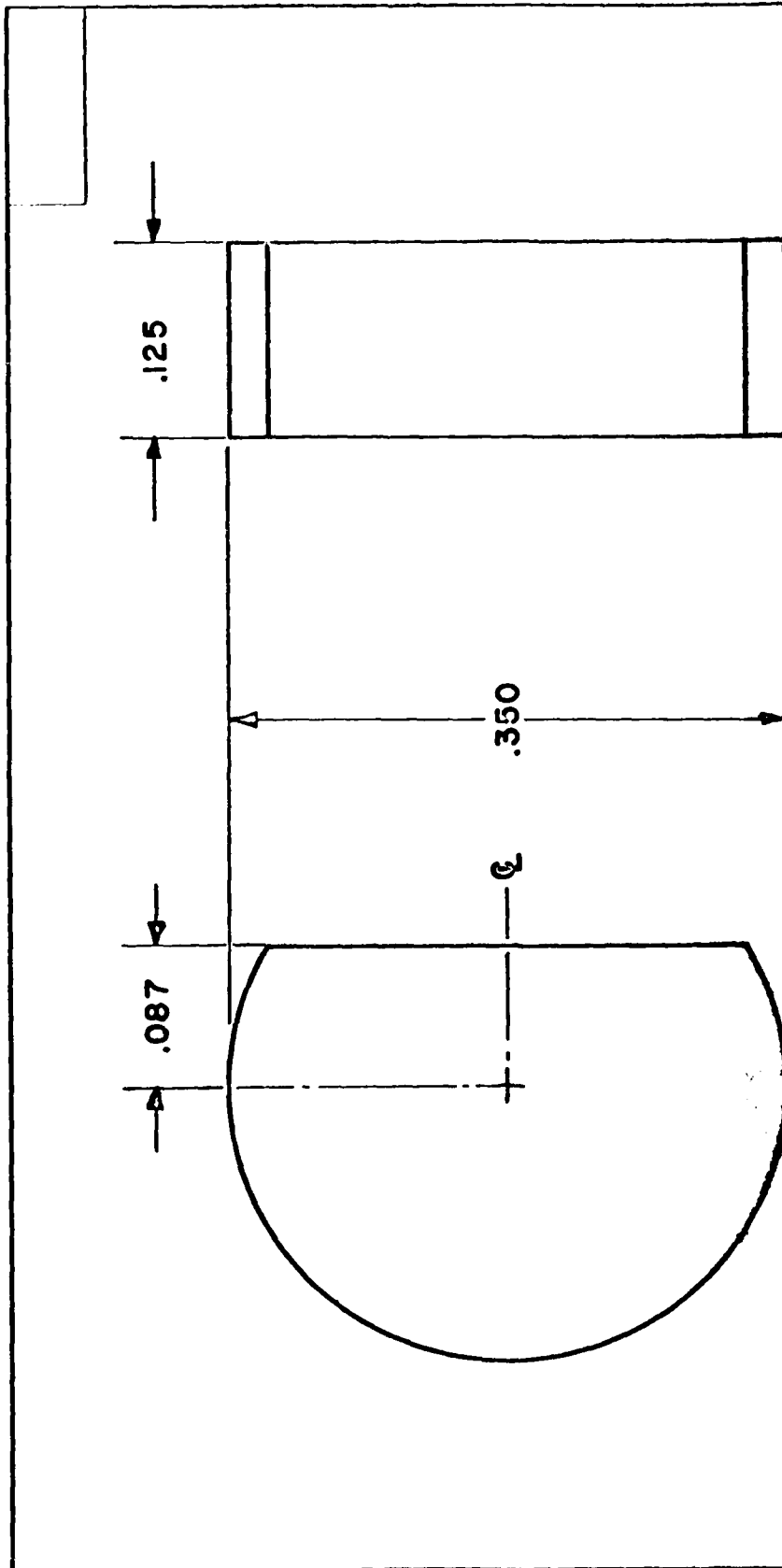


Figure 15 Photograph of Triple Stripe Geometry  
Applied to Surface of an Epitaxial Wafer.



Figure 16 Photograph of Individual Triple  
Element Modules.

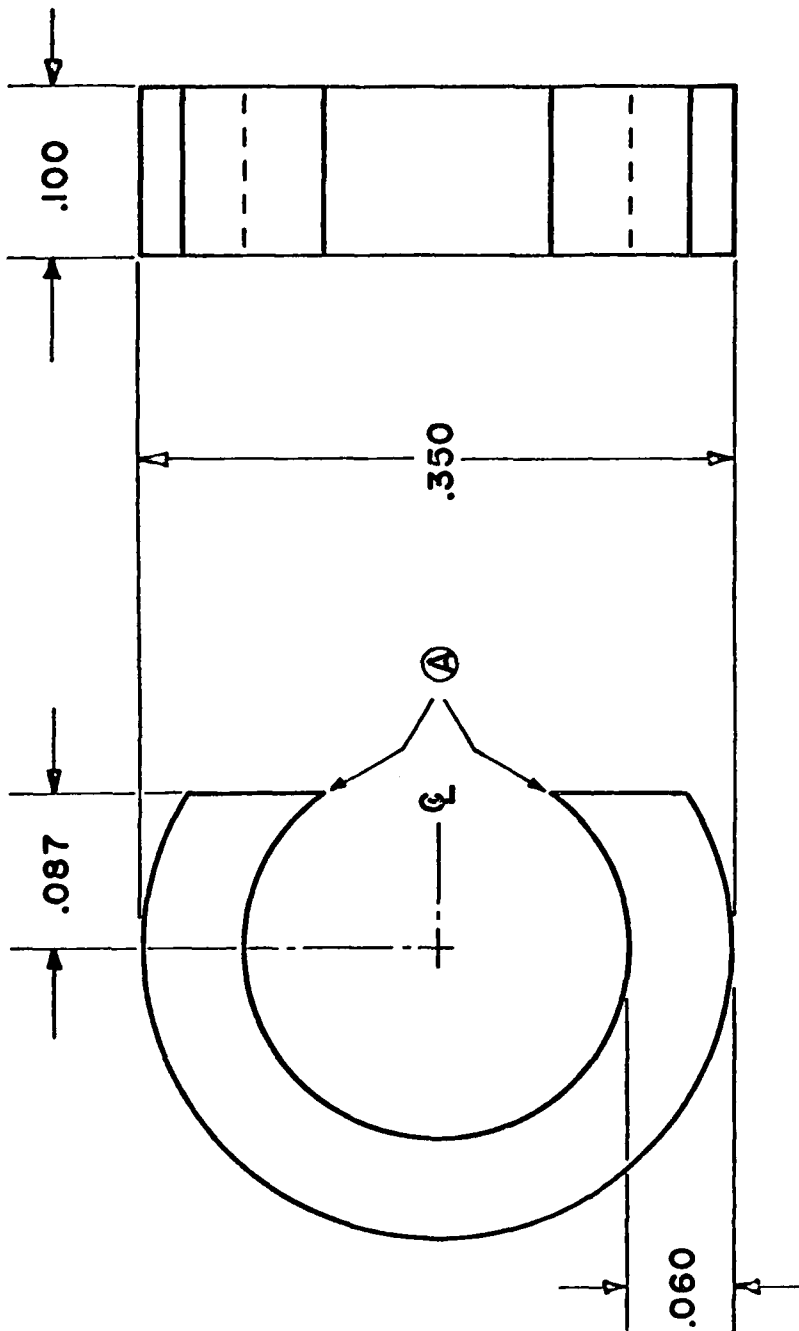


**MATERIAL - OFHC COPPER**  
**TOLERANCE: ±.002**

Figure 17 Pill Package - Mounting Base  
 (Positive Electrode)

<b>PILL PACKAGE</b>		<b>BOTTOM ELECTRODE</b>	
SCALE: <b>10X</b>	APPROVED BY	DRAWN BY	
DATE: <b>8-4-76</b>		<b>M.R.</b>	
<b>LDT-180A</b>		DRAWING NUMBER	

REVISION NO. 1004 APPROVED MASTER FORM



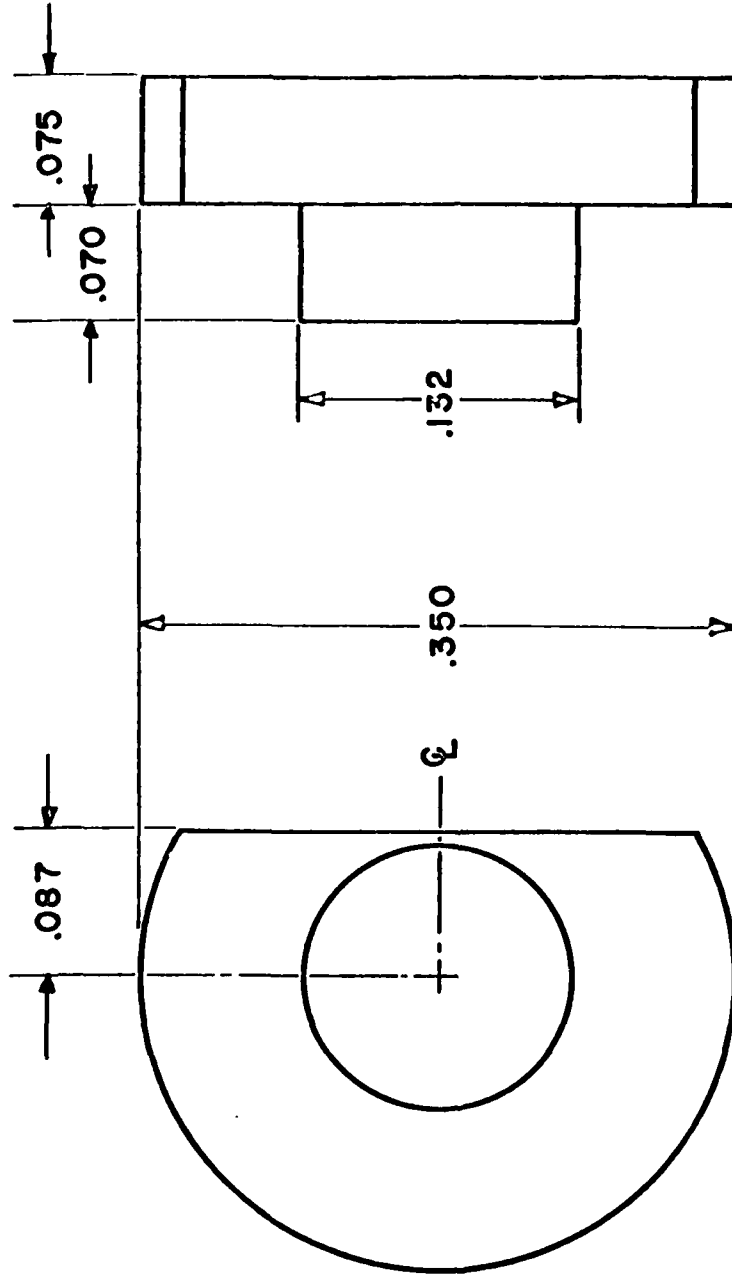
**MATERIAL - HI DENSITY ALUMINA**  
**TOLERANCE: ±.001**  
**.015 CHIP ALLOWED ALONG EDGE**  
**AT POINTS A**

**PILL PACKAGE SPACER**

SCALE: 10X	APPROVED BY	DRAWN BY
DATE: 8-4-76		M.R.
LDT-100C		DRAWING NUMBER

Figure 18 Pill Package - Spacer  
 (Ceramic Insulator)

DETACH NO. 10007 ASSEPROOF MASTER FORK



**MATERIAL - BRASS**  
**TOLERANCE: ±.002**

**PILL PACKAGE TOP ELECTRODE**

SCALE: <b>10X</b>	APPROVED BY	DRAWN BY
DATE: <b>9-17-76</b>		<b>m.R.</b>
<b>LDT-180</b>		
		DRAWING NUMBER

Figure 19 Pill Package - Cover Plate  
 (Negative Electrode)

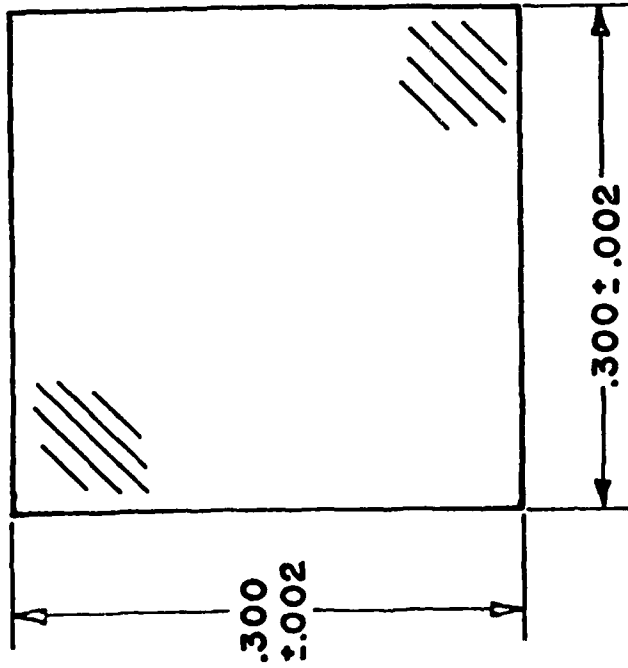
are shown in Figures 20 and 21 and photographs of the window and preform are shown in Figure 22 (a) and (b). The epoxy utilized in this assembly is Ablestik type 539 and is supplied as a stamped preform. Type 539 consists of a non-frozen epoxy applied to both sides of a thin mylar film carrier. Preforms of this type are available in 0.0005" increments up to 0.003" thick. The epoxy is tack free prior to curing and can be stored at 25°C for an indefinite period of time. Curing is accomplished by heating to 110°C for two hours and results in an extremely uniform bond line with a shear strength of 3000 psi. Because extremely thin films of epoxy are applied to the mylar carrier, deformation of the preform during cure is minimized. This feature together with the inherent uniformity of the mylar film carrier makes this an ideal material for the attachment of the optical window to the laser diode pill package. In a parallel effort, the use of a similar mylar preform as an electrical insulator to be employed in place of the ceramic was actively being investigated. Several advantages to using epoxy preforms for this application have become evident to date. In order to obtain a perfectly flat mounting surface for the 0.004" thick optical window, the front face of the pill package blank must be lapped prior to use. The presence of the ceramic insulator introduces some degree of difficulty in this step owing to the difference in hardness between

**NOTES:**

**1. MATERIAL - QUARTZ - CLEAR,  
FUZED**

**SAPPHIRE**

**2. COATING - AR COATED  
FOR 820nm  
BOTH SIDES.**

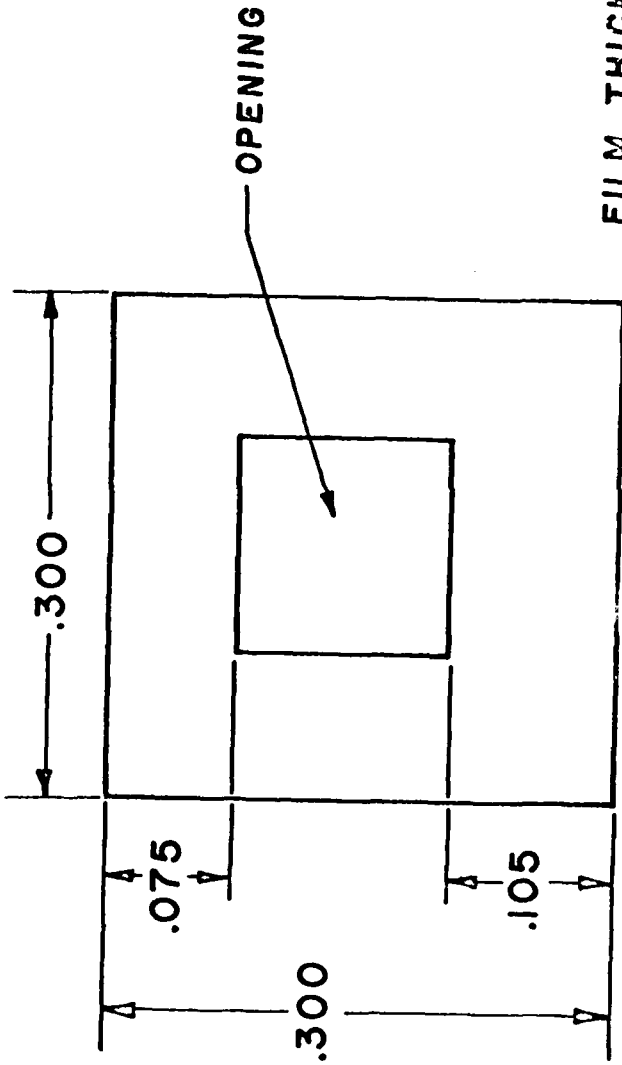


**THICKNESS -  $.004 \pm .0005$**

Figure 20 Pill Package -  
Optical Window

**WINDOW - PILL PACKAGE**

SCALE: <b>10X</b>	APPROVED BY	DRAWN BY
DATE: <b>9-16-76</b>		<b>M.R.</b>
<b>LDT-179</b>		DRAWING NUMBER



FILM THICKNESS  
.0015

MATERIAL - ABLESTIK  
ABLEFILM 539-TYPE I

Figure 21 Pill Package - Epoxy Preform

PILL PACKAGE - EPOXY PREFORM

SCALE: 10X	APPROVED BY	DRAWN BY
DATE: 9-1-76		M.R.
LDT-179		DRAWING NUMBER

DIETZEN NO 1887 ASEPROOF MASTER FORM



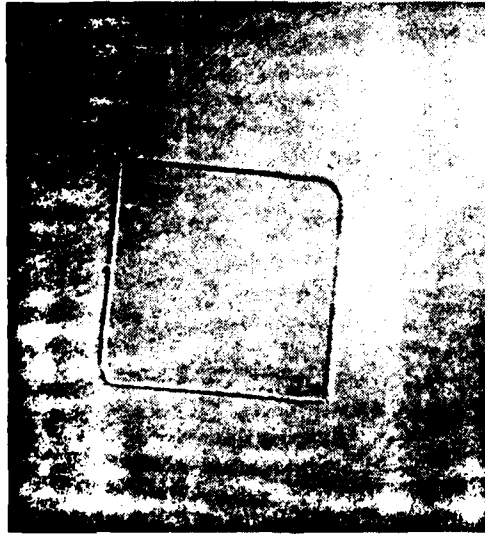
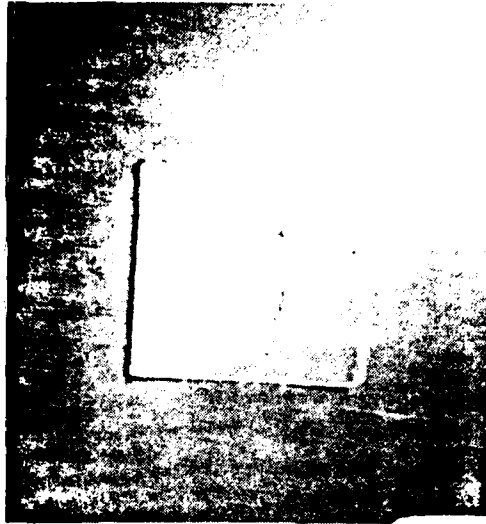
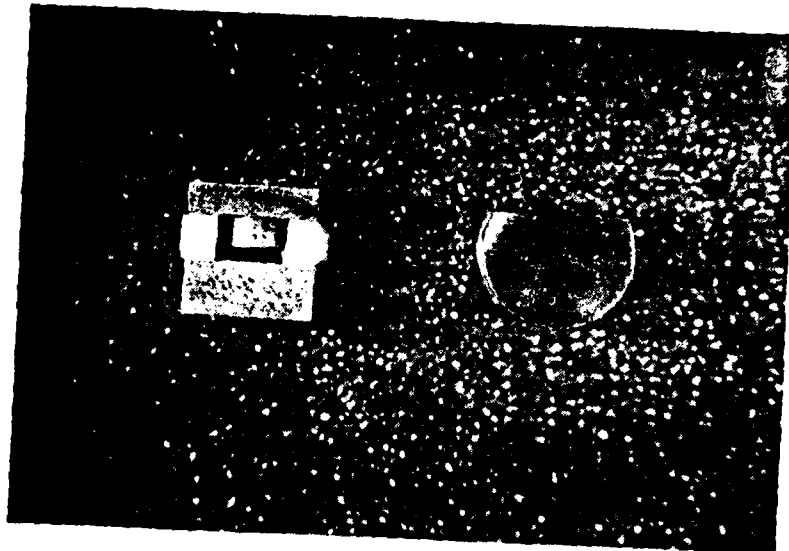


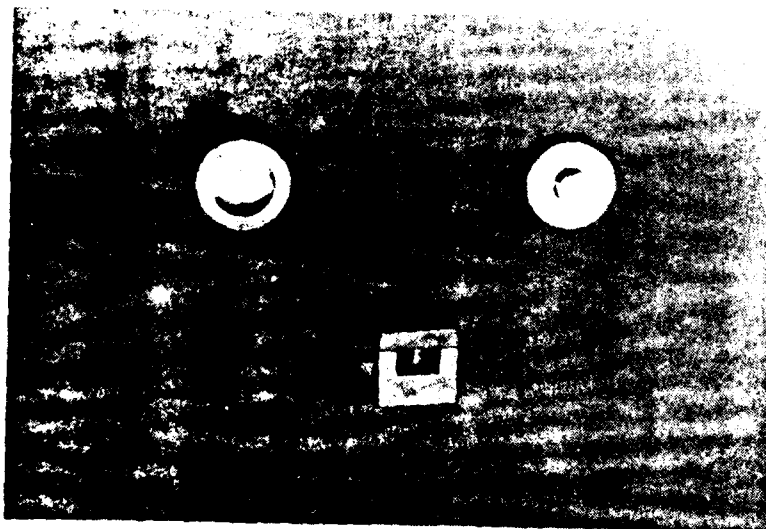
Figure 22 Photograph of Optical Window and Epoxy Preform.

$Al_2O_3$  and copper. Although perfectly flat mounting faces can be obtained, the lapping must be done carefully to prevent rounding. When the blank is designed for use with an epoxy-mylar insulator, the lapping accomplished with much less difficulty and with a minimum of material removal. In addition, the copper-mylar blank is about one third as costly as its copper ceramic counterpart. Photographs of both types of pill package blanks are shown in Figure 23 (a) and (b).

Experiments have been performed and indicate that packages assembled from all metal parts, with the epoxy preform, can be machined and lapped to provide a smooth surface for window attachment. With this smooth surface, it has been possible to attach the window with a low viscosity UV curing epoxy which allows for a thin epoxy layer on the order of a half mil thickness. This method is preferred to the preform method of window attachment as it provides effective sealing of the window without pressure and temperature, and a cure time of only 15 seconds.



a. Cu-Ceramic Blank. (2.5x)



b. Cu-Mylar Blank. (1.5x)

Figure 23 Pill Package Blanks

### 3.2.2

#### ASSEMBLY TECHNIQUES

A blow-up of the basic laser diode pill package is illustrated in Figure 24. The parts are assembled by aligning the upper and lower copper parts with the preform in between, applying moderate pressure to the parts while curing at 110° C for 2 hours. In practice a number of units are assembled and placed in a "vee" shaped fixture which serves to keep the parts aligned while pressure is applied. The fixture is shown in Figure 25. After curing of the epoxy preform, the package is machined to provide the flat window surface as shown in Figure 26. To complete the surface finish for window attachment the machined packages are placed in a rubber pad, such that the flat surface can be placed in contact with a lapping plate. The rubber pad is shown in Figure 27 and the lapping machine in Figure 28. When the texture of the flat window surface change to a mat finish, the lapping is complete. The pill package blanks are individually inspected and then electroless nickel and gold plated. Next a 2 mil gold fly wire is soldered to the upper electrode center post with 60/40 pb/Sn solder. The mounting area on the bottom electrode is tinned with Indium, the diode chip placed just back of the edge and

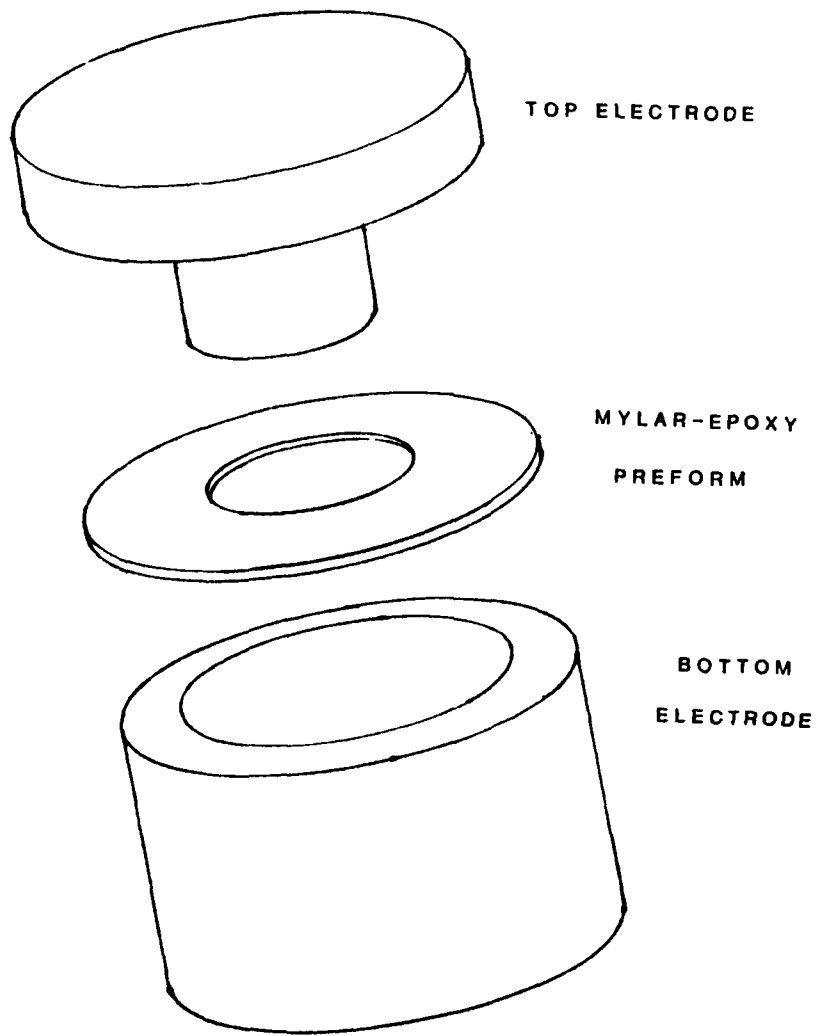


Figure 24 - PILL PACKAGE COMPONENTS



Figure 25- Bonding Fixture with Packages  
Clamped for Bonding.

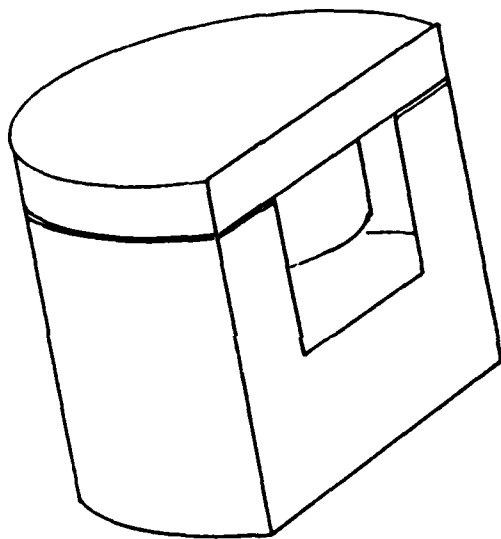


Figure 26.

PILL PACKAGE ASSEMBLED AND MILLED

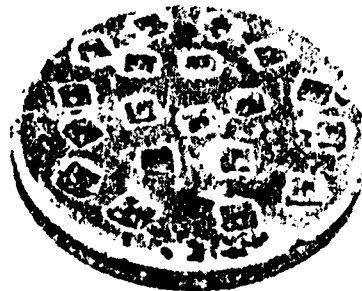


Figure 27.  
Rubber Lapping Pad.



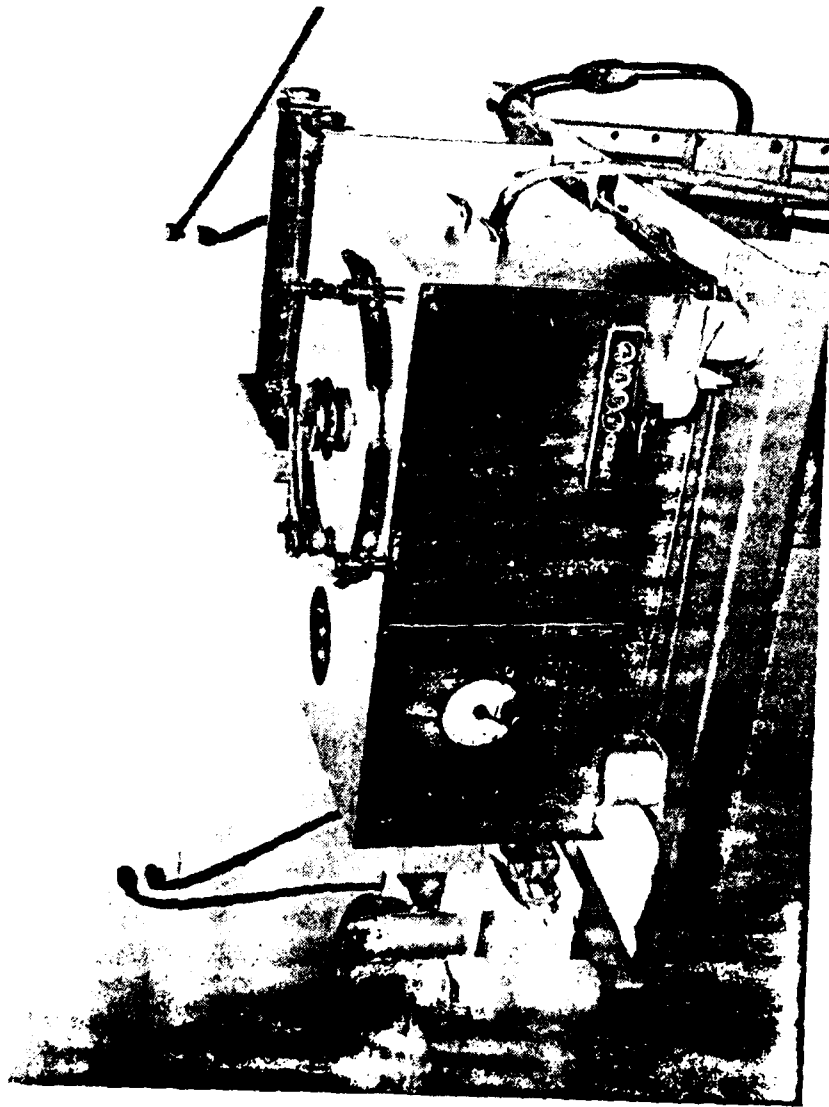


Figure 28 - Photograph of Lapping Apparatus used to Obtain Flat Window Mating Face.

soldered in place. An Indium preform is placed on top of the chip and the free end of the wire of the top electrode shaped to press into the preform. The assembly is reheated to the Indium melting point allowing the preform to melt and make connection to the top of the chip. The P-side of the chip is soldered to the bottom electrode. All the above soldering is performed on a carbon strip type heater. The packaged laser can be tested and burned in at this point in the assembly. After testing, the window is attached to the package by placing a thin bead of UV epoxy near the outer edge of the flat surface, placing the window on the bead and applying light pressure to the window to cause the epoxy to spread over the flat mounting surface. The epoxy can be observed to spread through the window and can be controlled so as not to flow onto the laser face. After a 2 second cure under a UV lamp, excess epoxy that has flowed around the outside of the package is removed with a solvent. A final cure of 15 seconds secures and seals the window. The window attachment sequence is carried out in a nitrogen dry box to minimize moisture content within the sealed package. The flow chart in Figure 29 shows the sequential steps in the package assembly and diode mounting. The final package configuration is shown in Figure 30 .

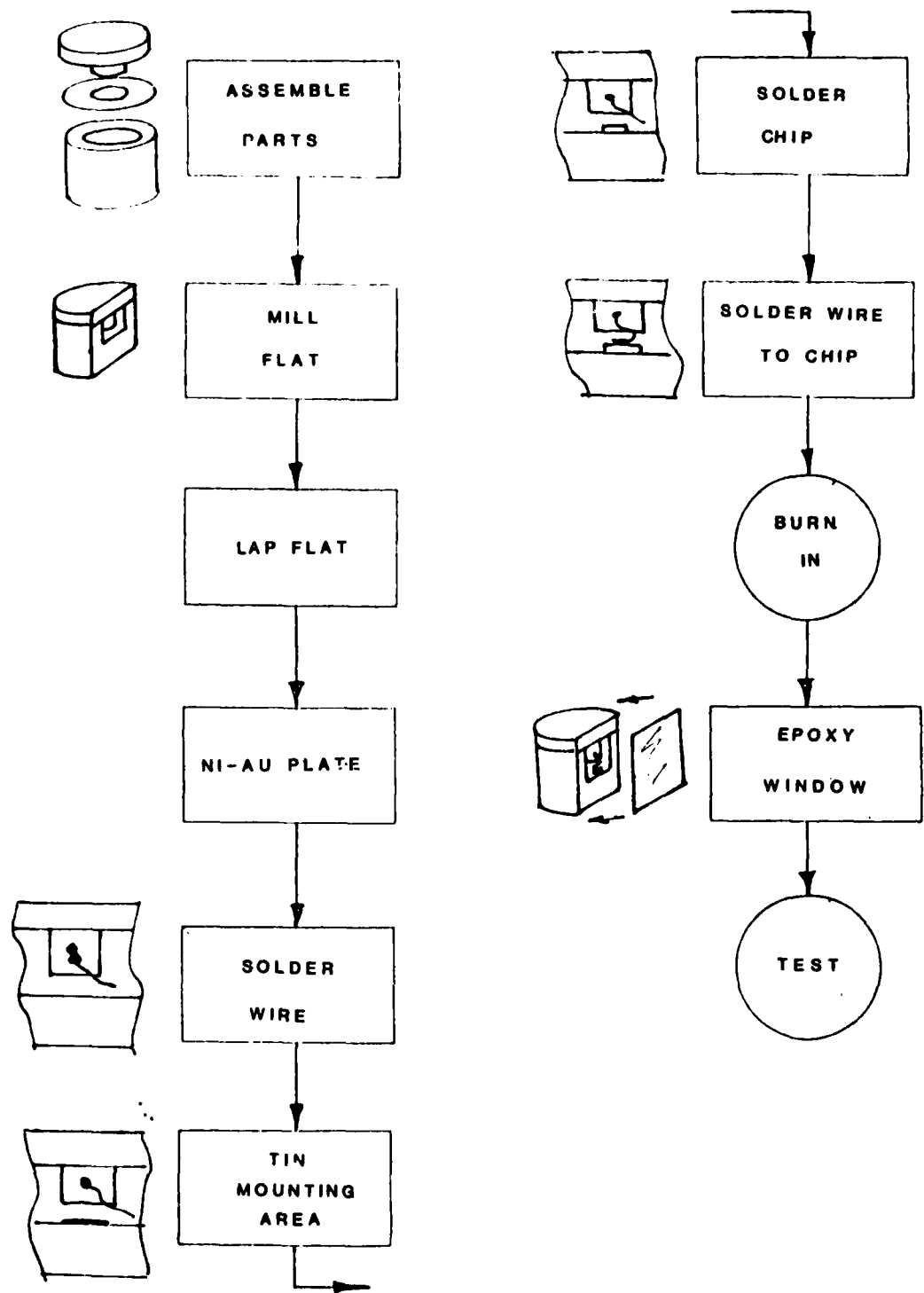
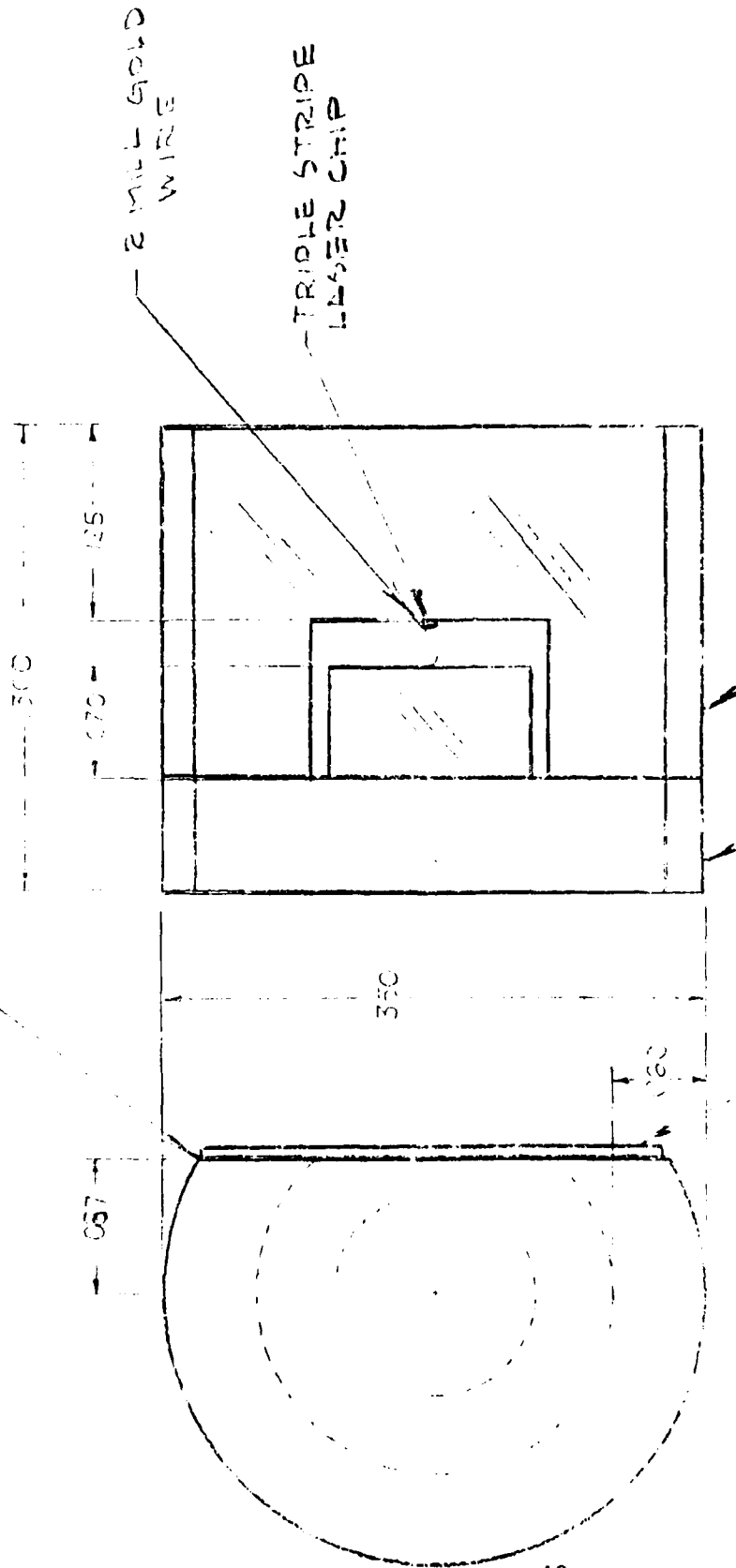


Figure 29 -

PILL PACKAGE-LASER ASSEMBLY FLOW CHART

NORCLAD AND GIUV EPOXY



MOUNTING ELECTRODE

MOUNTING ELECTRODE

Figure 30 - Completed Package Configuration

### 3.3 DEVICE EVALUATION AND TESTING

#### 3.3.1 TEST EQUIPMENT

A 10 MHz pulser capable of delivering drive currents up to 3.0 amperes at a duty factor of 10%, forms the basis for all the electro-optical measurements carried out on the devices. The circuit schematic is shown in Figure 31. The driver consists of two microwave transistors, CD1194 and CD1979, which are cascaded for high current gain. The pulser is triggered with a positive pulse or high logic level at the base of CD1194 through a decoupling capacitor. The diode FD600 is used for protection of the CD1194 from reverse  $V_{BE}$  voltages. The current through the laser is controlled by the 50 ohm potentiometer in the emitter circuit of CD1194. The coils in the supply buss are used for high frequency isolation and provide quick recharge speeds for the capacitor in the collector circuits. The pulser test set assembly is shown in Figure 32.

The Burn-In and Life Test Rack uses a different circuit which is shown schematically in Figure 33. The driver consists of two discrete components. A microwave transistor, CTC D3-28 ( $Q_2$ ), acts as a pre-driver for Siliconix VMOS FET 2N6657 ( $Q_3$ ), which is capable of switching

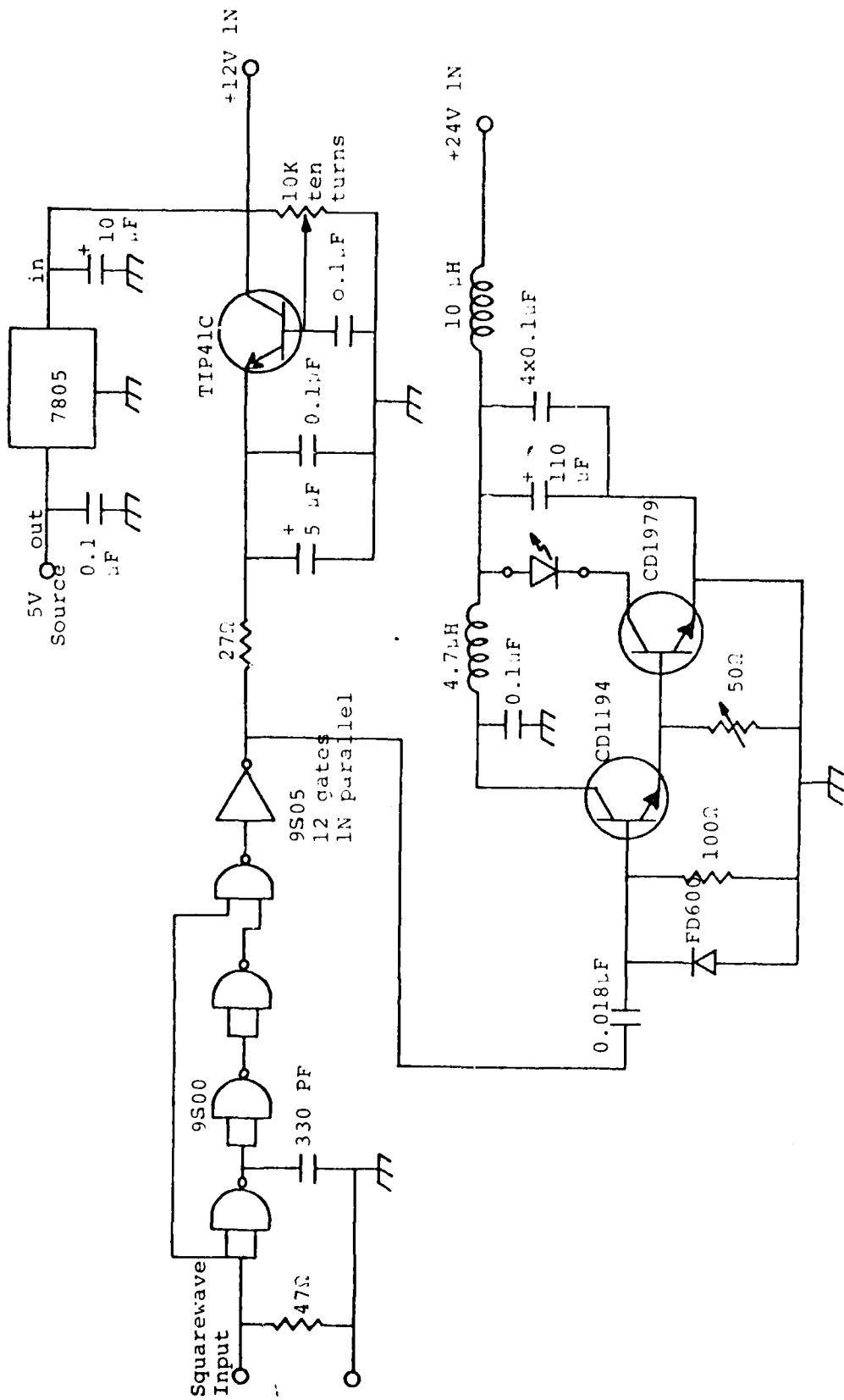


Figure 31. Transistor 10 ns Pulser.



Figure 32 -Transistor Test Pulser Assembly.

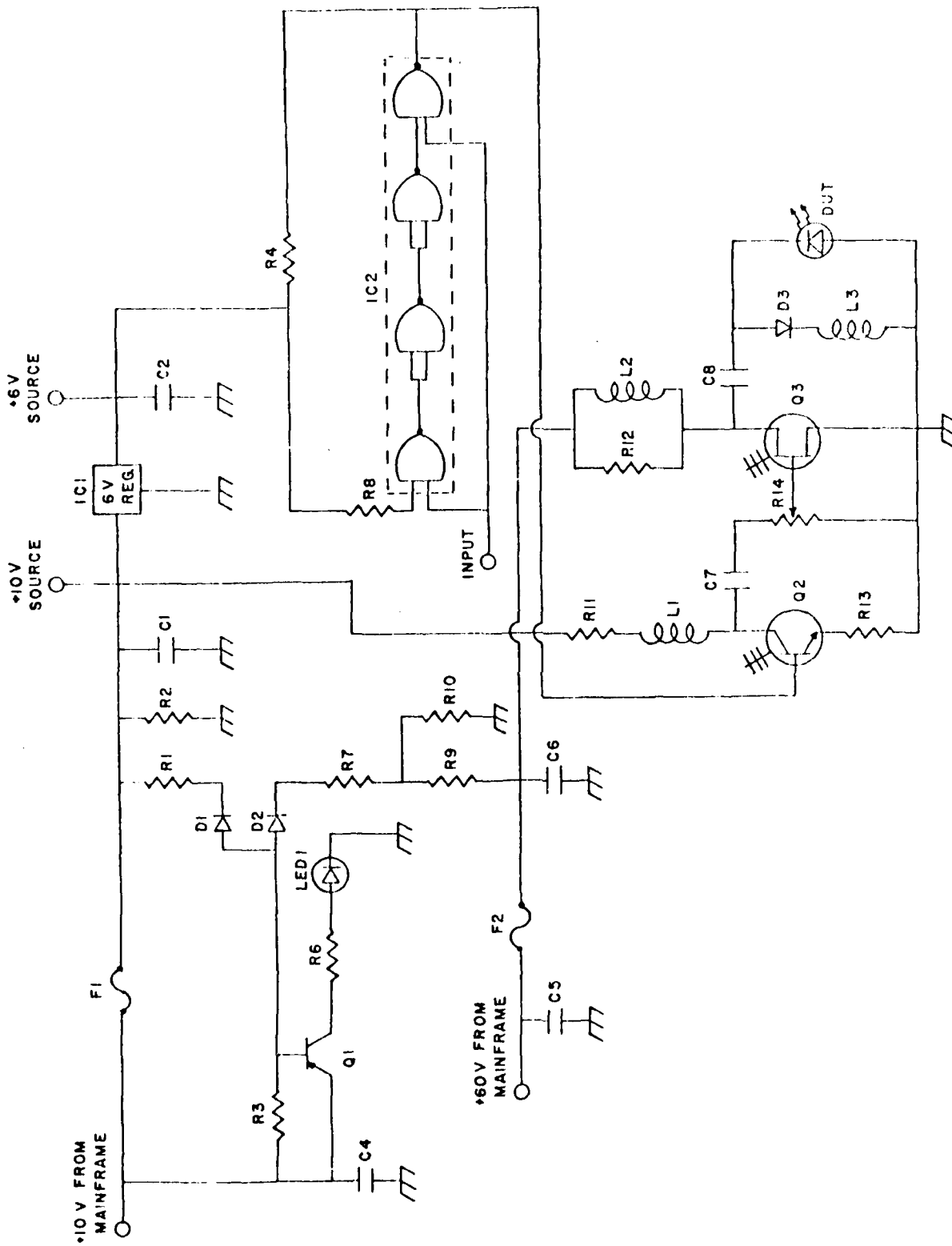


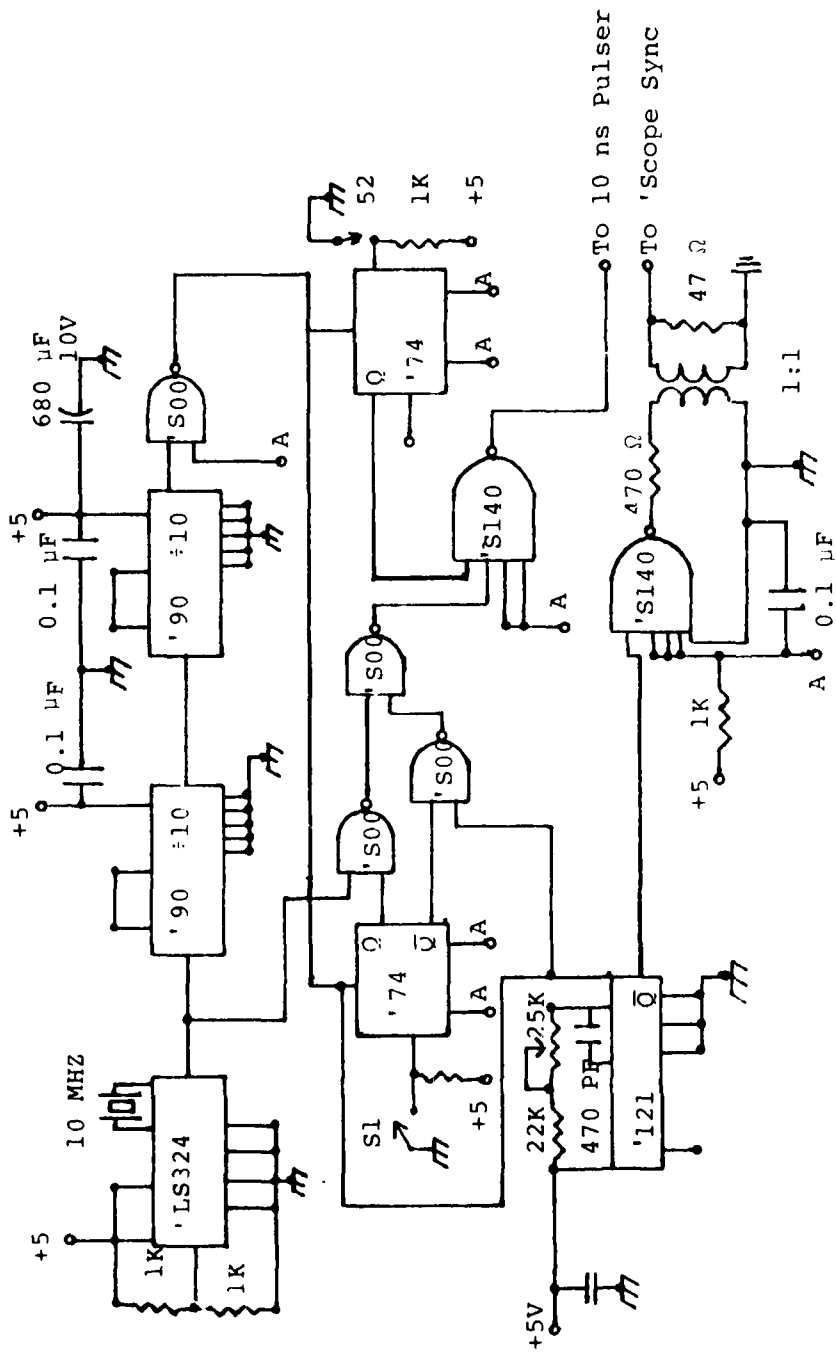
Figure 33 - Revised 10 MHz LED Driver (Single Position) Circuit Schematic.



in the nano-second range. The circuit is tuned for 10 ns pulse width operation. The input pulse must also have a 10 ns trigger pulse width with a 90% recharge time.

The pulse sequence is started when a high TTL logic level is present at the base of  $Q_2$  turning it "ON". The gate of  $Q_3$  is capacitively switched "OFF" by C7 through R14. The coil L1 begins storing energy from the Collector Current of  $Q_2$ . In the drain circuit of  $Q_3$ , the coil L2 and capacitor C8 is charging through the 60V supply, diode D8 and Coil L3. The DUT is back biased at this point. After 90% of the cycle, the input logic level goes low and  $Q_2$  turns "OFF". The coil L1 quickly pumps current through C7 which previously was discharged and depending on the setting of R14, turns  $Q_3$  "ON". The drain current comes from the DUT through C8 which was charged. The current through L3 is checked by D3. The discharge time of C8 will control the pulse width through the DUT. The sequence begins again when the TTL input goes high.

Figure 34 shows the schematic circuit for the 10 ns clock. Figure 35 is the circuit for a clock buffer for the multi-position rack. A single position board is shown in Figure 36.



Notes:

- 1. All Caps 0.1 F Unless Otherwise Noted.
- 2. All Logic 7400 Series TTL.

Figure 34 Clock and Control Circuit for Transistor Pulser.

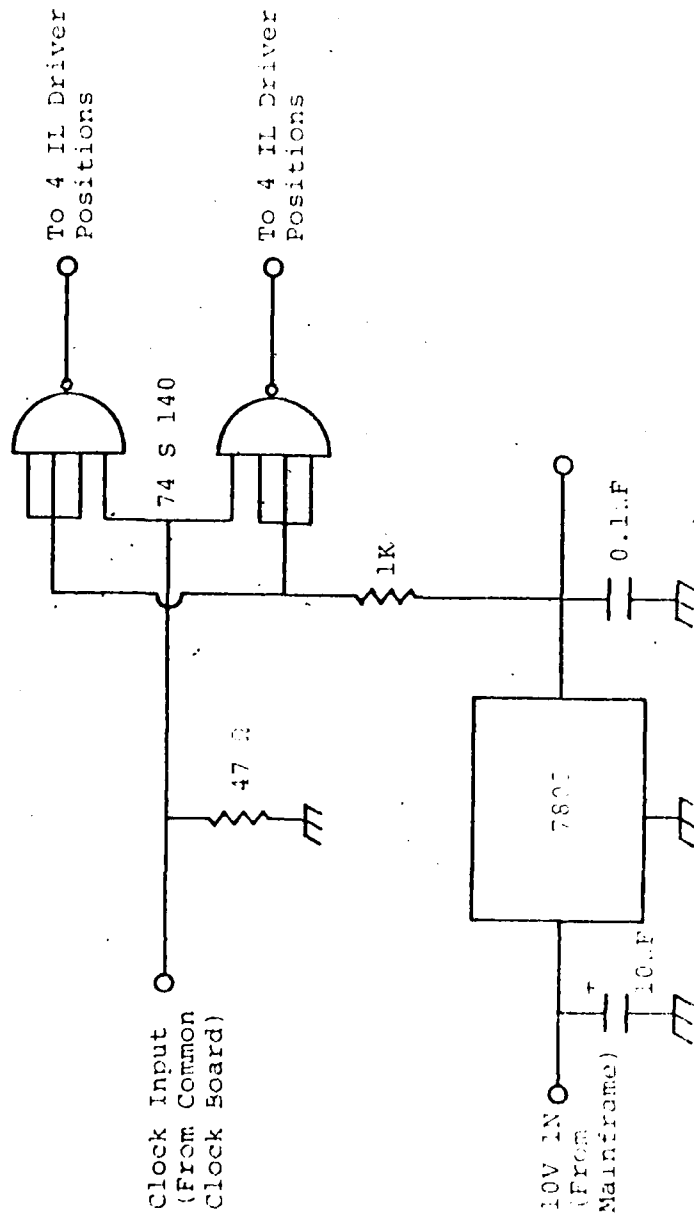


Figure 35, Local Clock Buffer for Burr-in Rack.



Figure 36 - Burn-In Position Board with Edge Connector Fingers.

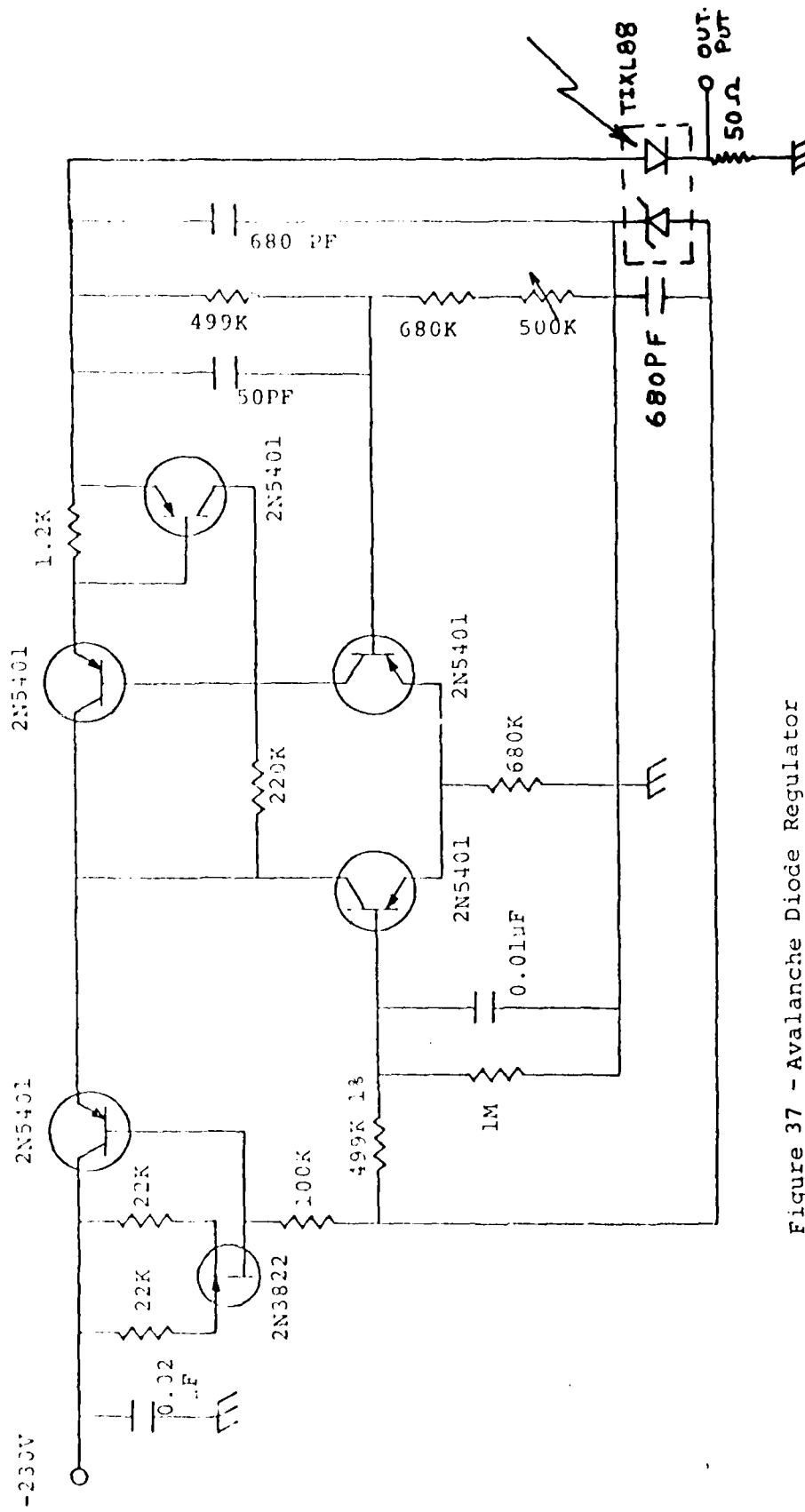


Figure 37 - Avalanche Diode Regulator

The detector circuit shown in Figure 37 is built around a TIXL88 Avalanche Photodiode/Reference Diode pair that have been manufactured to ensure close matching of both the breakdown voltages and temperature coefficients of the two diodes. The APD power Detector System is shown in Figure 38 indicating the essential features of the power supply and detector head. The internal structure of the detector head shown in Figure 39 depicts the layout of the APD and the diffusion film which allows the small active diode area measure a signal proportioned to the power incident upon the 1.09 cm X 0.394 cm aperture as required by SCS-516. Laser light which is incident on the aperture becomes diffused into an approximately lambertian distribution such that the energy in a relatively small angle is proportional to that which is incident upon the aperture. Since the APD's active diameter is 0.762 mm and it is mounted 79 mm from the diffuser, the solid angle subtended is approximately 1.25 degrees and the approximation is much better than the overall precision of the system. The detector box is mounted to the optical rail using standard fixtures including a vertical vernier which permits accurate positioning of the detector. In use, the detector head aperture is

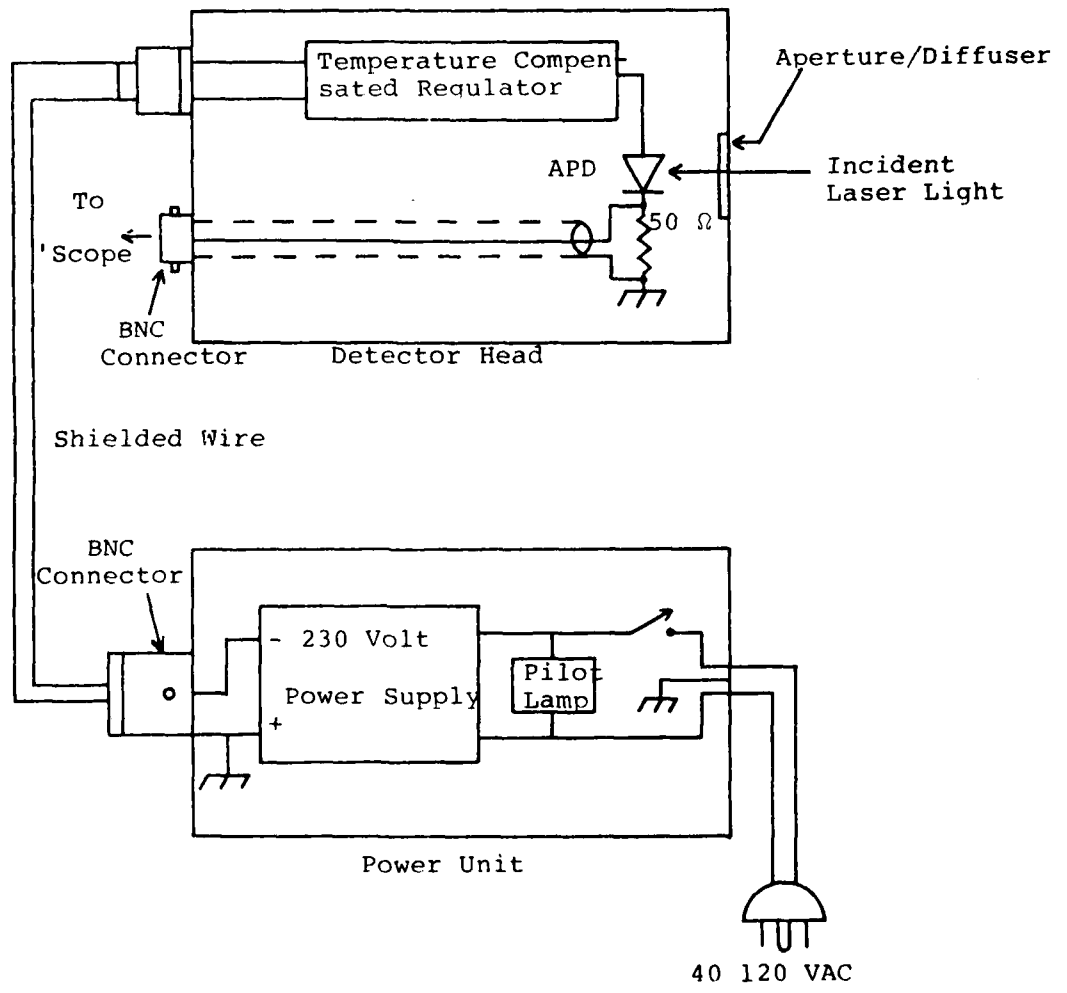


Figure 38 - APD Power Detector System.

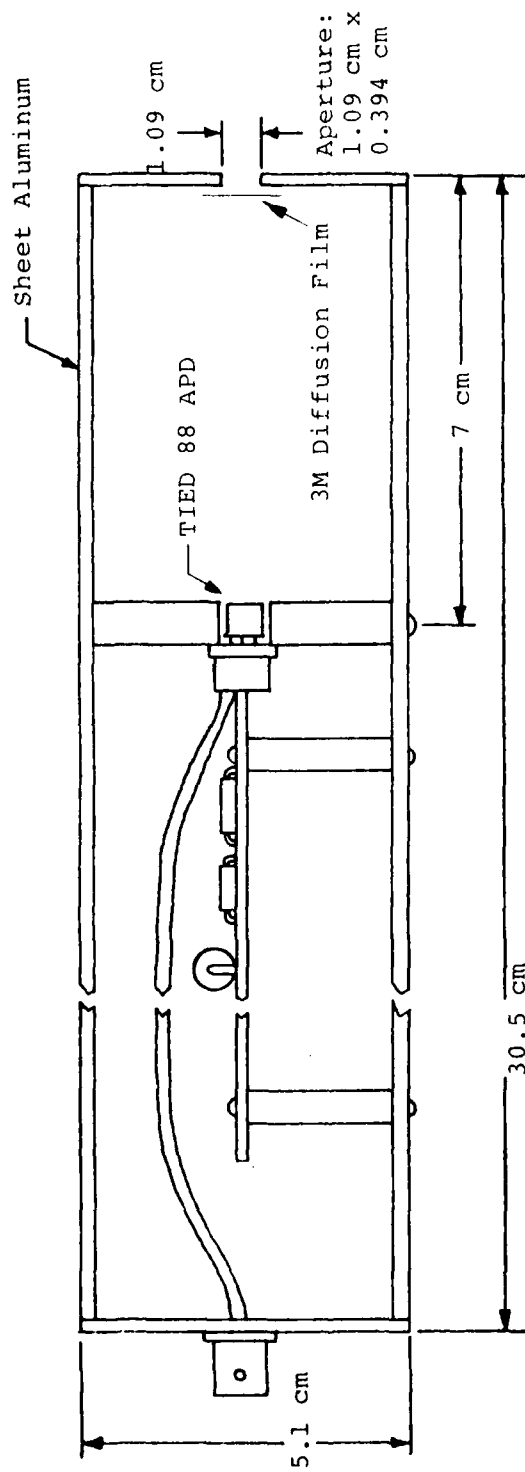


Figure 39 -Internal Structure Power Detector Head.



placed 1.5 cm from the laser to be tested, the power supply is connected and turned on and the detector output is fed to one channel of the sampling oscilloscope. Since the other channel is connected to the current probe in the laser pulser and the 'scope is synchronized to the clock, the oscilloscope trace will, with appropriate calibration factors, read power output vs. drive current.

The far field ("beam pattern") apparatus block diagram is shown in Figure 40. With the 10 ns pulser (Fig 32) mounted atop the goniometer, taking care to locate the laser optical axis on the axis of rotation of the goniometer, the EG&G detector head is located between 65 cm and 75 cm away from the laser (Figure 41) so that its active area subtends a solid angle of less than one degree. The output from the goniometer drives the XY recorder's X axis and the "chart recorder output" from the EG&G 460 drives the "Y" axis. Once the appropriate scale factors are set up, the head is simply rotated manually (Figure 42) to obtain the desired graph.

Figure 43 shows a similar circuit diagram interfaced with a spectrometer for wavelength and spectral width measurements.

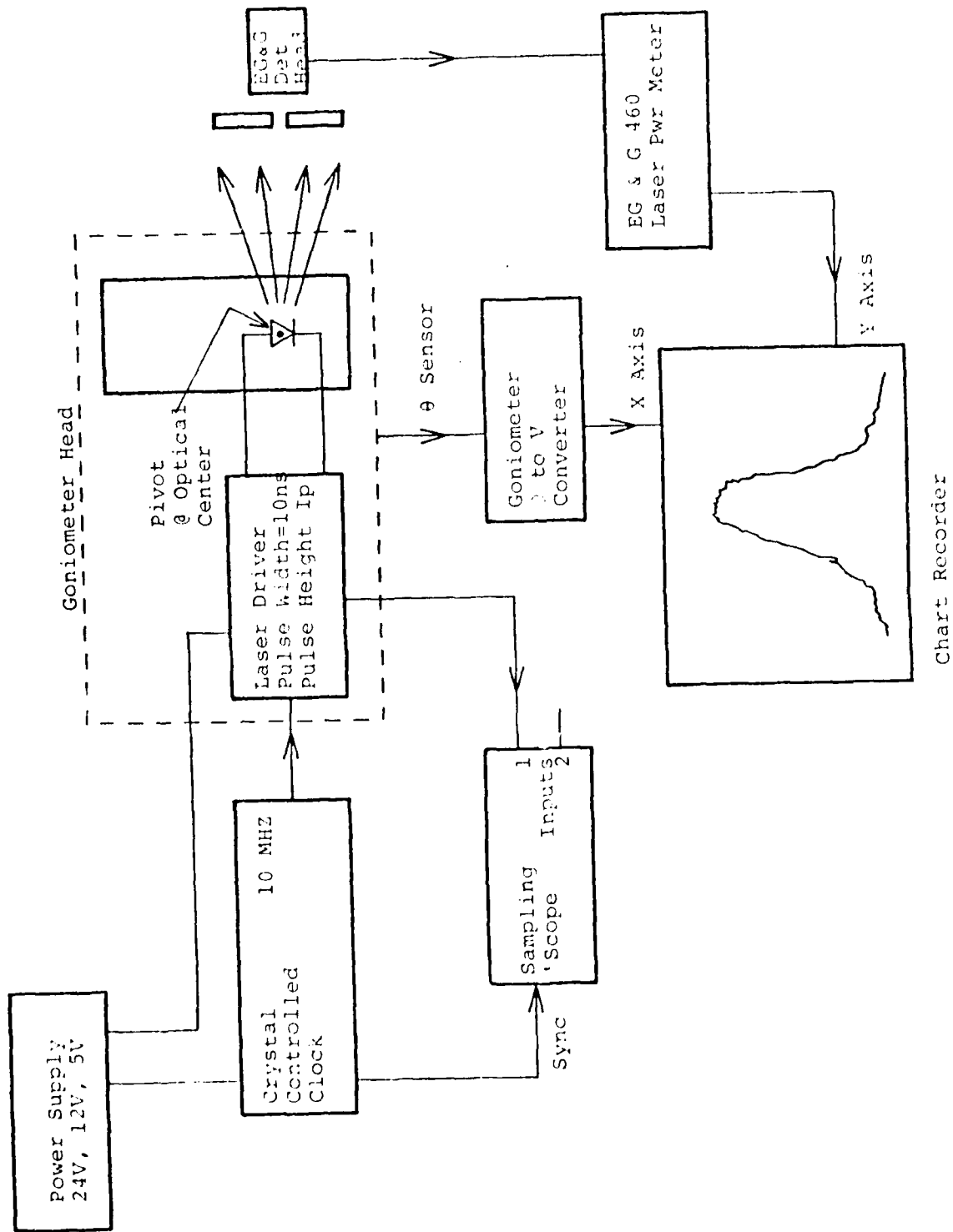


Figure 40 - Measurement of Beam Width.

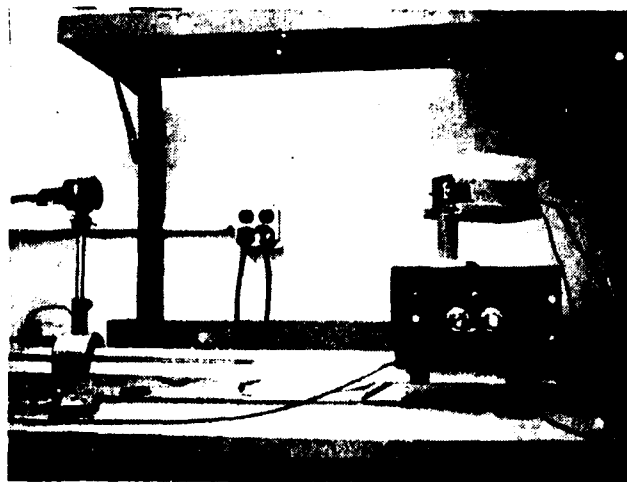


Figure 41 - Photo of EG&G with Pulser on  
Goniometer on Rail.

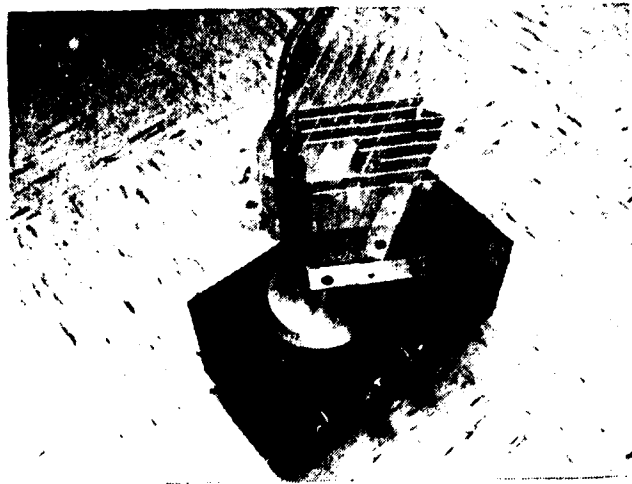


Figure 42 - Double Exposure Illustrating  
Goniometer Operation.

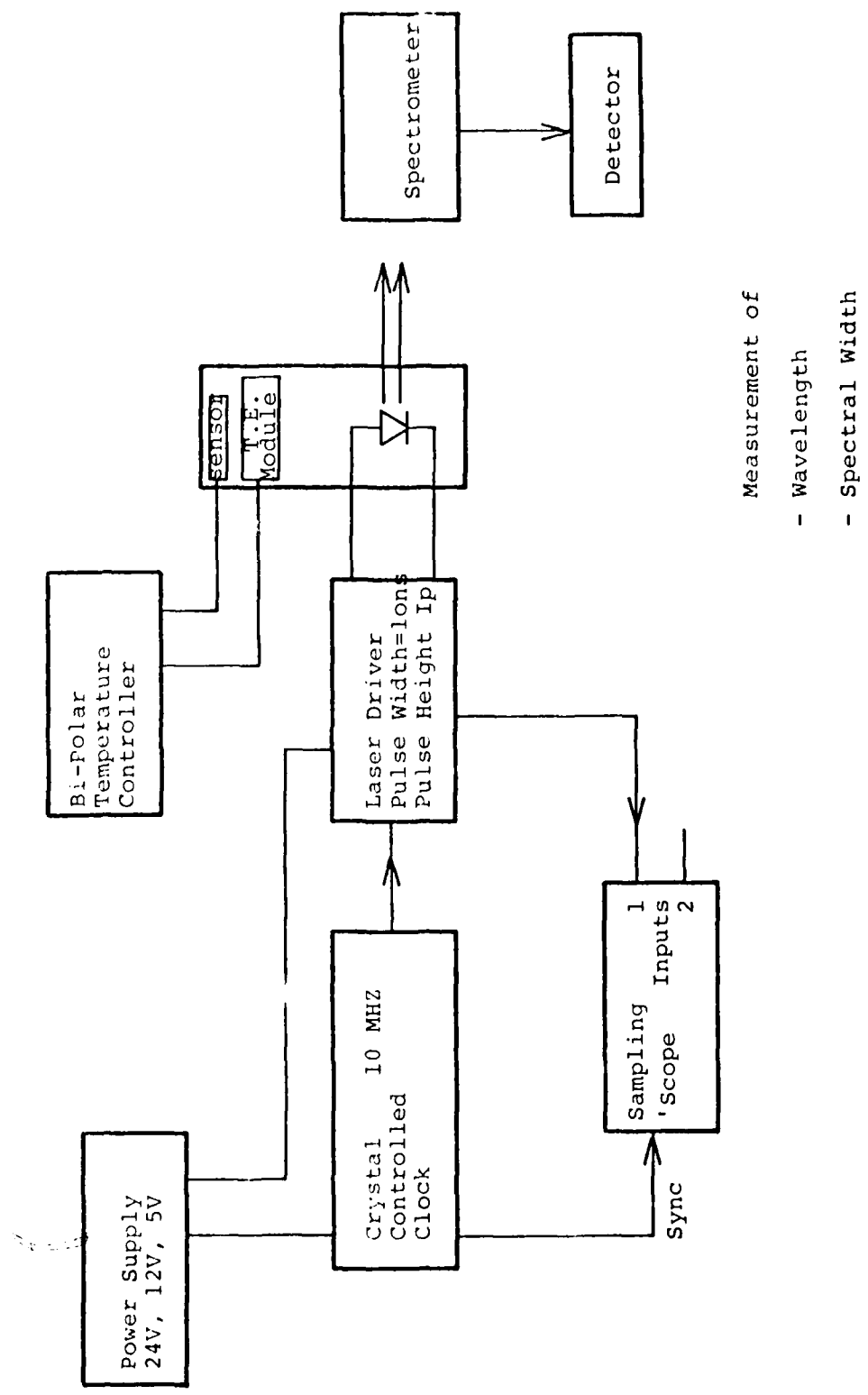
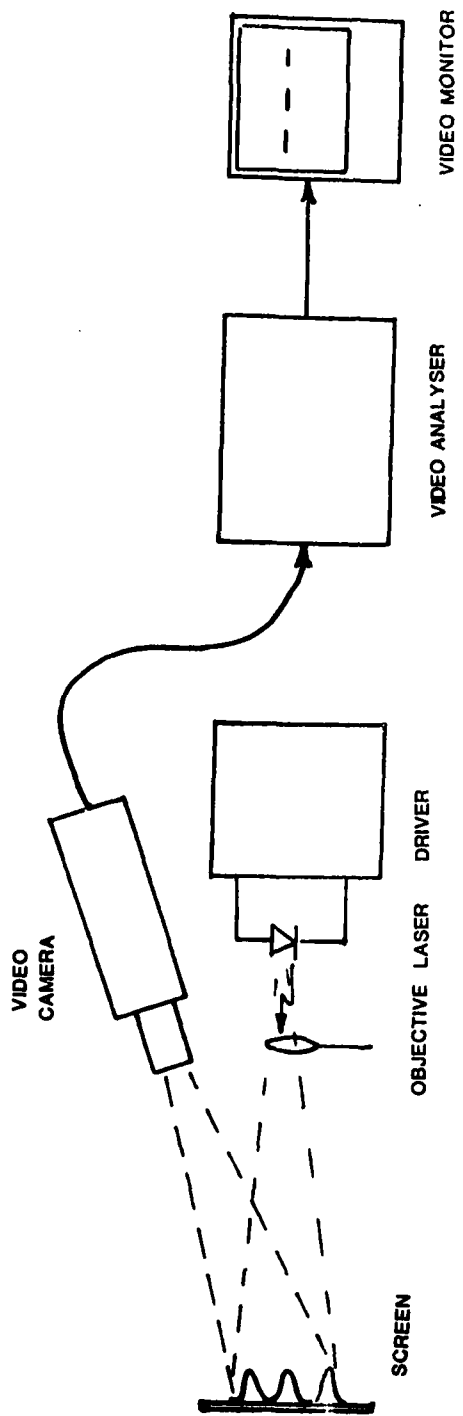


Figure 43

Figure 44 is a diagram of the stripe width and stripe to stripe uniformity measurement system. With a suitable lens, the triple stripe image is projected on to a screen with a measurement grid as background. This projected image is picked up by a video camera, processed by a video analyser and displayed on a video monitor. Part of the display on the monitor is the intensity pattern which can be gauged for stripe to stripe uniformity. Additionally, the actual stripe images are displayed and gauged against the grid background with the appropriate magnification factor for stripe width and stripe to stripe distance. Figure 45 is a photograph of the video monitor with an actual display. The display illustrates to the left, on the monitor, the intensity of the center stripe. The gridded background is seen with calibration dimensions. Figure 46 shows the block diagram of the  $I_p$  and peak power measurement equipment. The previously described components are integrated to form the basis for the test set.



STRIPES WIDTH MEASUREMENT SYSTEM

FIG. 44

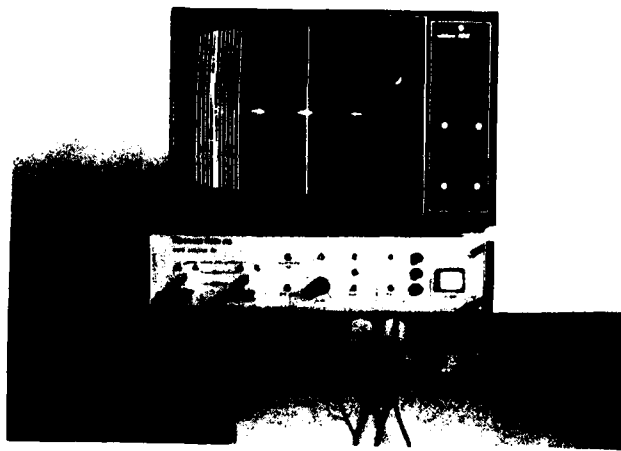


Fig. 45 - Triple Stripe Video Display



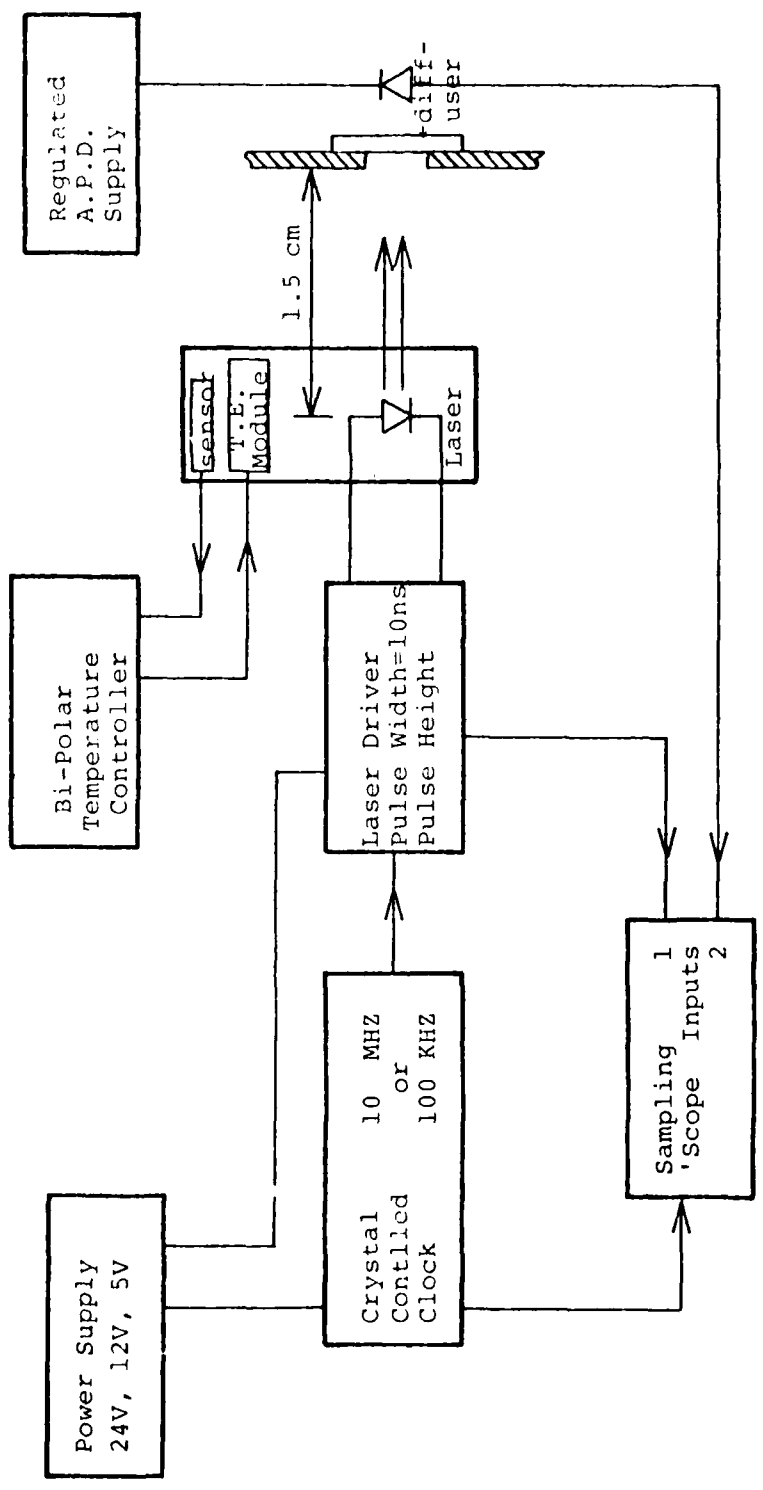


Figure 46. - Measurement of Ip and Peak Power.

SECTION IV

SUMMARY OF PILOT LINE TEST RESULTS

(0040)

TESTING CYCLE

TESTING CYCLE CONSISTED OF:

PROCESS CONDITIONING

PRE-BURN-IN ELECTRICAL

BURN-IN (168 HRS.)

POST BURN-IN ELECTRICAL

GROUP A INSPECTION

GROUP B INSPECTION

GROUP C INSPECTION

ENVIRONMENTAL TESTS PERFORMED AT:

AMERICAN ELECTRONICS LABORATORY

LANSDALE, PA

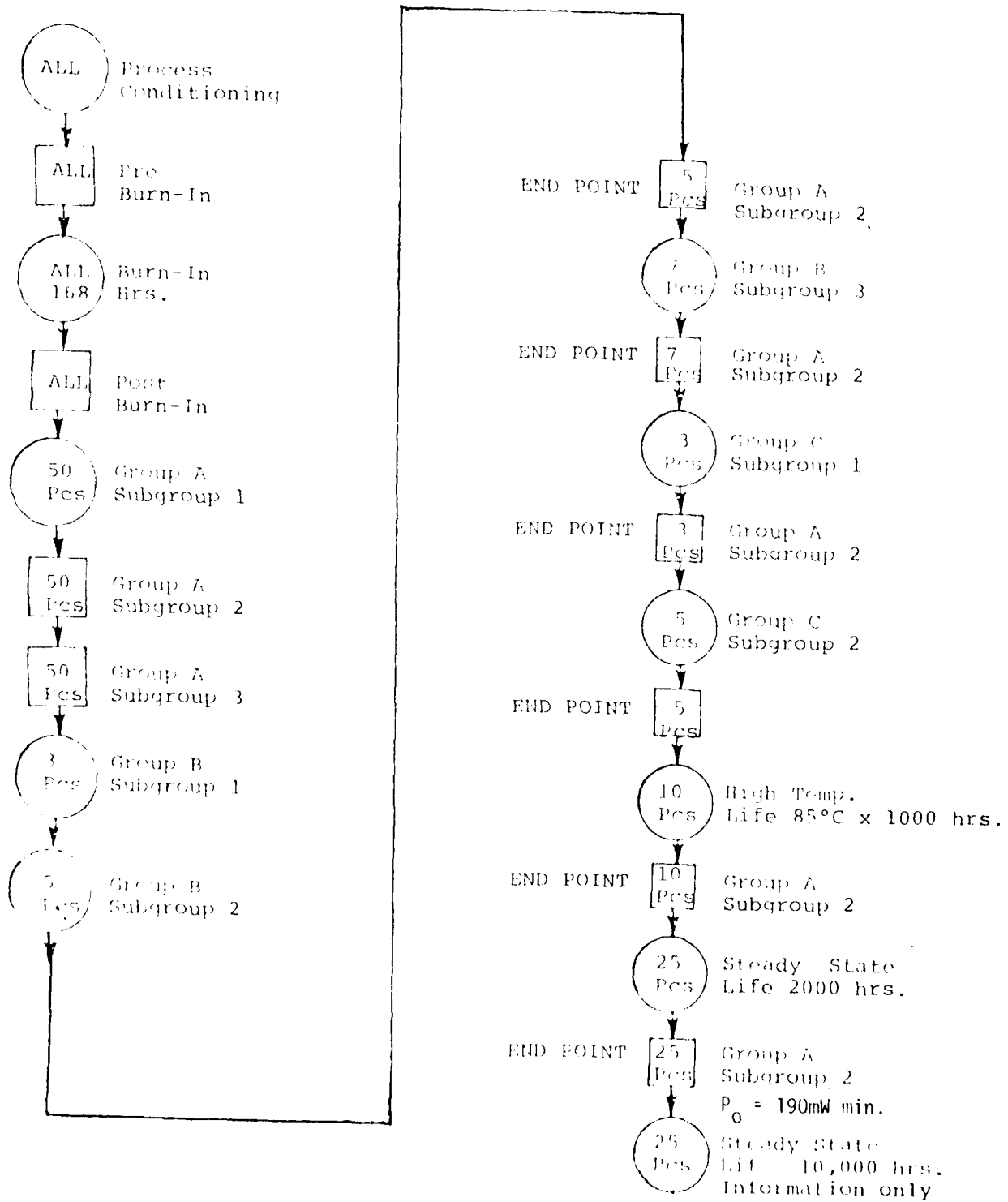
&

ASSOCIATED TESTING LABORATORIES

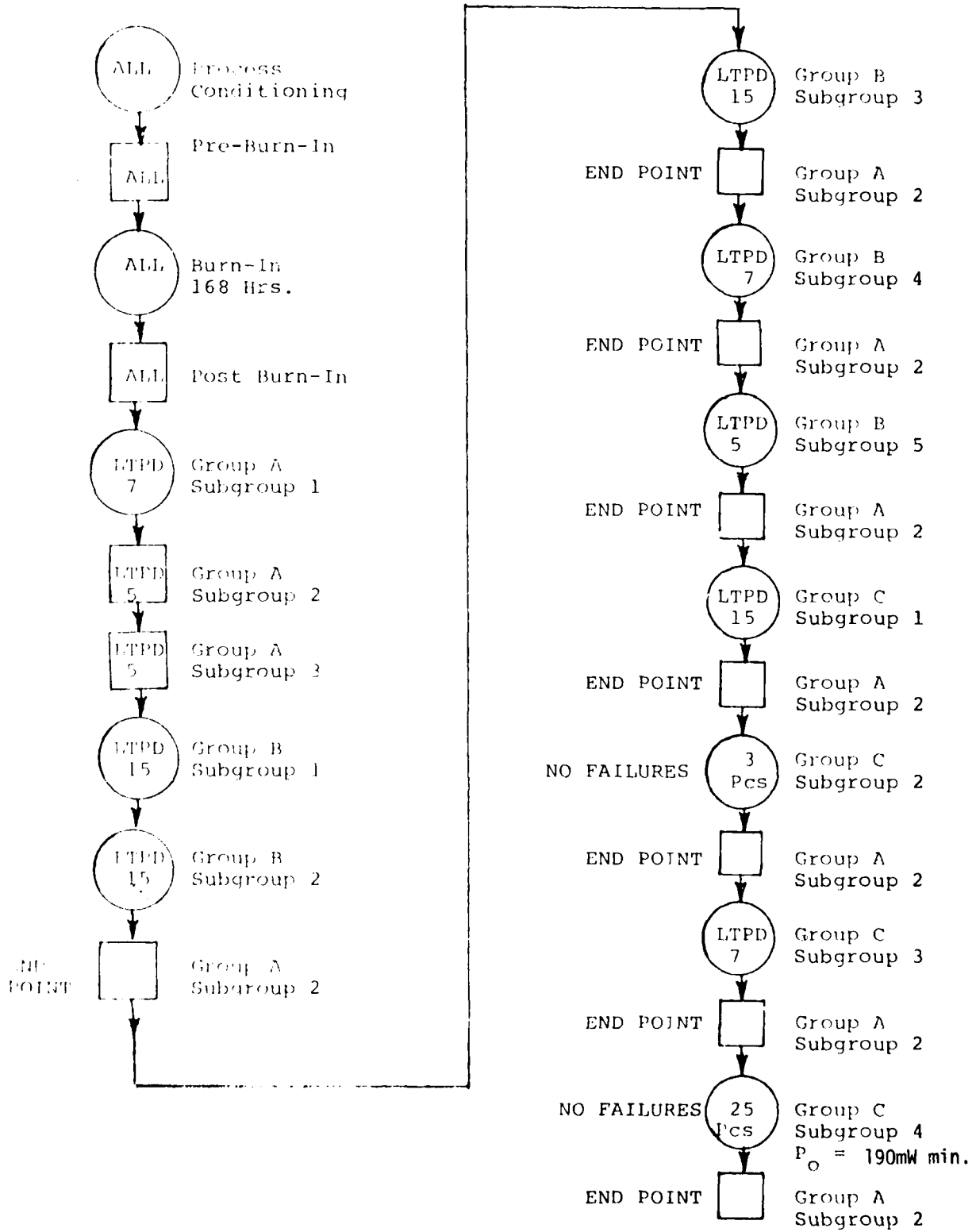
BURLINGTON, MA

FLOW CHART - FIRST ARTICLE (50 Pcs.)

(0040)



FLOW CHART - PRODUCTION TESTING  
(0040)



(0040)

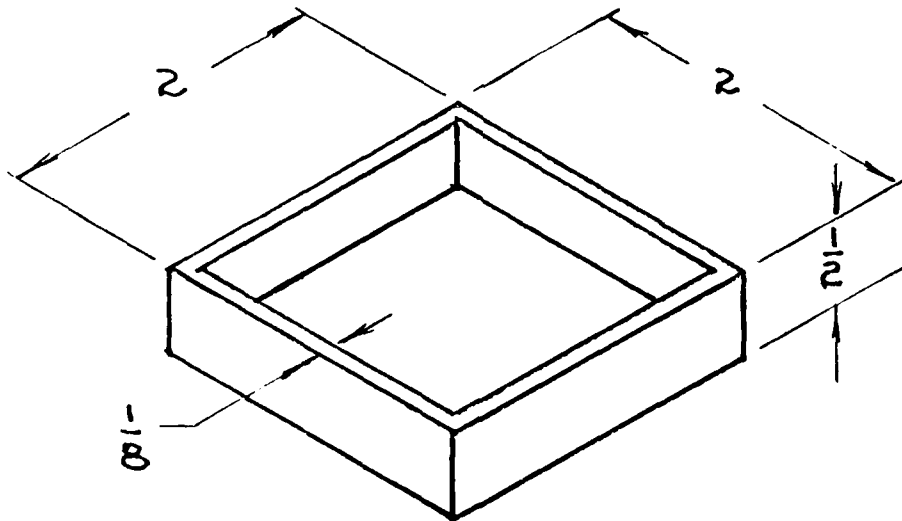
PROCESS CONDITIONING - ALL UNITS

CONDITIONS

TEST	MIL-STD.	METHOD	REQUIREMENTS	TYP. RES.
High Temperature Life	750	1031	85°C x 48 hrs.	PASS
Thermal Shock	202	107/A	$t_r = -40^\circ\text{C}$ $t_h = 85^\circ\text{C}$	PASS
Constant Acceleration	750	2006	1000 6 directions	PASS
PRE-BURN-IN				
Peak Wavelength			800-830 nm	820 nm
Output Power 25°C			200 mw: DF=10%: $t_p = 10\text{ns}$ : $I_p = 3\text{A max.}$	2A
BURN-IN			DF=10%: $t_p = 10\text{ns}$ ; $I_p = 2\text{A Typ.}$	
POST BURN-IN				
Peak Wavelength			800-830nm $\Delta\lambda = 5\% \text{ max.}$	820 nm
Output Power 25°C			200 mw: DF=10%: $t_p = 10\text{ns}$ : $I = 2\text{A Typ.}$	200 mw

(0040)

CAVITY LINED WITH HARD RUBBER  
DEVICES PLACED WINDOW DOWN ON RUBBER  
CAVITY FILLED WITH STEEL SHOT



ACCELERATION FIXTURE

(0040)

GROUP A

TEST	CONDITIONS REQUIREMENTS	TYP. RESULTS
SUBGROUP 1		
Visual & Mechanical	MIL-STD-750 Meth. 2071	PASS
Stripe Width	10% DF $t_p = 10$ ns	-
Triple	75 $\mu$ m Max.	
SUBGROUP 2		
END POINT TESTS		
Peak Wavelength	815 $\pm$ 15 nm	820 nm
Peak Pulse Output Power	200mw min. @ 2A Typ.	200 mw
SUBGROUP 3		
Beam Width	At 202mw min. at $I_p$	
a) Junction Plane	15°	13 $\pm$ 2°
b) Perpendicular to Junct.	40°	38 $\pm$ 2°



(0040)

GROUP B

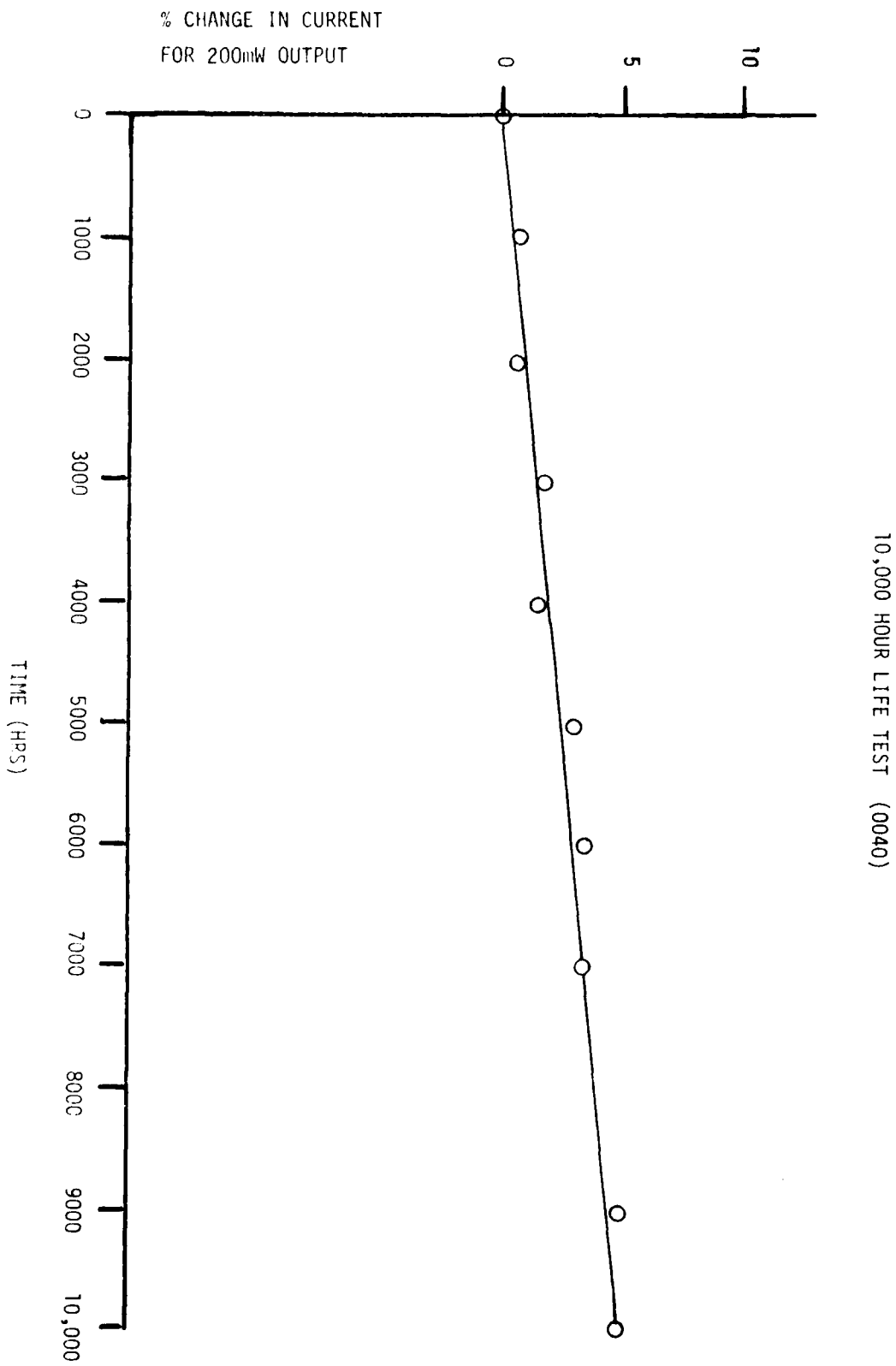
TEST	CONDITIONS			TYP. RES.
	MIL-STD	METHOD	REQUIREMENTS	
SUBGROUP 1				
Physical Dimensions	750	2071		PASS
SUBGROUP 2				
Thermal Shock	750	1051	A-10 cycles	PASS
Moisture Resistance	750	1021		PASS
End Point	Group A - Subgroup 2			NO CHANGE
SUBGROUP 3				
Shock	750	2016	500g 0.5 ms	PASS
Vibration Fatigue	750	2046	-	PASS
Vibration, V.F.	750	2056	-	PASS
Constant Acc	850	2006	1000g 6 dir	
End Point	Group A - Subgroup 2			
SUBGROUP 4				
High Temp. Life	850	1032	82°C x 340 hrs.	PASS
End Point	Group A - Subgroup 2			NO CHANGE
SUBGROUP 5				
Steady State Life (340 Hrs)	750	1027	DF=10% <sub>B</sub> t <sub>B</sub> =10ns: I=2A Typ.	
End Point	Group A - Subgroup 2			200mW @ 2A Typ.

For First Article Subgroups 1.2 & 3 Only

(0040)

GROUP C

TEST	MIL-STD	METHOD	REQUIREMENT	TYP. RESULTS
SUBGROUP 1				
Thermal Shock	750	1051	A1-25 cycles	PASS
End Point	Group A Subgroup 2			NO CHANGE
SUBGROUP 2				
Solvent Resistance	202	215		PASS
End Point	Group A Subgroup 2			PASS
SUBGROUP 3				
High Temp. Life	750	1031	85°C x 1000 hrs	PASS
End Point	Group A Subgroup 2			NO CHANGE
SUBGROUP 4				
Steady-State Life (2000 Hrs.)	750	1026	DF=10%: $t_D=10ns$ : I=3 A max.	PASS
End Point	Group A Subgroup 2 except Pa=190 mw			200 mw



SECTION V

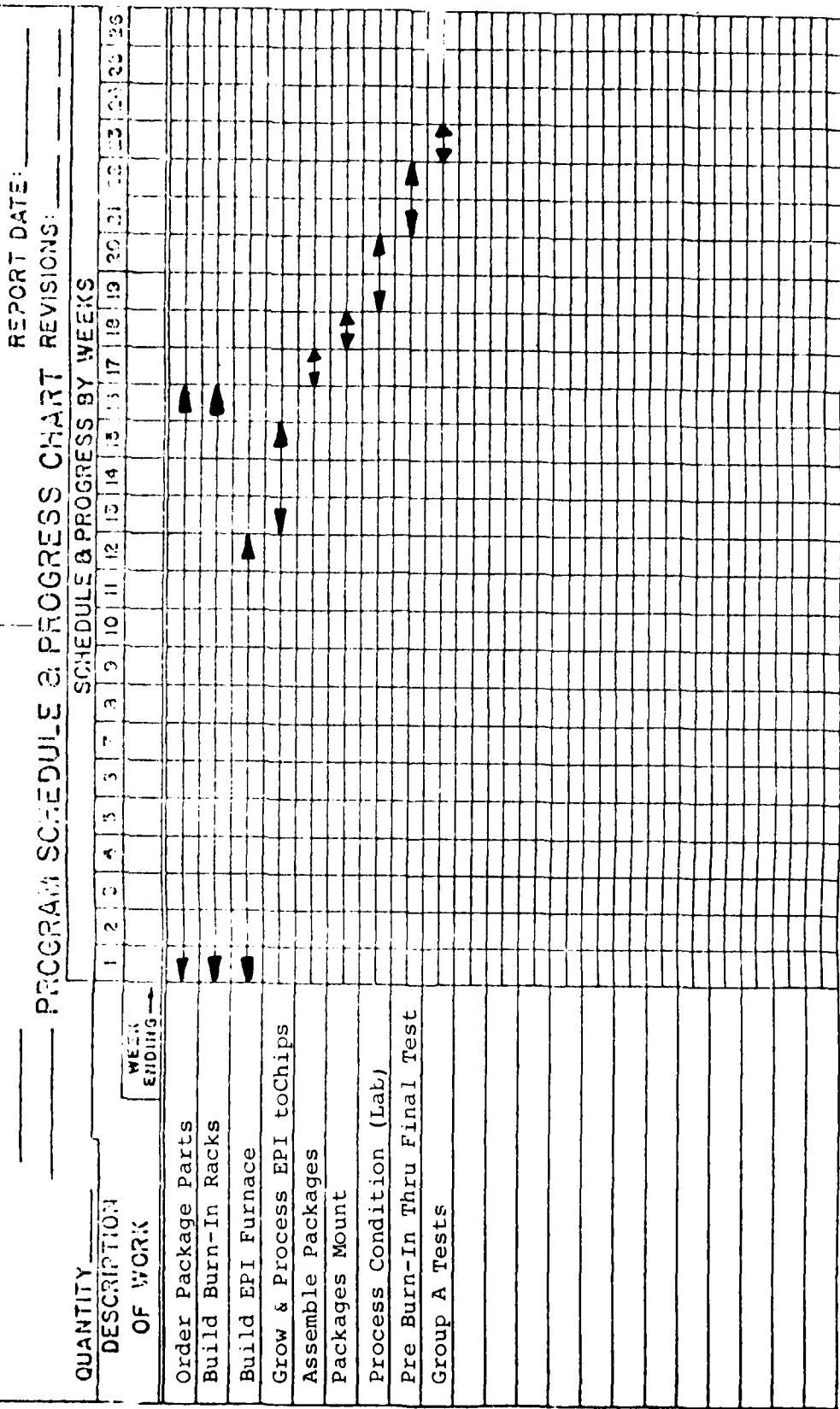
PILOT LINE RATE REPORT

PROCESS	YIELD %	DEVICES REQ'D	RATE/HR
Deliver Devices		300	
Final Electrical Test	90	330	48
Burn-In	100	330	
Pre Burn-In Electrical	63	452	48
Environmental Testing	100	452	
Attach Window	95	475	52
Wire Bond to Chip	90	522	20
Chip Mounting	80	627	20
Wire Bond to Post	95	658	48
Package Assembly	85	756	200

TABLE 8 - PILOT LINE RATES

SECTION VI  
MASS PRODUCTION PLAN

FOR FIRST WEEK'S PRODUCTION



CODE	REVISION	DESCRIPTION	PAGE
ORIGINAL SCHEDULE	h		
PROGRESS	i		
SCHEDULE EXTENSION	j		
	k		
	l		
	m		
	n		

TABLE 9 - VOLUME PRODUCTION SCHEDULE FOR FIRST WEEK'S PRODUCTION

PROCESS STEP	YIELD %	DEVICES/WK	RATE/HR	REQ'D/HR	PEOPLE REQ'D.
Deliver Devices		2553			
Final Electrical Test	90	2808	48	74	1.5
Burn-In	100	2808			
Pre Burn-In Electrical	63	3847	48	101	2.1
Environmental Testing	100	3847			
Attach Window	95	4039	52	67	1.3
Wire Bond to Chip	90	4443	20	111	5.6
Chip Mounting	80	5332	20	133	6.7
Wire Bond to Post	95	5599	48	140	2.9
Package Assembly	85	6439	200	160	1

TABLE 10 - VOLUME PRODUCTION RATES



EPITAXIAL REQUIREMENTS

Diode chips required per week	5332
Maximum number of chips per wafer	2900
Number good electrical chips per wafer	1780
Number wafers required @ 50% yield	6

EQUIPMENT REQUIREMENTS

2630 Burn-In positions @ \$ 180 per position  
7 Assembly Stations @ \$ 2,000 per station  
Epitaxial Furnace \$22,000  
Power Measurement Test Set \$10,000

PERSONNEL REQUIREMENT

Engineers	2
Technicians	2
Assembly	21

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LASER DIODE LABS INC NEW BRUNSWICK NJ  
INJECTION LASER DIODES FOR FIBER OPTIC COMMUNICATIONS.(U)  
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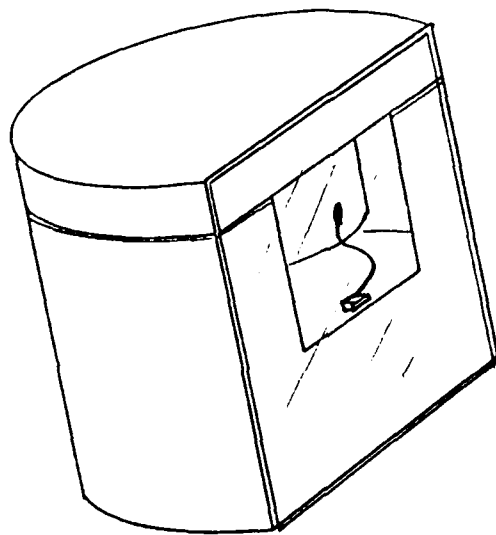
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APPENDIX A  
PRODUCT CAPABILITY DEMONSTRATION

DEMONSTRATION SCHEDULE

February 18, 1981

- 9:00 A.M. - Welcoming Session (Holiday Inn)
- 9:30 A.M. - Technical Presentation Program #8135
- Diode Specifications
  - Diode Chip Concepts
  - Packaging and Assembly Concepts
  - Testing Methods
- 10:45 A.M. - Coffee
- 11:00 A.M. - Technical Presentation Program #0040
- Diode Specifications
  - Diode Chip Concepts
  - Packaging and Assembly Concepts
  - Testing Methods
- 12:00 P.M. - Lunch
- 1:00 P.M. - Transport to LDL (Provided)
- 1:30 P.M. - Tour of LDL Facilities
- Demonstration of Diodes
- 2:30 P.M. - Transport to Holiday Inn (Provided)



CONTRACT DAAB07-76-C-0040

TRIPLE STRIPE LASER



U. S. ARMY CORADCOM SPECIFICATION DAAB07-76-C-0040  
PRODUCT CAPABILITY DEMONSTRATION, FEBRUARY 18, 1981

---

OBJECTIVES

GENERAL MM&T PROGRAM OBJECTIVES

THE ESTABLISHMENT OF MANUFACTURING PROCESSES,  
TECHNIQUES OR EQUIPMENT TO ENSURE EFFICIENT  
PRODUCTION OF CURRENT OR FUTURE DEFENSE PROGRAMS.

SPECIFIC OBJECTIVES

DEVELOP AND DEMONSTRATE A RELIABLE MONOLITHIC,  
LASER ARRAY CAPABLE OF 200 MW PULSED POWER OUTPUT  
AT 820 MM AND 10% DUTY CYCLE CAPABLE OF BEING  
INTERFACED WITH A FIBER ARRAY.

CONTRACT GOALS (LOGISTICS)

- \* ESTABLISH MANUFACTURING METHODS AND PROCESSES.
- \* ENGINEERING, CONFIRMATORY AND PILOT PRODUCTION PHASES.
- \* PILOT PRODUCTION CAPABILITY OF 200 DEVICES.

CONTRACT GOALS (TECHNICAL)

- \* TRIPLE STRIPE MONOLITHIC LASER ARRAY.
- \* 200 mW PEAK OPTICAL POWER AT 10% DUTY CYCLE.
- \* WINDOW PACKAGE FOR FIBER INTERFACING.
- \* ENVIRONMENTAL CAPABILITY



PROBLEMS ENCOUNTERED AND SOLVED

- \* DESIGN OF NARROW STRIPE PHOTO MASK.
- \* WINDOW FOR FIBER INTERFACING.
- \* EPOXIES FOR PACKAGE AND WINDOW ASSEMBLY.
- \* MECHANICAL STRENGTH OF PACKAGE.



PRODUCTION CAPABILITY DEMONSTRATION

REGISTER - FEBRUARY 18, 1981

NAME:	COMPANY:
J. EIDE	ITT
B. HAWKINS	SPECTRONICS DIV., HONEYWELL
JACK HUNTER	CORADCOM U.S. ARMY
LOUIS CORYELL	CORADCOM U.S. ARMY
AL FEDDELER	U.S. ARMY CORADCOM
TED APPLE	CORADCOM
MARK D. SKELDON	NIGHT VISION LABS
LEN FELDBERG	BURNDY CORP.
DAN DAPKUS	ROCKWELL INTERNATIONAL
LOU TOMASETTA	ROCKWELL
GEORGE IRISH	GTE SYLVANIA
MARCUS GARVEY	GTE SYLVANIA
C.J. HWANG	GENERAL OPTRONICS
JOSEPH F. SVACEK	GENERAL OPTRONICS
KEN PEFFLEY	OIS
M. ETTENBERG	RCA
BOB GILL	LDL PRESIDENT
PETE SCHNEIDER	LDL EXECUTIVE VICE PRESIDENT
TOM STOCKTON	LDL VICE PRESIDENT E & D
STEVE KLUNK	LDL SALES ENGINEERING MANAGER
RICHARD KLEIN	LDL MARKETING MANAGER
AL GENNARO	LDL MANAGER SPECIAL PRODUCTS
ALEX CERUZZI	LDL MANAGER DEVELOPMENT ENGINEERING
ROLLIN BALL	LDL SUPERVISOR E & D
ANDY KAN	LDL MANAGER E/O ENGINEERING
STEVE LERNER	LDL MANAGER QUALITY ASSURANCE

APPENDIX B

SCS-516 SPECIFICATIONS

INJECTION LASER DIODE FOR USE IN FIBER OPTIC COMMUNICATIONS

1. SCOPE

1.1 Scope.- This specification covers the detail requirements for Gallium Aluminum Arsenide (GaAlAs) injection laser diodes having a wavelength of 820 nanometers (nm). The injection laser (IL) devices shall incorporate the physical and electrical characteristics compatible with fiber optic cables and systems employing the use of fiber optics.

1.2 Recommended operating conditions:  $I_p = 3A$

$T_a = 20^{\circ}C$

$V_F = 2.0 V$  at  $I_p = 3A$

2. APPLICABLE DOCUMENTS

2.1 The following documents, of the issue in effect on the date of invitation for bids or request for proposals, form a part of this specification to the extent specified herein:

SPECIFICATIONS

MILITARY

MIL-C-675 Coating of Glass Optical Elements.  
MIL-S-19500 Semiconductor Devices, General Specification for.

STANDARDS

MILITARY

MIL-STD-202 Test Methods for Electronic and Electrical Component Parts.  
MIL-STD-750 Test Methods for Semiconductor Devices.

(Copies of documents required by contractors in connection with specific procurement functions should be obtained from the procuring activity or as directed by the contracting officer. Both title and number or symbol should be stipulated when requesting copies.)

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2.2 Other publications.- The following documents form a part of this specification to the extent specified herein. Unless otherwise indicated, the issue in effect on date of invitation for bids or request for proposal shall apply.

Laser Parameter Measurements Handbook, by H. G. Heard.

(Application for copies should be addressed to John Wiley & Sons, Inc., New York, N.Y.)

### 3. REQUIREMENTS

3.1 General description.- The IL devices are double heterojunction (DH) devices used at high data rates at a wavelength of 820 nm and shall be compatible with fiber optic cables. The operating temperature range shall be 20°C to 30°C.

3.2 Performance characteristics.- Performance characteristics shall be as specified in Tables III, IV and V.  $I_p$  is the value of the current to obtain peak pulse optical output power equal to 200 mW and shall have a minimum value of 3A. (See 4.6.5).  $I_p$  shall be determined for each device. This  $I_p$  value shall be the  $I_p$  value used for each device throughout the remainder of the document.

3.2.1 Process conditioning.- All units shall be process conditioned. (See 4.5.1).

3.2.2 Burn-In.- All units shall be burned-in. (See 4.5.2).

3.3 Design, construction, and physical dimensions.- The design, construction and physical dimensions shall be as specified in Figures 1, 2, and 3 and herein.

3.3.1 Metals.- External metal surfaces shall be corrosion resistant or shall be plated or treated to resist corrosion.

3.4 Window.- The window shall contain no strain or cracks over the entire diameter and be free from optical distortion and lens effects over the central 0.303 inch diameter. The window shall be anti-reflection coated on both surfaces for a wavelength of  $\lambda = 820$  nm. The coating shall conform to the abrasion resistance requirement of MIL-C-675.

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3.5 Marking.— Marking shall be in accordance with MIL-S-19500 except the following information shall be marked on each unit.

- (a) Date code.
- (b) Manufacturer's identification.
- (c) Part number: SCS-516

3.6 Resistance to solvents.— When the device is subjected to solvents, there shall be no evidence of: (a) mechanical or electrical damage, (b) deterioration of the materials or finishes, and (c) illegibility of case marking.

3.7 Solderability.— Leads shall be solderable.

3.8 Thermal shock.— After being subjected to specified temperature cycling, there shall be no evidence of defects or damage to case, leads, or seals or loss of marking legibility.

3.9 Shock.— After being subjected to a shock of 500g for .5 msec, there shall be no evidence of defects or damage to leads or seals. Also, the device shall be electrically operable (see Subgroup 2 of Table III).

3.10 Vibration fatigue.— After being subjected to a vibration with a constant peak acceleration of 20g minimum and a frequency of  $60 \pm 20$  Hz for at least  $32 \pm 8$  hours, there shall be no evidence of defects or damage to case, leads or seals. Also, the device shall be electrically operable (see Subgroup 2 of Table III).

3.11 Vibration, variable frequency.— After being subjected to a vibration with a constant peak acceleration of 20g minimum and a frequency range between 100 and 2000 Hz, there shall be no evidence of defects or damage to case, leads, or seals. Also, the device shall be electrically operable (see Subgroup 2 of Table III).

3.12 Constant acceleration.— After being subjected to a constant acceleration of 1000g for 1 minute in each of its orientations, there shall be no evidence of defects or damage to case, leads, or seals. Also, the device shall be electrically operable (see Subgroup 2 of Table III).

3.13 High temperature life.— After being stored at 85°C for the specified time there shall be no evidence of defects or damage to case, leads or seals or loss of marking legibility. Also, the device shall be electrically operable (see Subgroup 2 of Table III).

3.14 Steady state operation.— After being subjected to steady state operation ( $I_p = 100$  mA) for the specified temperature and time, the device shall be electrically operable (see Subgroup 2 of Table III).

3.15 Moisture resistance.— After being subjected to the specified humidity and temperature cycling, there shall be no evidence of corrosion of external metal surfaces. Also, the device shall be electrically operable (see Subgroup 2 of Table III).

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4. QUALITY ASSURANCE PROVISIONS

4.1 Responsibility for inspection.- Unless otherwise specified in the contract, the contractor is responsible for the performance of all inspection requirements as specified herein. Except as otherwise specified in the contract, the contractor may use his own or any other facilities suitable for the performance of the inspection requirements specified herein, unless disapproved by the Government. The Government reserves the right to perform any of the inspections set forth in the specification where such inspections are deemed necessary to assure supplies and services conform to prescribed requirements.

4.2 Classification of inspection.- Inspection shall be classified as follows:

(a) First article inspection (does not include preparation for delivery). (See 4.4).

(b) Quality conformance inspection. (See 4.5).

4.3 Test plan.- The contractor prepared Government-approved test plan, as cited in the contract, shall contain:

(a) Time schedule and sequence of examinations and tests.

(b) A description of the method of test and procedures.

(c) Identification and brief description of each inspection instrument and date of most recent calibration.

4.4 First article.- Unless otherwise specified in the contract, the first article inspection shall be performed by the contractor.

4.4.1 First article units.- The contractor shall furnish 50 samples for first article inspection.

4.4.2 First article inspection.- The first article inspection shall consist of Table II and all the tests included in the Government-approved test plan (See 4.3), to show compliance with the requirements of section 3. No failures shall be permitted.

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4.4.2.1 Order of testing.- Prior to first article inspection, all units shall have been process conditioned followed by burn-in. (See 4.5.1 and 4.5.2).

4.5 Quality conformance inspection.- Quality conformance inspection shall consist of the examinations and tests specified for Group A inspection (Table III), Group B inspection (Table IV), and Group C inspection (Table V). The following shall apply:

(a) Prior to performing Group A inspection, all units shall be subjected to the tests specified in paragraphs 4.5.1 and 4.5.2.

(b) If the manufacturer chooses the following option(s) for testing, the sample units that are to be used in Group C inspection shall be designated as such prior to conducting the referenced Group B tests. Moreover, the number of failed diodes to be counted for lot acceptance or rejection as a result of Group C test shall be equal to all failed diodes of the test in Group B inspection, which were pre-designated for use in Group C inspection, plus any additional failures occurring during Group C testing.

(1) For subgroup 3 life test in Group C inspection, the manufacturer has the option of using all or a portion of the sample already subjected to 340 hours of Group B life testing for an additional 660 hours of testing to meet the 1,000 hour requirement.

(2) For the thermal shock (temperature cycling) test of Group C inspection, the manufacturer has the option of using all or a portion of the sample already subjected to 10 cycles of Group B thermal shock (temperature cycling) testing for an additional 15 cycles of testing to meet the 25-cycle requirement.

4.5.1 Process conditioning.- Process conditioning shall be performed on 100 percent of the units. The measurement and sequence shall be as specified in Table I.

4.5.2 Burn-In.- Burn-in shall be performed on 100% of the units for 268 hours minimum under the following conditions:

$I_p =$  (See 3.2)

$T_a = 20^\circ\text{C}$

DF = 10%

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4.5.2.1 Pre-burn-in measurements.- Prior to burn-in, measurement of the parameters listed in subgroup 2 of Table III shall be performed on 100% of the units at  $T_a = 25^\circ\text{C}$ .

4.5.2.2 Post burn-in measurements.- Post burn-in measurements, listed in subgroup 2 of Table III, shall be performed within 8 hours of the removal of bias conditions at  $25^\circ\text{C}$ . The values observed for each device shall not exceed the following, relative to the pre-burn-in measurements:

$$\Delta \gamma_p = 1\%$$

$$\Delta P_{opt} = 1\%$$

Table I.- Process conditioning

Test	MIL-STD	Method No.	Details
High temperature life (non-operating)	750	1031	Storage temperature = $85^\circ\text{C}$ Storage time = 48 hours minimum
Thermal shock	202	107	Test Condition A except $t(\text{high}) = 85^\circ\text{C}$ ; $t(\text{low}) = -40^\circ\text{C}$ ; time at temperature extremes = 15 minutes maximum
Constant acceleration	750	2006	1,000 g

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Table II.- First article inspection

Test	Reqt Para	Method	No of samples <sup>2/</sup>				
			3	5	7	10	25
Group A inspection	as specified	Table III <sup>1/</sup>	To be performed on all units				
Group B inspection	as specified	Table IV <sup>1/</sup>					
Subgroup 1			X				
Subgroup 2				X			
Subgroup 3					X		
Group C inspection	as specified	Table V <sup>1/</sup>					
Subgroup 1			X				
Subgroup 2				X			
High temperature life	3.13	Method 1031 of MIL-STD-750 T <sub>a</sub> = 85°C for 1000 hrs				X	
Steady state operation life	3.14	Method 1026 of MIL-STD-750 T <sub>a</sub> = 25°C for 2000 hrs I <sub>p</sub> = (See 3.2) DF = 10%					X

<sup>1/</sup> LTPD values do not apply for first article inspection.

<sup>2/</sup> No. of samples specified for each column shall be subjected to all the tests of that column.

<sup>3/</sup> After 2000 hours, the I<sub>opt</sub> shall equal 190 mW minimum.

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Table III.- Group A inspection  
 $T_a = 25^\circ\text{C} \pm 2^\circ\text{C}$  unless otherwise specified

Test	Condition	Test Method	Min	Max	units	LTID
<u>Subgroup 1</u>						7
Visual and mechanical inspection		Method 2071 of MIL-STD-750	See 3.3			
Window		4.6.1				
Stripe width	$I_p =$ (See 3.2)	4.6.3				
(a) single	$t_p = 10$ ns		25		$\mu\text{m}$	
(b) triple	DF = 10%		75		$\mu\text{m}$	
<u>Subgroup 2</u>						5
Peak wavelength	$I_p =$ (See 3.2)	4.6.4	800	830	nm	
Peak optical pulse power output	$I_p =$ (See 3.2)	4.6.5	200		mW	
<u>Subgroup 3</u>						5
Thermal impedance	$I_p =$ (See 3.2) $t_p = 10$ ns	4.6.6	10		$^\circ\text{C}$	
Beam width	$I_p =$ (See 3.2) $t_p = 10$ ns	4.6.7				
(a) in junction plane			15		angular degrees	
(b) perpendicular to junction				40	angular degrees	

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Table IV.- Group B inspection

Test	Reqd Para	MIL-STD-750 Method	Condition	LTPD
<u>Subgroup 1</u>				15
Physical dimensions	3.3	2071	See Figures 1, 2 & 3	
<u>Subgroup 2</u>				15
Thermal shock (temperature cycling)	3.8	1051	Test Condition A except t(high) = 85°C; t(low) = -40°C; 10 cycles; time at temperature extremes = 15 minutes maximum	
Moisture resistance	3.3.1, 3.15	1021		
End point measurements: Subgroup 2 of Table III				
<u>Subgroup 2</u>				15
Shock	3.9	2016	Non-operating 500 g	
Vibration fatigue	3.10	2046	Non-operating	
Vibration, variable frequency	3.11	2056	Non-operating	
Constant acceleration	3.12	2006	force applied = 1,000 g	
End point measurements: Subgroup 2 of Table III				
<u>Subgroup 4</u>				7
High temperature life (non-operating) (See 4.5(b))	3.13	1032	T <sub>a</sub> = 85°C	
End point measurements: Subgroup 2 of Table III				
<u>Subgroup 5</u>				5
Steady state operation life	3.14	1027	I <sub>p</sub> = (See 3.2) at 50°C DF = 10% (See 6.2) t <sub>p</sub> = 10 ns at R <sub>p</sub> = MHz	
End point measurements: Subgroup 2 of Table III				

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Table V.- Group C inspection

Test	Req't Para	MIL-STD-750 Method	Details	LTPD
<u>Subgroup 1</u>				15
Thermal shock (temperature cycling) (See 4.5(b))	3.8	1051	Test Condition A <sub>1</sub> except t(high) = 85°C; t(low) = -40°C; time at temperature extremes = 15 minutes, min; total test time = 72 hrs, max	
End point measurements: Subgroup 2 of Table III				
<u>Subgroup 2</u>				3 devices no failures
Resistance to solvents (See 4.6.2)	3.6	Method 215 of MIL-STD- 202		
End point measurements: Subgroup 2 of Table III				
<u>Subgroup 3</u>				7
High temperature life (non-operating) (See 4.5(b))	3.13	1031	T <sub>a</sub> = 85°C for 1000 hrs	
End point measurements: Subgroup 2 of Table III				
<u>Subgroup 4</u>				5
Steady state operation life	3.14	1026	I <sub>p</sub> = (See 3.2) T <sub>a</sub> = 25°C for 2000 hrs DF = 10% (See 6.2)	
End point measurements: Subgroup 2 of Table III				

<sup>1/</sup>Limits of subgroup 2 Table III same except P<sub>opt</sub> = 190 mW min.

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4.6 Test methods and conditions.- Conditions and methods of examination and test shall be as specified in Tables I, II, III, IV and V and as follows:

4.6.1 Window.- Visual inspection shall be made to insure there are no cracks or optical distortions in the window.

4.6.2 Resistance to solvents.- Resistance to solvents shall be performed in accordance with Method 215 of MIL-STD-202.

4.6.3 Stripe width.- The stripe width size can be determined by using a microscope objective and a normal lens (for projection) combination with a magnification of at least 200X. The image shall be scanned in the junction plane with a calibrated ITT Phototube #F4000 (see 6.3), masked with an 0.5 mm slit. Slit shall be perpendicular to the direction scanned. The relative intensity shall be measured until it falls to 90% of its peak value. These boundaries will define the stripe width. (See Figure 4).

4.6.4 Peak wavelength ( $\lambda_p$ ).- Peak wavelength shall be measured using a grating spectrometer with a resolution of at least one angstrom.

4.6.5 Peak optical pulse power ( $P_{opt}$ ).-  $P_{opt}$  is measured using a calibrated ITT Phototube #F4000 terminated into 50 ohms positioned at a distance of 1.5 cm with a rectangular aperture of width .39 cm and length 1.03 cm. (See Figure 6). (See 6.3).

4.6.6 Thermal impedance.- With unit mounted on a heat sink capable of being heated above room temperature, it is driven at 0.1% duty cycle to minimize self-heating effects. Measurements of peak output wavelength ( $\lambda_p$ ) versus temperature (T) from 20°C to 40°C are recorded. In order to take into account its own heating effect, unit is then operated at 20°C and at 10% duty cycle. The peak output wavelength is then recorded under these conditions. The voltage drop ( $V_D$ ) across the output of the unit is then measured. (See 6.2).

4.6.7 Beam width.- A calibrated ITT Phototube #F4000 (see 6.3), shall be mounted on a turntable and masked with a small aperture so that its angular resolution is at least one degree. The distance between the unit and the detector shall be at least 20 cm. The relative intensity shall be measured until its value falls down to 50% of its peak value. This area will define the beam width. The beam width in angular degrees is measured in both the junction plane and in the plane perpendicular to the junction plane. (See Figure 5).

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## 5. PREPARATION FOR DELIVERY

5.1 Preservation, packaging and packing.- Units shall be prepared for delivery as specified in the contract.

## 6. NOTES

6.1 Abbreviations, symbols, and definitions.- The abbreviations, symbols, and definitions are as follows:

DF	duty factor
$I_p$	input pulse current
$P_{opt}$	peak pulse optical power output
$T_a$	ambient temperature
$t_p$	pulse width at 3 db point
$R_p$	pulse repetition rate
$V_f$	forward voltage
$\lambda_p$	peak wavelength

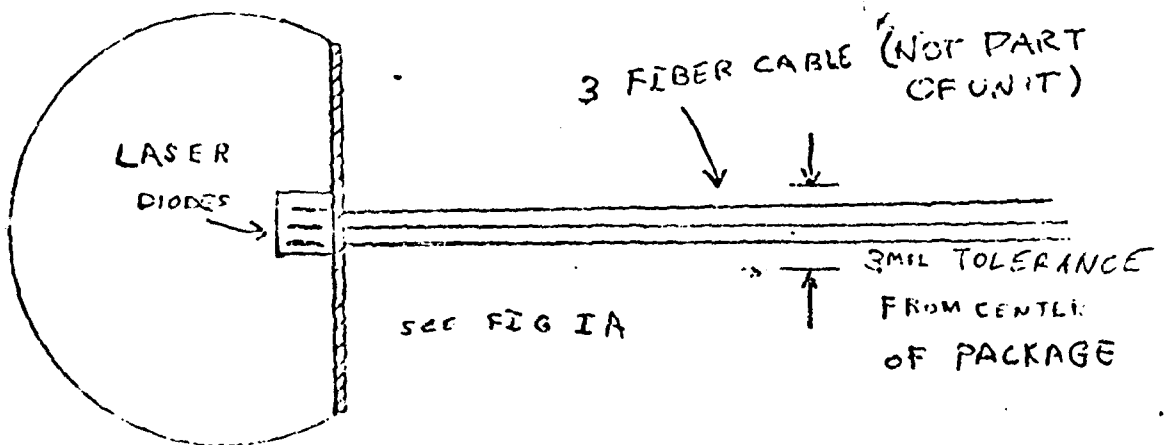
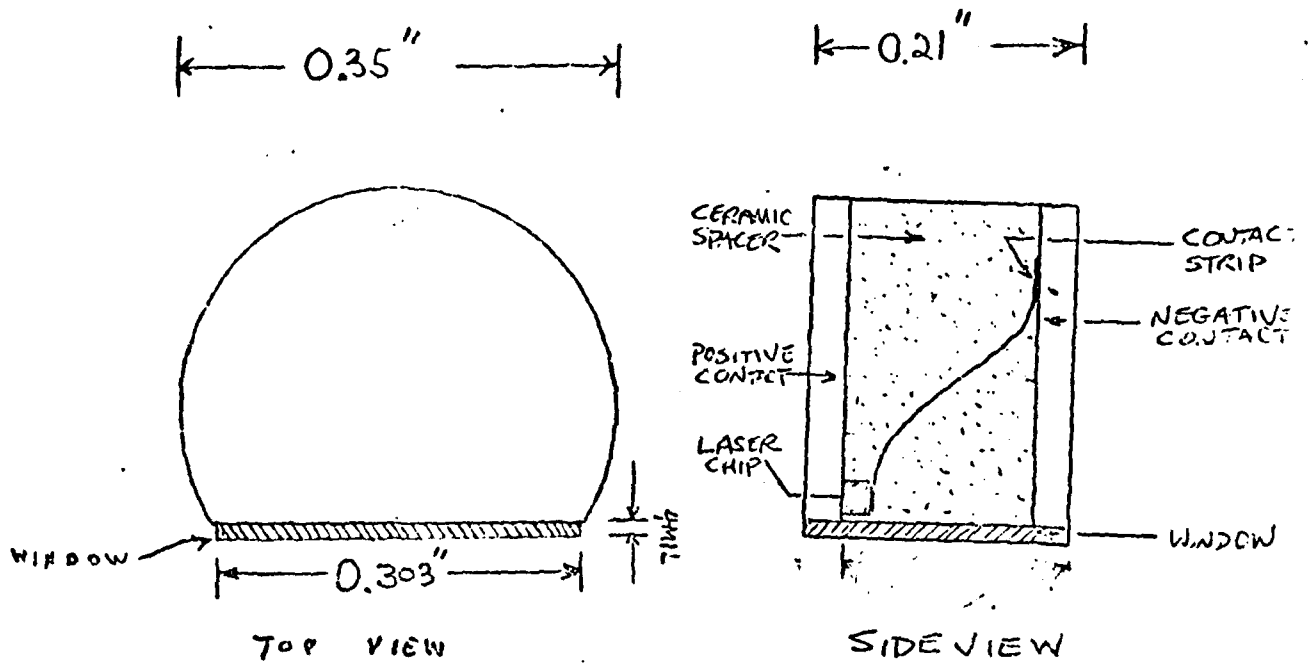
6.2 Calculation of thermal impedance ( $Z_t$ ).- Thermal impedance can be calculated by taking the slope ( $\alpha$ ) of the curve  $\lambda$  vs temperature measured in 4.6.6 and the following:

$$Z_t = \frac{\Delta T}{\Delta P} \quad \text{where } \Delta P = I_p \times V_D \times DF \text{ and } DF = T_p \times t_p$$

$$\Delta T = \frac{\Delta \lambda}{\alpha} \quad \text{- where } \Delta T, \text{ and } \Delta \lambda \text{ are taken from graph}$$

6.3 Method for calibration of ITT phototube #E1300.- This information can be found on pages 180 to 190 in "Laser Parameter Measurements Handbook." Manufacturer's calibration is acceptable if traceable to an NBS standard.

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NOTE: DIMENSIONS ARE MAXIMUM

FIG. 1. Laser package

DAABU/ 10 U-0040



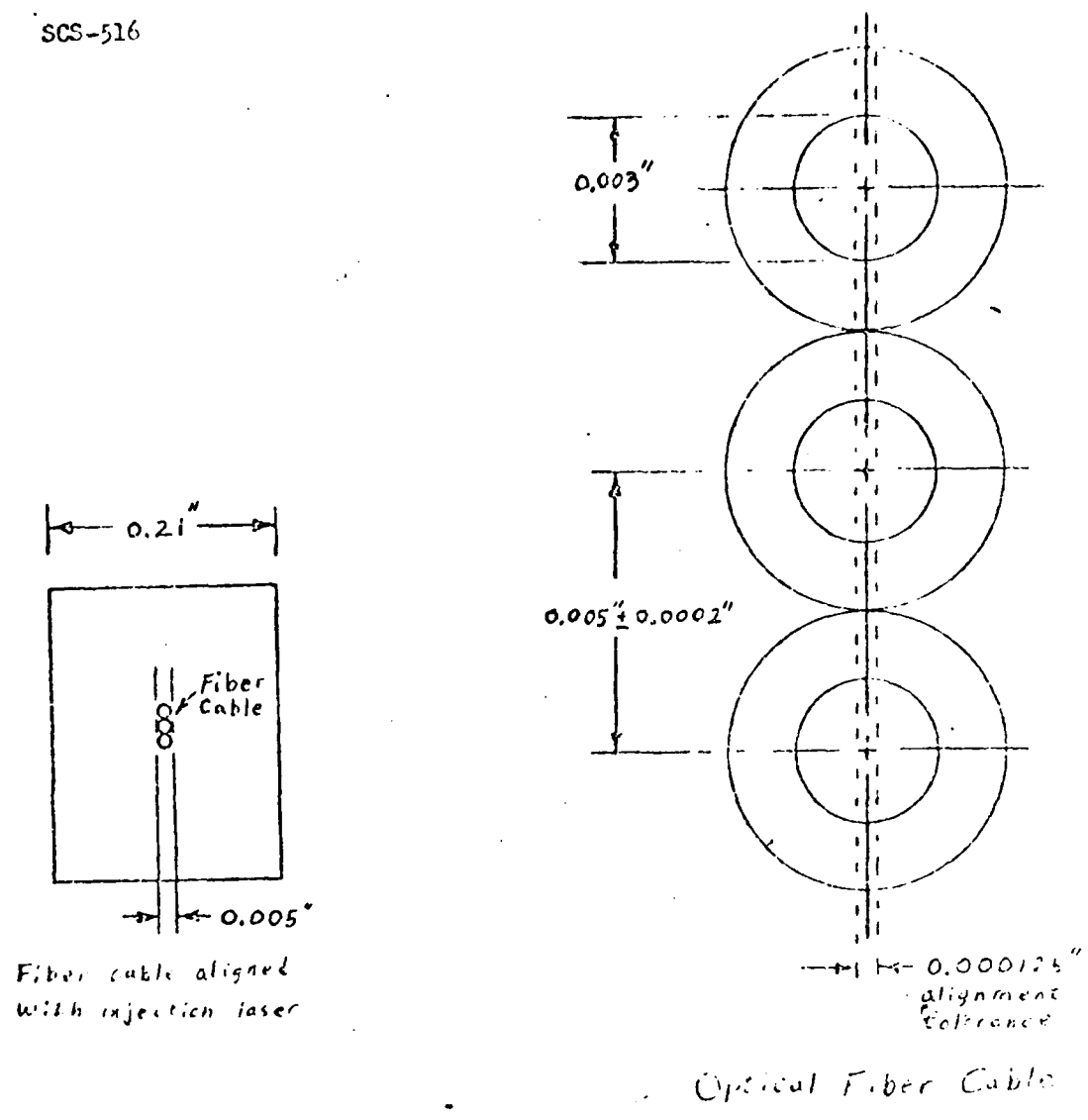
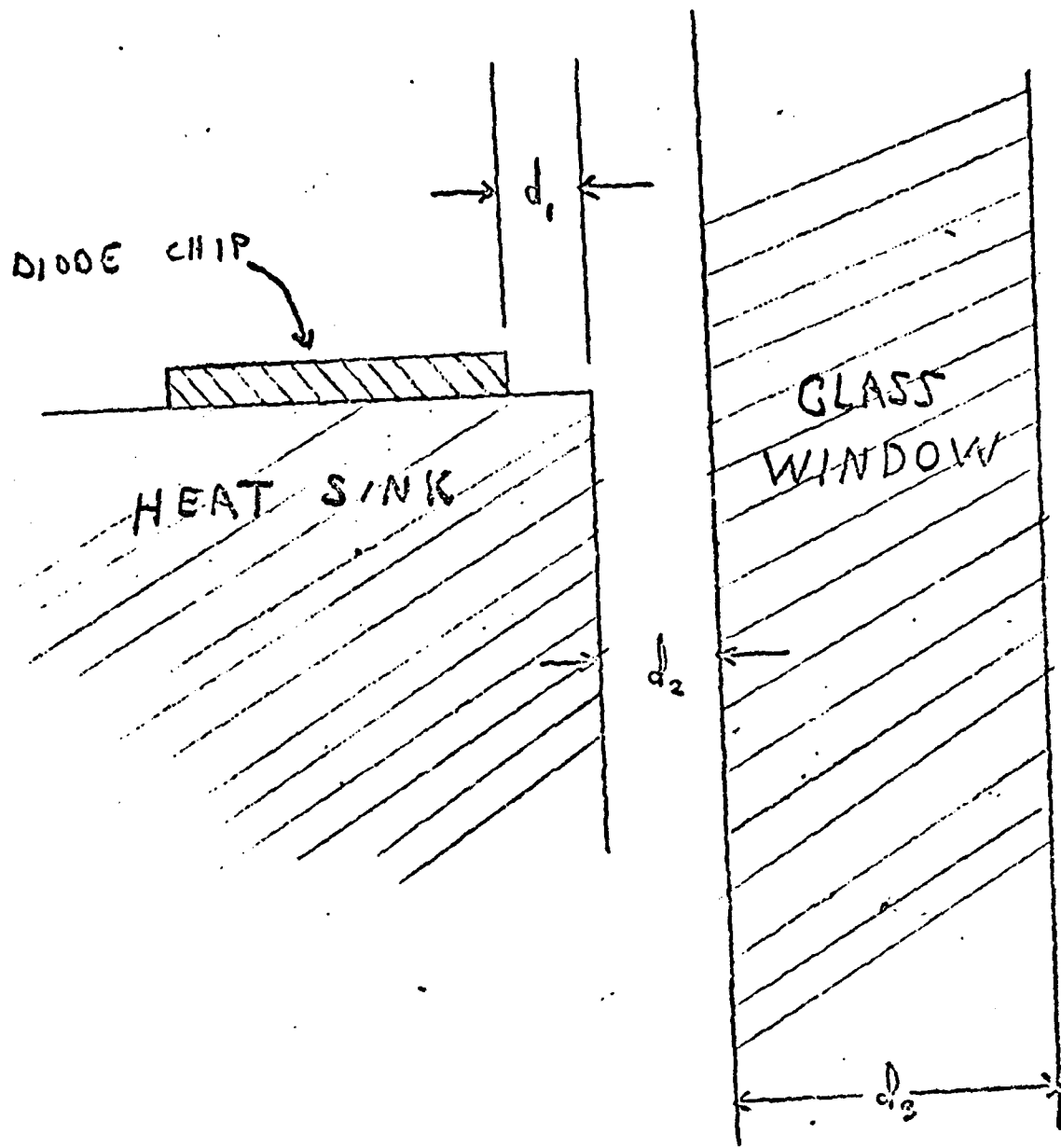


Figure 1A. Fiber cable (NET PART OF UNIT)

DAAR07 76 C-0040

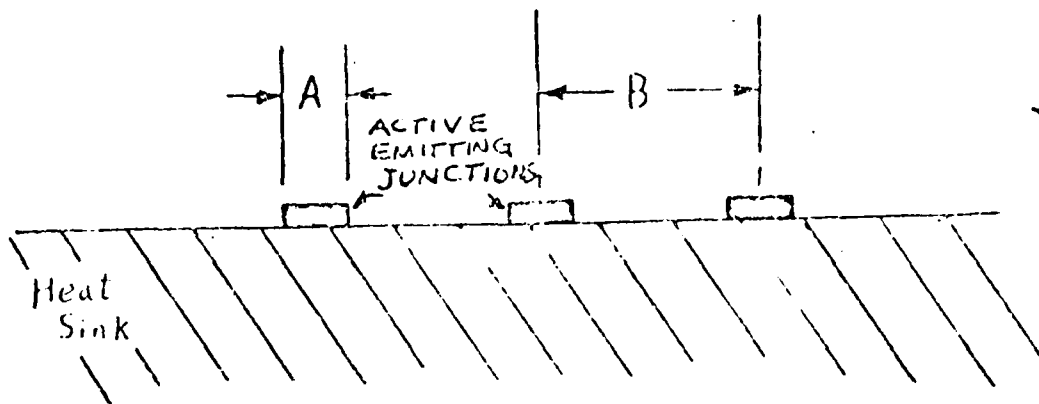


- (MAX)  $d_1 = 1 \text{ MIL } (0.0254 \text{ MM})$
- $d_2 = 1.5 \text{ MIL } (0.0381 \text{ MM}) \pm .5 \text{ MIL}$
- (MIN)  $d_3 = 3 \text{ MIL } (0.1016 \text{ MM})$
- (MAX)  $= 5 \text{ MIL}$

Figure 2. Mounting dimensions

DAAB07 76 C-0040

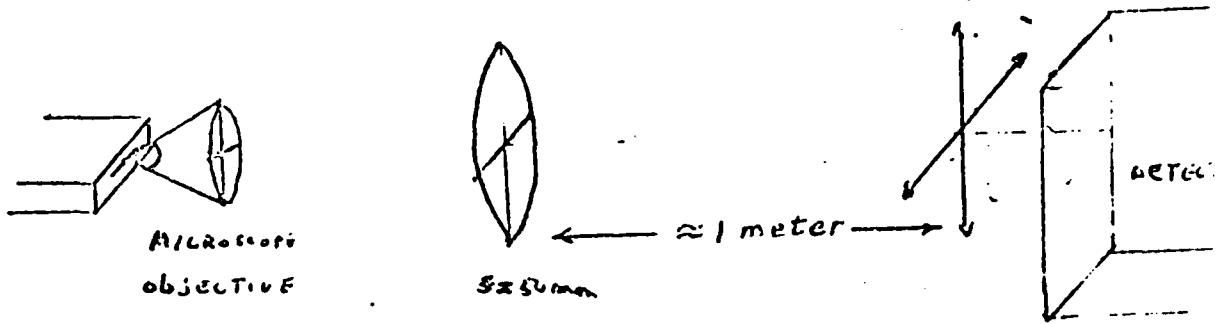
# TRIPLE STRIPE GEOMETRY



DIMENSION	INCHES	MM
A (MAX)	0.001	25
B	0.005 ±0.0002	125 ±5

FIG. 3 FRONT VIEW OF  
DIODE ASSEMBLY

DAAB07 76 C-0040



FRONT VIEW  
OF DETECTOR

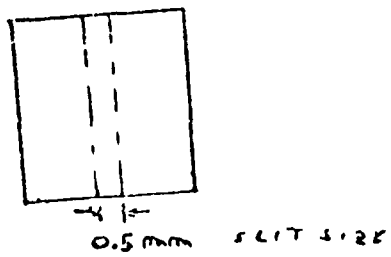


Figure 4. Stripe width

DAAB07 76 C-0040

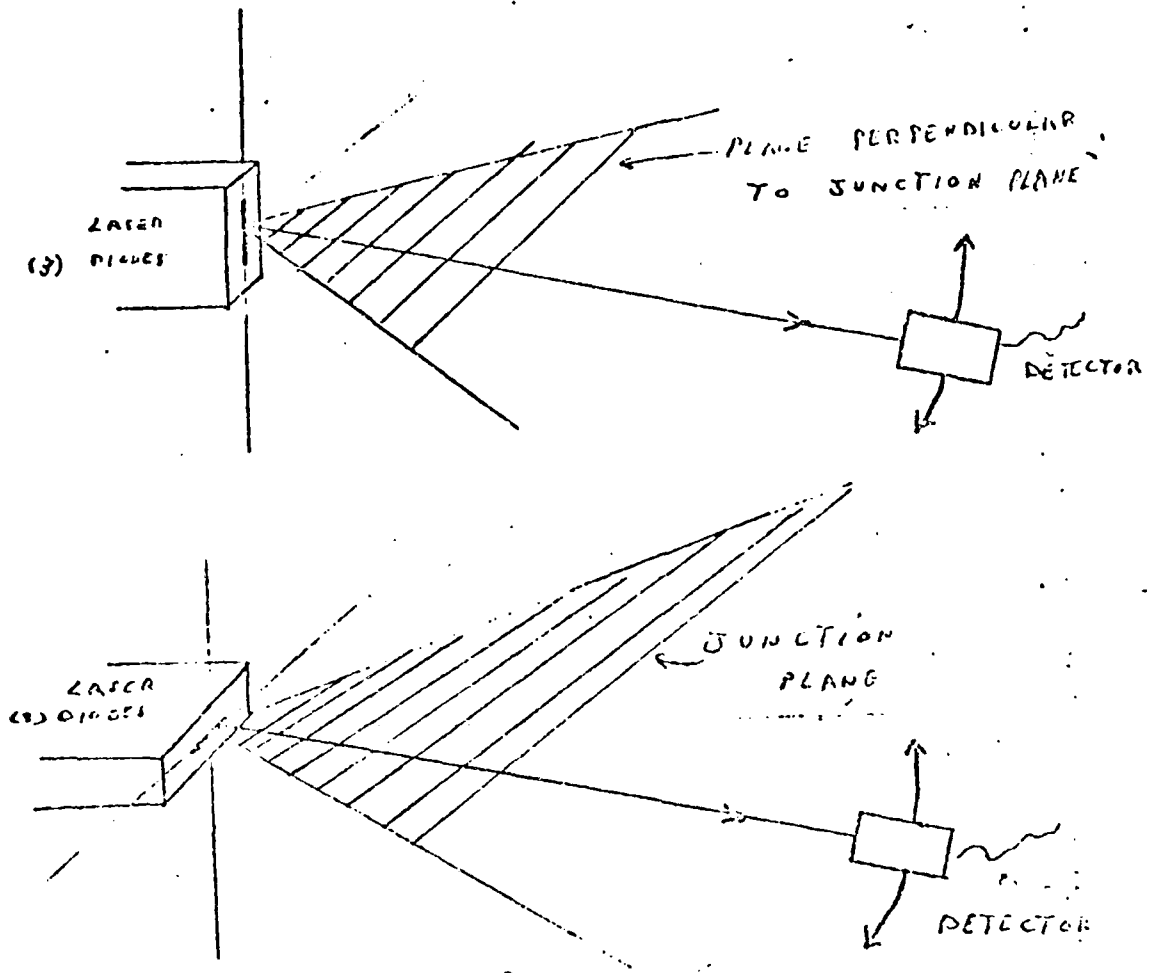


Figure 5. Beam width

DAAB07 76 C-0040

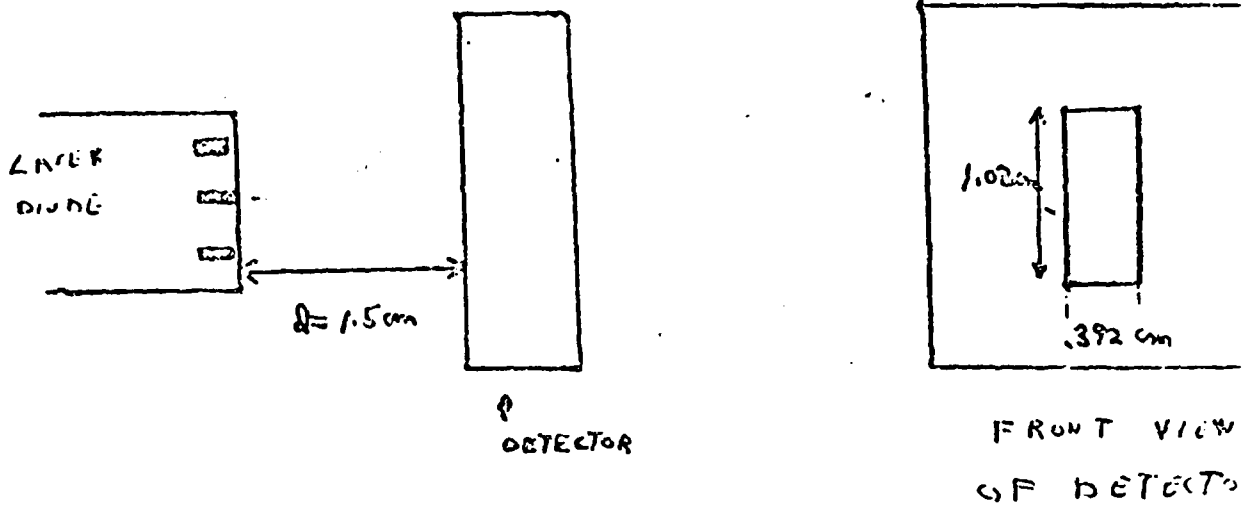


FIG. 6 LASER POWER MEASUREMENTS

DAAB07 76 C-0040

INJECTION LASER DIODE FOR USE IN FIBER OPTIC COMMUNICATIONS

Page 1

1.2 line 2, delete "20°C" and substitute "25°C"

Page 2

3.2 line 3, delete "minimum" and substitute "maximum"

3.4 delete and substitute:

"3.4 Window.- The window shall contain no strain or cracks over that portion which is in the optical path (area of input radiation incident on the injection laser chip). This portion of the window shall also be free from optical distortion and lens effects. The window shall be anti-reflection coated on both surfaces for a wavelength of  $\lambda = 820$  nm. The coating shall conform to the abrasion resistance requirement of MIL-C-675."

Page 3

3.7 delete in its entirety.

3.14 line 2, delete "( $I_p = 100$  mA)"

Page 5

4.5.2 line 4, delete "20°C" and substitute "25°C"

Page 8

Table III, Subgroup 3, Thermal impedance, under units column, delete "°C" and substitute "°C/W"

Page 9

Table IV, Subgroup 5, under Condition column, delete "50°C" and substitute "25°C" for  $I_p$

DAAB07 73 C-0040

Table V, Subgroup 2, under Details column for Resistance to solvents, add, "except solvents used shall be:

- (a) Methyl alcohol, per O-M-232, Grade A.
- (b) Ethyl alcohol, per O-E-00760, Type 1, Grade A.
- (c) Isopropyl alcohol, per TT-I-735, Grade A.
- (d) Three (3) parts by volume of isopropyl alcohol, as specified in (c) above and one (1) part by volume of distilled water."

4.6.1 Add, "This test shall be performed prior to attaching the window to the case."

4.6.2 Add, "except solvents used shall be:

- (a) Methyl alcohol, per O-M-232, Grade A.
- (b) Ethyl alcohol, per O-E-00760, Type 1, Grade A.
- (c) Isopropyl alcohol, per TT-I-735, Grade A.
- (d) Three (3) parts by volume of isopropyl alcohol, as specified in (c) above and one (1) part by volume of distilled water."

4.6.5 line 3, delete ".39 cm" and substitute ".394 cm"  
line 3, delete "1.03 cm" and substitute "1.09 cm"

4.6.6 lines 4 and 5, delete "20°C" and substitute "25°C"

Fig 6 Front view of detector, delete "1.03 cm" and substitute "1.09 cm"  
Delete ".392 cm" and substitute ".394 cm"

DAAB07 73 C-0040



INJECTION LASER DIODE FOR USE IN FIBER OPTIC  
COMMUNICATIONS

Page 8

- Subgroup 1 - Stripe width (a) single - change "25 mm minimum" to "25 mm maximum."
- Stripe width (b) triple - change "75 mm minimum" to "75 mm maximum."
- Subgroup 3 - Thermal impedance - change "10° c/w minimum" to "10° c/w maximum."
- Beam width (9) in junction plane - change "15 angular degrees minimum" to "15 angular degrees maximum."

INJECTION LASER DIODE FOR USE IN FIBER OPTIC  
COMMUNICATIONS

Page 8

To Table III - Subgroup 3, add:

Test	Condition	Test Method	Min	Max	Units
Average Optical Power Output Per Stripe	$I_p =$ (see 3.2) $t_p = 10$ ns	4.6.8 & 6.4	6.3	7.0	mW

Page 11

4.6.8 Power Uniformity from Stripe to Stripe

Laser stripe must be magnified to 200 x using a lens that has a f number of 1.2. The projected images of each of the three junction faces must be tested for average power using a silicon photodiode.

Page 12

6.4 Definition of average optical power

Average optical power = Peak optical power / 10

Average optical power/stripe = 1/3 average optical power.

**/MODIFICATION OF CONTRACT**

1 2

1. MODIFICATION NO. 100001		2. EFFECTIVE DATE See Block 19 below 19 below		3. REQUISITION/PURCHASE REQUEST NO. N/A		4. PROJECT TAG (If applicable)	
ISSUED BY COMMUNICATIONS SYSTEMS PROCUREMENT BRANCH OFFICE OF PROCUREMENT, CERCOM, FT MONMOUTH, NJ 07703; Buyer/Symbol: Captain L'Heureux ORSEL-PC-C-CS-2(LHE) Phone: 201-532-4775		CODE W15171		5. ADMINISTERED BY (If other than block 5) DCASMA - Springfield 240 Route 22 Springfield, NJ 07081		CODE 5310LA	
CONTRACTOR NAME AND ADDRESS LASER DIODE LABORATORIES, INC. 205 Forrest Street Metuchen, NJ 08817 <small>'Street, city, county, state, and ZIP Code)</small>		CODE 4D331		FACILITY CODE		6. AMENDMENT OF SOLICITATION NO. _____ DATED _____ (See block 9) MODIFICATION OF CONTRACT/ORDER NO. DAAB07-76-C-0040 DATED 76 JUN 30 (See block 11)	

7. THIS BLOCK APPLIES ONLY TO AMENDMENTS OF SOLICITATIONS

The above numbered solicitation is amended as set forth in block 12. The hour and date specified for receipt of Offers  is extended,  is not extended. Offerors must acknowledge receipt of this amendment prior to the hour and date specified in the solicitation, or as amended, by one of the following methods:

(a) By signing and returning \_\_\_\_\_ copies of this amendment; (b) By acknowledging receipt of this amendment on each copy of the offer submitted; or (c) By separate letter or telegram which includes a reference to the solicitation and amendment numbers. FAILURE OF YOUR ACKNOWLEDGMENT TO BE RECEIVED AT THE ISSUING OFFICE PRIOR TO THE HOUR AND DATE SPECIFIED MAY RESULT IN REJECTION OF YOUR OFFER. If, by virtue of this amendment you desire to change an offer already submitted, such change may be made by telegram or letter, provided such telegram or letter makes reference to the solicitation and this amendment, and is received prior to the opening hour and date specified.

8. ACCOUNTING AND APPROPRIATION DATA (If required)  
 N/A

**CONTRACTOR'S COPY**

9. THIS BLOCK APPLIES ONLY TO MODIFICATIONS OF CONTRACTS/ORDERS

(a)  This Change Order is issued pursuant to \_\_\_\_\_  
 The Changes set forth in block 12 are made to the above numbered contract/order.

(b)  The above numbered contract/order is modified to reflect the administrative changes (such as changes in paying office, appropriation data, etc.) set forth in block 12.

(c)  This Supplemental Agreement is entered into pursuant to authority of Mutual Agreement of the parties.  
 It modifies the above numbered contract as set forth in block 12.

10. DESCRIPTION OF AMENDMENT/MODIFICATION

I

This Supplemental Agreement is entered into by the parties to amend the basic Specification (SCS-516) as well as to redefine the Pilot Production Run (CLIN 0001AC).

II

Section E - Supplies/Services is amended as follows:

Delete: Block 19 in its entirety.

Add: Pilot Run shall consist of fifty (50) each Single Stripe, fifty (50) each Double Stripe, and two-hundred (200) each Triple Stripe units in accordance with SCS-516 dated 29 December 75 and Amendment No. 4 to SCS-516 dated 4 November 77.

Section F - Description/Specification is amended as follows:

Subsection F.49, Paragraph 2c - Delete "The capacity of each operation" and substitute therefore "The minimum capacity of each operation."

13.  CONTRACTOR/OFFEROR IS NOT REQUIRED TO SIGN THIS DOCUMENT  CONTRACTOR/OFFEROR IS REQUIRED TO SIGN THIS DOCUMENT AND RETURN \_\_\_\_\_ COPIES TO ISSUING OFFICE

14. NAME OF CONTRACTOR/OFFEROR LASER DIODE LABORATORIES, 117. UNITED STATES OF AMERICA

15. NAME AND TITLE OF SIGNER (Type or print)		16. DATE SIGNED		18. NAME OF CONTRACTING OFFICER (Type or print)		19. DATE SIGNED	
_____ (Signature of person authorized to sign)		_____		STEPHEN L. THACHER Major, Signal Corps		_____	

Modification P00001 to:  
Contract No. DAAB07-76-C-0040

Section F - Description/Specification is amended as follows (Cont'd):

Subsection F.49, Paragraph 2d

Delete "The yield of each operation at the specified rate"

and substitute therefore "The estimated yield of each  
operation at the specified rate."

Subsection F.2

"Add" - Amendment No. 4 4 Nov 77 to SCS-516.

III

PCO responsibility for subject contract is hereby transferred from Mr. Gordon  
E. McCain to Major Stephen L. Thacher, DRSEL-PC-C-CS-2(THA) 201-532-3506.

IV

Inclusion of the above changes shall be at no additional cost to the  
Government. All other terms and conditions of this contract remain unchanged.

INJECTION LASER DIODE FOR USE IN FIBER OPTIC COMMUNICATIONS

This amendment forms a part of Electronics Command Technical Requirements SCS-516  
15 August 1975

Page 1

1.2 line 2, delete "20°C" and substitute "25°C"

2.1 add the following under SPECIFICATIONS

"FEDERAL

O-E-00760	Ethyl Alcohol (Ethanol); Denatured Alcohol; Proprietary Solvents and Special Industrial Solvents.
O-M-232	Methanol (Methyl Alcohol).
TT-I-735	Isopropyl Alcohol."

Page 2

3.2 line 3, delete "minimum" and substitute "maximum"

3.4 delete and substitute:

"3.4 Window.- The window shall contain no strain or cracks over that portion which is in the optical path (area of input radiation incident on the injection laser chip). This portion of the window shall also be free from optical distortion and lens effects. The window shall be anti-reflection coated on both surfaces for a wavelength of  $\lambda = 820$  nm. The coating shall conform to the abrasion resistance requirement of MIL-C-675."

Page 3

3.7 delete in its entirety

3.14 line 2, delete "(I<sub>F</sub> = 100 mA)"

- \* Add the following paragraph:

"4.4.2.2 Procedure in case of test equipment failure or operator error. If a device is believed to have failed as a result of faulty test equipment or operator error, the failure shall be entered in the test record which shall be submitted to the Government along with a complete explanation verifying why the failure is believed to be invalid. The Government will then decide whether or not the failure is due to a valid part defect. If the Government rules that the failure is invalid, a replacement device from the same inspection lot may be added to the sample. The replacement device shall be subjected to all those tests to which the discarded device was subjected prior to its failure and to any remaining specified tests to which the discarded device was not subjected prior to its failure."

- \* Add the following subparagraph to paragraph 4.5:

"(c) Procedure in case of test equipment failure or operator error. If a device is believed to have failed as a result of faulty test equipment or operator error, the failure shall be entered in the test record which shall be submitted to the procuring activity along with a complete explanation verifying why the failure is believed to be invalid. The procuring activity will then decide whether or not the failure is due to a valid part defect. If the procuring activity rules that the failure is invalid, a replacement device from the same inspection lot may be added to the sample. The replacement device shall be subjected to all those tests to which the discarded device was subjected prior to its failure and to any remaining specified tests to which the discarded device was not subjected prior to its failure."

4.5.2 line 4, delete "20°C" and substitute "25°C"

- \* 4.5.2.2 line 6, delete " $\Delta P_{opt} = 1\%$ " and substitute " $\Delta P_{opt} = 5\%$ "

\* Table III, delete and substitute the following:

"Table III.- Group A inspection  
 $T_a = 25^{\circ}\text{C} \pm 2^{\circ}\text{C}$  unless otherwise specified

Test	Condition	Test Method	Min	Max	Units	LTPD
<u>Subgroup 1</u>						7
Visual and mechanical inspection		Method 2071 of MIL-STD-750	See 3.3			
Window		4.6.1				
Stripe width	$I_p =$ (See 3.2)	4.6.3				
(a) single	$t_p = 10$ ns			25	$\mu\text{m}$	
(b) double	DF = 10%			50	$\mu\text{m}$	
(c) triple				75	$\mu\text{m}$	
<u>Subgroup 2</u>						5
Peak wavelength	$I_p =$ (See 3.2)	4.6.4	800	830	nm	
Peak optical pulse power output	$I_p =$ (See 3.2)	4.6.5				
(a) single			65		mW	
(b) double			130		mW	
(c) triple			200		mW	
<u>Subgroup 3</u>						5
Thermal impedance	$I_p =$ (See 3.2)	4.6.6				
(a) single	$t_p = 10$ ns			30	$^{\circ}\text{C}/\text{W}$	
(b) double				15	$^{\circ}\text{C}/\text{W}$	
(c) triple				10	$^{\circ}\text{C}/\text{W}$	
Beam width	$I_p =$ (See 3.2)	4.6.7				
(a) in junction plane	$t_p = 10$ ns			15	angular degrees	
(b) perpendicular to junction				40	angular degrees	
Power uniformity from stripe to stripe	$I_p =$ (See 3.2) $t_p = 10$ ns	4.6.8		10%	<u>1/</u>	

1/ Any device in which the relative power output of the weakest stripe is less than 90% of the relative power output of the most powerful stripe shall be rejected.

Table IV, Subgroup 5, under Condition column, delete "50OC" and substitute "25OC" for I<sub>p</sub>

Table V, Subgroup 2, under Details column for Resistance to solvents, add, "except solvents used shall be:

- (a) Methyl alcohol, per O-M-232, Grade A.
- (b) Ethyl alcohol, per O-E-00760, Type 1, Grade A.
- (c) Isopropyl alcohol, per TT-I-735, Grade A.

(d) Three (3) parts by volume of isopropyl alcohol, as specified in (c) above and one (1) part by volume of distilled water."

4.6.1 Add, "This test shall be performed prior to attaching the window to the case."

4.6.2 Add, "except solvents used shall be:

- (a) Methyl alcohol, per O-M-232, Grade A.
- (b) Ethyl alcohol, per O-E-00760, Type 1, Grade A.
- (c) Isopropyl alcohol, per TT-I-735, Grade A.

(d) Three (3) parts by volume of isopropyl alcohol, as specified in (c) above and one (1) part by volume of distilled water."

\* 4.6.3 delete and substitute:

"4.6.3 Stripe width. The stripe width size can be determined by using a closed circuit TV based system. A 40X microscope objective shall be used to project an image with magnification of at least 200X of the laser on a sheet of metric graph paper. This image, after being reduced in intensity by insertion of suitable attenuation in the laser beam path is in turn picked up via the TV camera. The combined images of the laser and the grid shall be displayed on the screen of the TV monitor. Since the stripe spacing is determined with a high degree of accuracy by the photolithographic mask, the magnification of the projection system may readily be determined. The stripe width may, therefore, be measured directly without requiring XY calibration of the TV system. An oscilloscope shall be used to monitor the video waveform and insure that the TV camera is not being saturated."



\* 4.6.5 delete and substitute:

"4.6.5 Peak optical pulse power ( $P_{opt}$ ) -  $P_{opt}$  is measured using a calibrated avalanche photodiode system terminated into 50 ohms positioned at a distance of 1.5 cm with a rectangular aperture of width 0.39 cm and length 1.03 cm. (See Figure 6 and paragraph 6.3)."

4.6.6 lines 4 and 5, delete "20°C" and substitute "25°C"

\* 4.6.7 delete and substitute:

"4.6.7 Beam width. With the laser mounted in a rotatable pulser, the detector head of a calibrated E.G. & G. model 460 is placed at least 65 cm away to obtain an angular resolution of at least one degree. The relative intensity shall be measured until its value falls to 50% of its peak value. This area will define the beam width. The beam width in angular degrees is measured in both planes parallel and perpendicular to the junction. (See Figure 5)."

Page 12

\* Add the following new paragraph:

"4.6.8 Power uniformity from stripe to stripe. Using a CCTV system as outlined in 4.6.3, the video waveform from the TV camera shall be monitored on an oscilloscope. The peaks of the video waveform correspond to the relative powers from the individual stripes.

\* 6.3 delete and substitute:

"6.3 Method for calibration of the avalanche photodiode (APD) system. Using ten representative triple stripe lasers pulsed at low duty cycle, measurements shall be made with both the APD and an NBS traceable ITT F4000 tube. In both cases the separation between source and detector shall be as small as possible to insure collection of all the energy and good correspondence. Correlation of these data will give a calibration factor for the APD system."

Page 13

\* Add new paragraph:

"6.3.1 Method for relative calibration of the TV system amplitude response. Focus the TV camera on a standard grey scale with known reflectance values. The resulting video waveform voltages monitored on an oscilloscope will correspond proportionally to these values and will permit drawing a relative calibration curve for the amplitude response of the TV system."

SCS-516  
AMENDMENT-4

Add the following paragraph:

"6.4 Calculation of average optical power.

Average optical power =  $P_{opt}/10$

Average optical power/stripe = 1/3 average optical power."

Page 13

FIG 1. Delete FIG 1. and substitute new FIG. 1.

Page 14

FIGURE 1A. Delete "0.21" dimension and substitute ".300 ± .005"

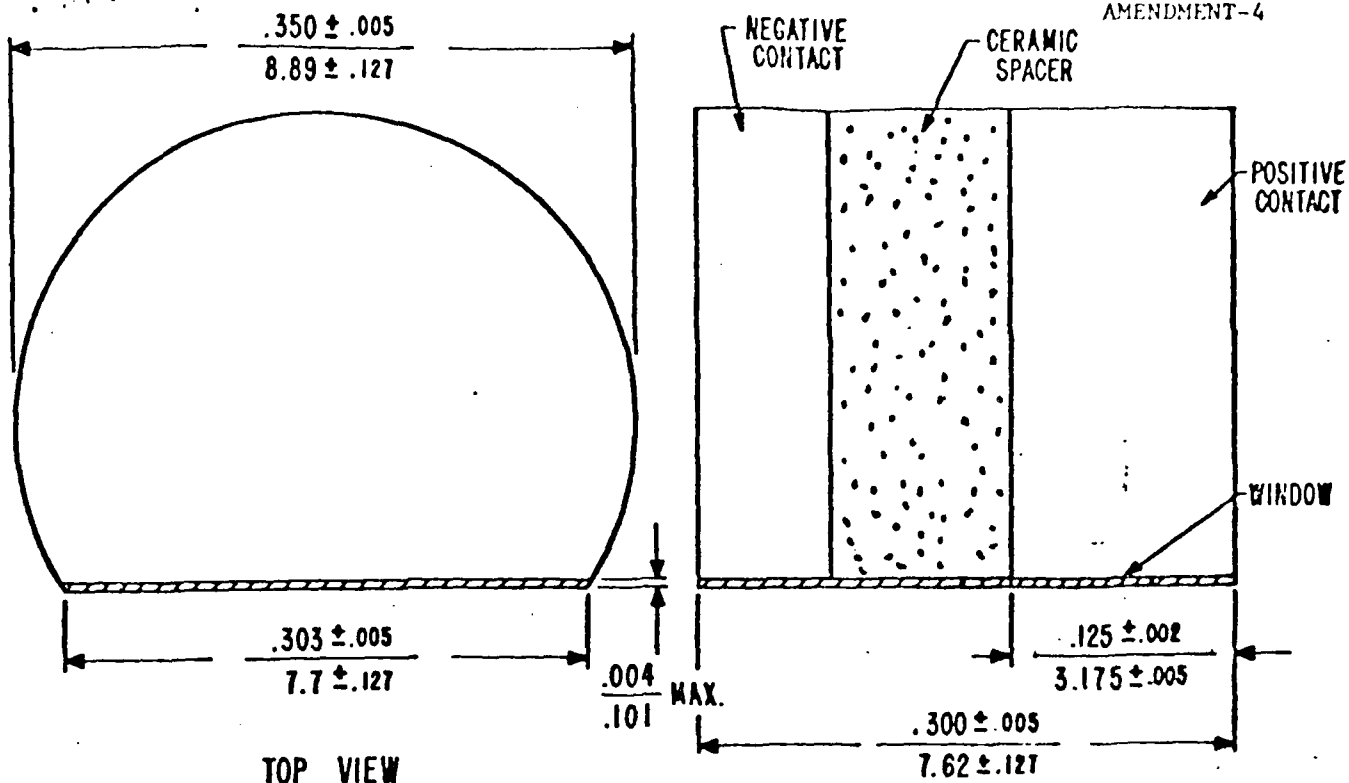
Page 17

\* Figure 4, delete in its entirety.

Page 19

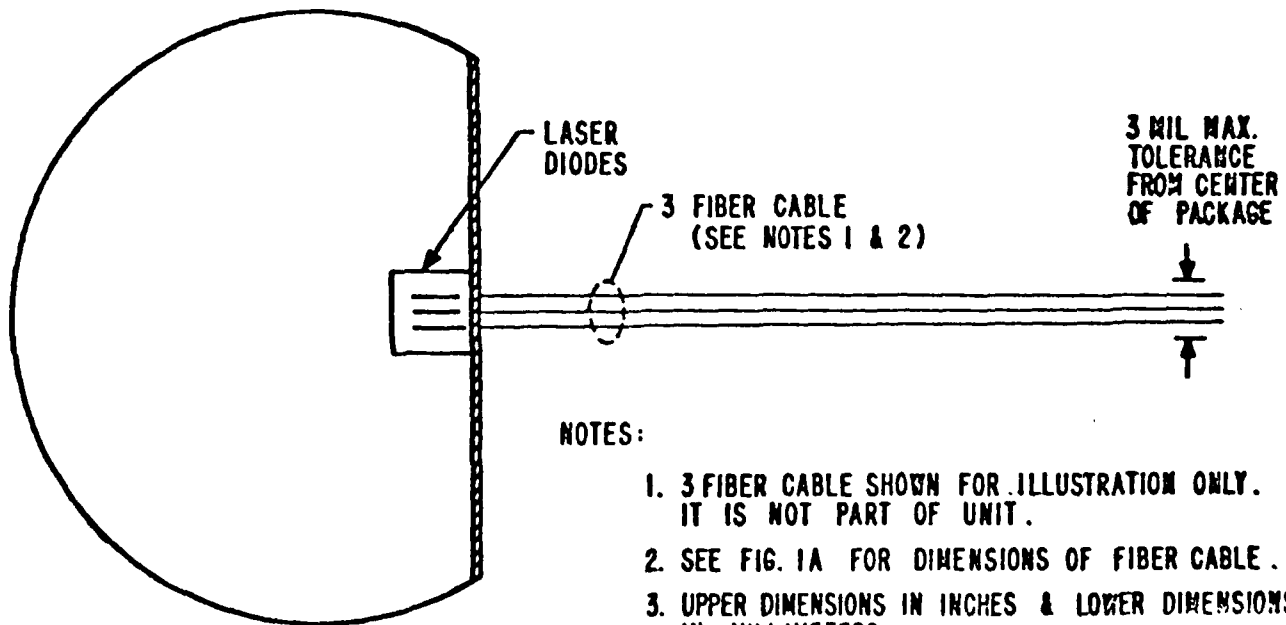
FIG 6 Front view of detector, delete "1.03 cm" and substitute "1.09 cm"  
Delete ".392 cm" and substitute ".394 cm"

NOTE: The margins of this amendment are marked with an asterisk to indicate where changes (additions, modifications, corrections, deletions) from the previous amendment were made. This was done as a convenience only and the Government assumes no liability whatsoever for any inaccuracies in these notations. Bidders and contractors are cautioned to evaluate the requirements of this document based on the entire content irrespective of the marginal notations and relationship to the last previous amendment.



TOP VIEW

SIDE VIEW  
(WITH CUTAWAY SECTION)



NOTES:

1. 3 FIBER CABLE SHOWN FOR ILLUSTRATION ONLY. IT IS NOT PART OF UNIT.
2. SEE FIG. 1A FOR DIMENSIONS OF FIBER CABLE.
3. UPPER DIMENSIONS IN INCHES & LOWER DIMENSIONS IN MILLIMETERS.

1. MODIFICATION NO. PO0002 2. EFFECTIVE DATE See Block 19 below 3. REQUISITION/PURCHASE REQUEST NO. N/A 4. PROJECT NO. (If applicable)

5. ISSUED BY COMMUNICATIONS SYSTEMS PROCUREMENT BRANCH, DIRECTORATE OF PROCUREMENT, PERCOM, FT MONMOUTH, NJ CODE W15P7T 6. ADMINISTERED BY (If other than block 5) DCASMA-Springfield CODE 240 Route 22 Springfield, NJ 07081

Buyer Symbol: Captain L'Heureux

7. CONTRACTOR NAME AND ADDRESS LASEP DIODE LABORATORIES, INC. CODE 4D351 FACILITY CODE

*(Street, city, county, state, and ZIP Code)*  
205 Forrest Street  
Metuchen, NJ 08817

8. AMENDMENT OF SOLICITATION NO.  DATED  (See block 9)

MODIFICATION OF  CONTRACT NO. DAAB07-76-C-0040 DATED 76 JUN 30 (See block 11)

9. THIS BLOCK APPLIES ONLY TO AMENDMENTS OF SOLICITATIONS

The above numbered solicitation is amended as set forth in block 12. The hour and date specified for receipt of Offers  is extended,  is not extended.

Offerors must acknowledge receipt of this amendment prior to the hour and date specified in the solicitation, or as amended, by one of the following methods:

(a) By signing and returning \_\_\_\_\_ copies of this amendment; (b) by acknowledging receipt of this amendment on each copy of the offer submitted; or (c) by separate letter or telegram which includes a reference to the solicitation and amendment numbers. FAILURE OF YOUR ACKNOWLEDGMENT TO BE RECEIVED AT THE ISSUING OFFICE PRIOR TO THE HOUR AND DATE SPECIFIED MAY RESULT IN REJECTION OF YOUR OFFER. If, by virtue of this amendment you desire to change an offer already submitted, such change may be made by telegram or letter, provided such telegram or letter makes reference to the solicitation and this amendment, and is received prior to the opening hour and date specified.

10. ACCOUNTING AND APPROPRIATION DATA (If required)  
N/A

11. THIS BLOCK APPLIES ONLY TO MODIFICATIONS OF CONTRACTS/ORDERS

(a)  This Change Order is issued pursuant to \_\_\_\_\_  
 The Changes set forth in block 12 are made to the above numbered contract/order.

(b)  The above numbered contract/order is modified to reflect the administrative changes (such as changes in paying office, appropriation data, etc.) set forth in block 12.

(c)  This Supplemental Agreement is entered into pursuant to authority of Subsection L.2 (ASPR 7-103.2 changes).  
 It modifies the above numbered contract as set forth in block 12.

12. DESCRIPTION OF MODIFICATION

I

Section H, Deliveries or Performance, and Modification A00001 dated 8 September 1977, are amended as follows:

	FROM	TO
<u>CLIN</u>		
0001AB - Confirmatory Samples-----	600	720
0001AC - Pilot Run-----	810	930
0003 (B002) Test Report on Confirmatory Samples-----	600	720
0004 (C003) Final Report-----	930	1050
0004 (C004) General Report Step II-----	930	1050
0004 (C005) Pilot Line Rate Report-----	600	720
0006 - Production Capability Demonstration-----	870	990
0007 (E001) Production Capability Demonstration Plan-----	810	930
0008 - Additional Life Testing-----	930	1050

Except as provided herein, all terms and conditions of the document referenced in block 8, as heretofore changed, remain unchanged and in full force and effect.

13.  CONTRACTOR/OFFEROR IS NOT REQUIRED TO SIGN THIS DOCUMENT  CONTRACTOR IS REQUIRED TO SIGN THIS DOCUMENT AND RETURN 1 COPY TO ISSUING OFFICE

14. NAME OF CONTRACTOR LASER DIODE LABORATORIES, INC. 17. UNITED STATES OF AMERICA

BY \_\_\_\_\_ (Signature of person authorized to sign) BY \_\_\_\_\_ (Signature of Contracting Officer)

15. NAME AND TITLE OF SIGNER (Type or print) 16. DATE SIGNED 18. NAME OF CONTRACTING OFFICER (Type or print) 19. DATE SIGNED

JOHN A. BEEKMAN

1978 MAR 20

Modification No. P00002 to:  
Contract No. DAAB07-76-C-0040

II

The consideration for this extension in Delivery Schedule is the additional tasks required to fabricate one and two stripe devices as outlined in Modification P00001 to this Contract (currently awaiting execution by Contractor).

III

Inclusion of the above changes shall be at no additional cost to the Government. All other terms and conditions of this Contract remain in effect.

**MODIFICATION OF CONTRACT**

1 7

1. MODIFICATION NO. P00003	2. EFFECTIVE DATE See Block 19 below	3. REQUISITION/PURCHASE REQUEST NO N/A	4. PROJECT NO. (If applicable)
-------------------------------	--	---	--------------------------------

5. ISSUED BY COMMUNICATIONS CODE W15P7T SYSTEMS PROCUREMENT BRANCH, DIRECTORATE OF PROCUREMENT, FT MONMOUTH, NJ 07703 Buyer/Symbol: CPT Roy L'Heureux/ DRSEL-PP-I-CC-2(LHE) Phone: 201-532-1412	6. ADMINISTERED BY (If other than block 5) DCASMA, Springfield 240 Route 22 Springfield, NJ 07081	CODE 53101A
--	--	----------------

7. CONTRACTOR NAME AND ADDRESS  LASER DIODE LABORATORIES, INC. 205 Forrest Street Metuchen, NJ 08817 <small>(Street, city, county, state, and ZIP Code)</small>	CODE 4D351	FACILITY CODE	8. AMENDMENT OF SOLICITATION NO.  DATED _____ (See block 9)  MODIFICATION OF <input checked="" type="checkbox"/> CONTRACT NO. DAAB07-76-C-0040  DATED <u>76 JUN 30</u> (See block 11)
--	---------------	---------------	--

9. THIS BLOCK APPLIES ONLY TO AMENDMENTS OF SOLICITATIONS

The above numbered solicitation is amended as set forth in block 12. The hour and date specified for receipt of Offers  is extended,  is not extended. Offerors must acknowledge receipt of this amendment prior to the hour and date specified in the solicitation, or as amended, by one of the following methods:

(a) By signing and returning \_\_\_\_\_ copies of this amendment; (b) By acknowledging receipt of this amendment on each copy of the offer submitted, or (c) By separate letter or telegram which includes a reference to the solicitation and amendment numbers. FAILURE OF YOUR ACKNOWLEDGMENT TO BE RECEIVED AT THE ISSUING OFFICE PRIOR TO THE HOUR AND DATE SPECIFIED MAY RESULT IN REJECTION OF YOUR OFFER. If, by virtue of this amendment you desire to change an offer already submitted, such change may be made by telegram or letter, provided such telegram or letter makes reference to the solicitation and this amendment, and is received prior to the opening hour and date specified.

10. ACCOUNTING AND APPROPRIATION DATA (If required)

N/A

11. THIS BLOCK APPLIES ONLY TO MODIFICATIONS OF CONTRACTS/ORDERS

(a)  This Change Order is issued pursuant to \_\_\_\_\_  
 The Changes set forth in block 12 are made to the above numbered contract/order.

(b)  The above numbered contract/order is modified to reflect the administrative changes (such as changes in paying office, appropriation data, etc.) set forth in block 12.

(c)  This Supplemental Agreement is entered into pursuant to authority of \_\_\_\_\_  
 It modifies the above numbered contract as set forth in block 12.

12. DESCRIPTION OF MODIFICATION

Contract DAAB07-76-C-0040 is changed as follows:

I

Section F, Description/Specifications, is amended as follows:

Section F.48, Subparagraph 4:

Change Commander, US Army Electronics Command, ATTN: DRSEL-CT-LD to Commander, US Army Electronics Research and Development Command, ATTN: DELNV-L-C and Commander, US Army Electronics Command, ATTN: DRSEL-PP-I-PI-1 to Commander, US Army Electronics Research and Development Command, ATTN: DELSD-D-PC.

Except as provided herein, all terms and conditions of the document referenced in block 8, as heretofore changed, remain unchanged and in full force and effect.

13.  CONTRACTOR/OFFEROR IS NOT REQUIRED TO SIGN THIS DOCUMENT  CONTRACTOR/OFFEROR IS REQUIRED TO SIGN THIS DOCUMENT AND RETURN \_\_\_\_\_ COPIES TO ISSUING OFFICE

14. NAME OF CONTRACTOR/OFFEROR	17. UNITED STATES OF AMERICA
BY _____ <small>(Signature of person authorized to sign)</small>	BY _____ <small>(Signature of Contracting Officer)</small>

15. NAME AND TITLE OF SIGNER (Type or print)	16. DATE SIGNED	18. NAME OF CONTRACTING OFFICER (Type or print) STEPHEN L. THACHER Major, Signal Corps	19. DATE SIGNED 1978 MAY 16
--	-----------------	--	--------------------------------

Modification P00003 to:  
Contract No. DAAB07-76-C-0040

Section H, Items 0001AB, B002, D001:

Change Commander, US Army Electronics Command, ATTN: DRSEL-RD-ET-2,  
Fort Monmouth, NJ 07703 to Commander, US Army Electronics  
Research and Development Command, ATTN: DELNV-L-C, Fort  
Monmouth, NJ 07703.

Section H, Items C001, C002, C004, C005, E001

Change Commander, US Army Electronics Commander, ATTN: DRSEL-PP-  
I-1, Fort Monmouth, NJ 07703 to Commander, US Army  
Electronics Research and Development Command, ATTN: DELSD-  
D-PC, Fort Monmouth, NJ 07703.

Section I, Inspection and Acceptance, is amended as follows:

Section 1.14 - Change Commander, US Army Electronics Command, ATTN:  
DRSEL-ET-LD, Fort Monmouth, NJ 07703 to Commander,  
US Army Electronics Research and Development Command,  
ATTN: DELNV-L-C, Fort Monmouth, NJ 07703.

Change Commander, US Army Electronics Command, ATTN:  
DRSEL-RD-ET-2, Fort Monmouth, NJ 07703 to Commander,  
US Army Electronics Research and Development Command,  
ATTN: DELNV-L-C, Fort Monmouth, NJ 07703.

Change Commander, US Army Electronics Command, ATTN:  
DRSEL-PP-I-PI-1, Fort Monmouth, NJ 07703 to Commander,  
US Army Electronics Research and Development Command,  
ATTN: DELSD-D-PC, Fort Monmouth, NJ 07703.

Section K, Contract Administration Data, is amended as follows:

Delete: Subsection K.2(a) in its entirety and substitute therefore:

The Purchasing Office Representative is:

NAME: CPT Roy W. L'Heureux

ORGANIZATIONAL CODE: DRSEL-PC-C-CS-2(LHE)

TELEPHONE AREA CODE AND NO.: (201)-532-1412

Section M is amended as follows:

DD 1423 Form Exhibit B, Item B002 and Exhibit D, D001:

Change Code W15P7N to W15P8S.

Modification P00003 to:  
Contract No. DAAB07-76-C-0040

II

PCO responsibility for this contract has changed as follows:

FROM

Mr. Gordon McMain  
DRSEL-PC-C-CS-1

TO:

STEPHEN L. THACHER  
Major, Signal Corps  
DRSEL-PC-C-CS-2(THA)  
Phone: (201)-532-3506



STANDARD FORM 30, JULY 1966 GENERAL SERVICES ADMINISTRATION FED. ACQ. REG. 41 CFR 101-11.6		AMENDMENT OF SOLICITATION/MODIFICATION OF CONTRACT		PAGE 1 OF 9 1 9
1. AMENDMENT/MODIFICATION NO. DAA807-76-C-0040, 00004		2. EFFECTIVE DATE See 81k 19		3. REQUISITION/PURCHASE REQUEST NO. N/A
4. PROJECT NO. (if applicable)		5. ISSUED BY USACORADCOM, Procurement Directorate Proc Div D, Ft. Monmouth, N.J. 07703 Mr. John C. Hunter/DRDCO-PC-D(HUN) (201) 532-1716		
6. ADMINISTERED BY (if other than block 5) DCASMA, Springfield 240 Route 22 Springfield, New Jersey 07081		7. CODE S3101A		
8. CONTRACTOR NAME AND ADDRESS Laser Diode Laboratories, Inc. 1130 Somerset Street New Brunswick, New Jersey 08901		9. FACILITY CODE NEW BRUNSWICK NOV 20 1980		10. AMENDMENT OF SOLICITATION NO. <input type="checkbox"/> AMENDMENT OF SOLICITATION NO. DATED _____ (See block 9)
11. MODIFICATION OF CONTRACT ORDER NO. DAA807-76-C-0040		12. DATED 76 Jun 30 (See block 11)		
13. THIS BLOCK APPLIES ONLY TO AMENDMENTS OF SOLICITATIONS				
<input type="checkbox"/> The above numbered solicitation is amended as set forth in block 12. The hour and date specified for receipt of offers <input type="checkbox"/> is extended, <input type="checkbox"/> is not extended. Offers must acknowledge receipt of this amendment prior to the hour and date specified in the solicitation, or as amended, by one of the following methods: a) By signing and returning _____ copies of this amendment. b) By acknowledging receipt of this amendment on each copy of the offer submitted, or c) By separate letter or telegram which includes a reference to the solicitation and amendment numbers. FAILURE OF YOUR ACKNOWLEDGMENT TO BE RECEIVED AT THE ISSUING OFFICE PRIOR TO THE HOUR AND DATE SPECIFIED MAY RESULT IN REJECTION OF YOUR OFFER. d) In virtue of this amendment you desire to change an offer already submitted, such change may be made by telegram or letter, provided such telegram or letter makes reference to the solicitation and this amendment and is received prior to the opening hour and date specified.				
14. ACCOUNTING AND APPROPRIATION DATA (if required) N/A				
15. THIS BLOCK APPLIES ONLY TO MODIFICATIONS OF CONTRACTS/ORDERS				
a) <input type="checkbox"/> The Change Order is issued pursuant to _____ The Changes set forth in block 12 are made to the above numbered contract/order. b) <input type="checkbox"/> The above numbered contract/order is modified to reflect the administrative changes, such as changes in paying office, appropriation data, etc.) set forth in block 12. c) <input checked="" type="checkbox"/> This Supplemental Agreement is entered into pursuant to authority of <u>Changes Provision, Subsection 1.2 of the contract.</u> It modifies the above numbered contract as set forth in block 12.				
16. DESCRIPTION OF AMENDMENT/MODIFICATION				
PROJECT: MANUFACTURING METHODS AND TECHNOLOGY PROGRAM OF INJECTION LASER DIODE FOR USE IN FIBER OPTIC COMMUNICATIONS.  I  PART II, THE SCHEDULE, SECTION E is amended as follows:  Add SLIN 0001AD to SUPPLIES/SERVICES  "0001AD Three (3) each LASER STACKS LDL Part No. IRE 167  No Cost"				
17. EXTEND AS PROVIDED HEREIN: All terms and conditions of the document referenced in block 8, as heretofore changed, remain unchanged and in full force and effect.				
18. CONTRACTOR/OFFEROR IS NOT REQUIRED TO SIGN THIS DOCUMENT <input type="checkbox"/> CONTRACTOR/OFFEROR IS REQUIRED TO SIGN THIS DOCUMENT AND RETURN TO ISSUING OFFICE <input checked="" type="checkbox"/> CODV				
19. NAME OF CONTRACTOR/OFFEROR BY Thomas E. Stockton Signature of person authorized to sign		20. UNITED STATES OF AMERICA BY Joseph E. Feeney Signature of Contracting Officer		
21. NAME AND TITLE OF SIGNER (Type or print) THOMAS E. STOCKTON V.P. ENGINEERING		22. DATE SIGNED 10 Nov 80		23. NAME OF CONTRACTING OFFICER (Type or print) JOSEPH E. FEENEY
				24. DATE SIGNED 17 NOV 1980

II

PART II, THE SCHEDULE, SECTION F, Description/Specifications, is amended as follows:

1. Subsection F.48, Subparagraph 6 - Delete this paragraph in its entirety and substitute the following:

"6. Additional Confirmatory Sample Test Requirements:

Twenty-five (25) Confirmatory Samples will be subjected to a 2000 Hour Life Test. Upon completion the samples will be retested in accordance with Table II. The Life Test and Table II (Retest) data will be incorporated into the Final Report. The Life Test samples shall be shipped to the Government upon completion of tests."

2. Add the following subparagraph to SECTION F:

"F.50 FINAL REPORT - SUPPLEMENTAL INSTRUCTIONS

The Final Report shall be prepared in accordance with the requirements as specified by CDRL C003. In addition, the report shall contain an Executive Summary, Pilot Line Rate Data, and Life Test Data."

III

PART II, THE SCHEDULE, SECTION H, Deliveries or Performance:

DELETE the contents of this Section in its entirety and SUBSTITUTE the following:

<u>CLIN/SLIN</u>	<u>ITEM</u>	<u>DELIVERY DATE</u>
0001AA	Engineering Samples Total 26 each (Lot 1 & 2).	Received & Accepted Nov 1977
0001AB	Confirmatory Samples 25 each (Lot 1).	Received & Accepted 3 July 1979.
	25 each (Lot 2) (Life Test Units)	Not Later Than 27 Feb 1981

Contract No. DAAB07-76-C-0040  
Modification No. P00004  
Laser Diode Laboratories, Inc.  
Page No. 3 of 9

REVISED DELIVERY OR PERFORMANCE SCHEDULE (Continued)

<u>CLIN/SLIN</u>	<u>ITEM</u>	<u>DELIVERY DATE</u>
0001AC	Pilot Run Samples 50 each Single Stripe Units 50 each Double Stripe Units 200 each Triple Stripe Units	Received & Accepted 15 Aug 1980 Received & Accepted 24 Sep 1980 5 Dec 1980
0001AD	LASER STACKS - 3 each	Not Later Than 27 Feb 1981
0002/A001	PERT	Received & Accepted
0003/B001	Engineering Sample Test Report (For Lots 1 & 2)	Received & Accepted
0003/B002	Confirmatory Sample Test Report (For Lots 1 & 2 except Life Test)	Received & Accepted
0004/C001	Monthly Technical Reports Reports for July 1976 thru Sep 1980 Oct 1980 Report Nov 1980 Report Dec 1980 Report	Received & Reviewed Not Later than 10 Nov 1980 Not Later than 10 Dec 1980 Not Later than 10 Jan 1981
0004/C002	Quarterly Reports Reports for Sep 1976 thru Aug 1980 Oct 1980 Report	Received & Reviewed Not Later Than 10 Nov 80
0004/C003	Final Report Draft Final	14 Nov 1980 27 Feb 1981

Contract No. DAAB07-76-C-0040  
 Modification No. P00004  
 Laser Diode Laboratories, Inc.  
 Page No. 4 of 9

REVISED DELIVERY OR PERFORMANCE SCHEDULE (Continued)

<u>CLIN/SLIN</u>	<u>ITEM</u>	<u>DELIVERY DATE</u>
0004/C004	General Report - DELETED (Incorporated as "Executive Summary" in Final Report)	--
0004/C005	Pilot Line Rate Report - DELETED (Incorporated in the Final Report)	--
0005/D001	Test Plan (Confirmatory Sample)	Received & Accepted
0006	Production Capability Demonstration	11 Feb 1981
	Draft Invitation Letter	12 Dec 1980
	Industry Invitation Letters (Mailed By)	16 Jan 1981
0007/E001	Production Capability Demonstration Plan	
	Draft	12 Dec 1980
	Final	16 Jan 1981
0008AA	Life Tests	Completion Not Later Than 20 Feb 1981

IV

PART II, THE SCHEDULE, SECTION I - Inspection and Acceptance -

DELETE the contents of this Section in its entirety and SUBSTITUTE the following:

"I.14 INSPECTION AND ACCEPTANCE

<u>CLIN/SLIN</u>	<u>ITEM</u>	<u>FINAL INSPECTION/ACCEPTANCE PERFORMED BY: *</u>
0001AA	Engineering Samples	Received & Accepted
0001AB	Confirmatory Samples	
	Lot 1	Received & Accepted
	Lot 2 (After Life Test)	DELIV-L

Contract No. DAAB07-76-C-0040  
Modification No. P00004  
Laser Diode Laboratories, Inc.  
Page No. 5 of 9

INSPECTION AND ACCEPTANCE (Continued)

<u>CLIN/SLIN</u>	<u>ITEM</u>	<u>FINAL INSPECTION/ACCEPTANCE PERFORMED BY: *</u>
0001AC	Pilot Run Samples Single Stripe Units Double Stripe Units Triple Stripe Units	Received & Accepted Received & Accepted DELNV-L
0001AD	Laser Stack Units	DELNV-L
0002/A001	PERT	Received & Accepted
0003/B001	Engineering Sample Test Report	Received & Accepted
0003/B002	Confirmatory Sample Test Report	Received & Accepted
0004/C001	Monthly Technical Reports Oct/Nov/Dec 1980 Reports	DELNV-L
0004/C002	Quarterly Reports Oct 1980 Report	DELNV-L
0004/C003	Final Report Draft Final	DELNV-L DELNV-L
0005/D001	Test Plan (Confirmatory Sample)	Received & Accepted
0006	Production Capability Demonstration Draft Invitation Letter	DELNV-L DRDCO-PC-D
0007/E001	Production Capability Demonstration Plan Draft Final	DELNV-L DELNV-L
0008AA	Life Tests	DELNV-L

\*Responsibility codes used are not to be construed as full address identifiers. Full addressees and "SHIP TO" data cited below.

Contract No. DAAB07-76-C-0040  
Modification No. P00004  
Laser Diode Laboratories, Inc.  
Page No. 6 of 9

INSPECTION AND ACCEPTANCE (Continued)

Verification of the capability of the contractor to fabricate the devices at the specified rate for the pilot run will be performed at the factory of the contractor during performance of the pilot run by:

\*DELNV-L and/or DRDCO-COM-RM-1

Inspection and Acceptance of the Devices under SLIN 0001AC Triple Stripe Units (pilot run) will be performed at the factory of the contractor by:

\*DCASMA

Final Inspection and Acceptance of the Production Capability Demonstration, CLIN 0006, will be made at time of demonstration by:

\*DELNV-L and/or DRDCO-COM-RM-1 and/or DRDCO-PC-D

Location of demonstration will be as mutually agreed by the contractor and the Contracting Officer prior to Invitation Letter issuance.

Inspection and Acceptance of SLIN 0008AA will be performed at the factory of the contractor by:

\*DCASMA and/or DRDCO-COM-RM-1

Address listings with "SHIP TO" or "MARKED FOR" data shall be used when shipping hardware or software (data) items.

For Code DELNV-L:

SHIP TO:

Property Officer, USA MERADCOM  
Bldg 335  
Fort Belvoir, VA 22060

MARKED FOR:

Commander  
USA ERADCOM  
ATTN: DELNV-L (Mr. Skeldon)  
Fort Belvoir, VA 22060

Contract No. DAAB07-76-C-0040  
Modification No. P00004  
Laser Diode Laboratories, Inc.  
Page No. 7 of 9

INSPECTION AND ACCEPTANCE (Continued)

For Code DRDCO-COM-RM-1:

Commander  
USA CORADCOM  
CENCOMS  
ATTN: DRDCO-COM-RM-1 (Mr. L. Coryell)  
Fort Monmouth, New Jersey 07703

For Code DRDCO-PC-D:

Commander  
USA CORADCOM  
Procurement Directorate  
ATTN: DRDCO-PC-D (Mr. J. C. Hunter)  
Fort Monmouth, New Jersey 07703

For Code DCASMA:

DCASMA, Springfield  
240 Route 22  
Springfield, New Jersey 07681  
ATTN: DCRNGSCC-S4 (Mr. J. Martorano)  
Contract DAAB07-76-C-0040"

V

PART II, THE SCHEDULE, SECTION K, CONTRACT ADMINISTRATION DATA, is amended as follows:

1. Subsection K.1, PLACE OF PERFORMANCE, subparagraph 1, DELETE in its entirety and SUBSTITUTE the following:

"1. The work called for herein will be performed by the contractor at the following locations:

<u>ITEM NO.</u>	<u>LOCATION OF</u>	
All	Final Manufacture	New Brunswick, New Jersey 08901
	Packaging and Packing	New Brunswick, New Jersey 08901
	Shipping Point	New Brunswick, New Jersey 08901

Contract No. DAAB07-76-C-0040  
Modification No. P00004  
Laser Diode Laboratories, Inc.  
Page No. 8 of 9

CONTRACT ADMINISTRATION DATA (Continued).

<u>ITEM NO.</u>	<u>LOCATION OF</u>
	Producing Facilities Locations
	Laser Diode Laboratories, Inc., Owner 1130 Somerset Street New Brunswick, New Jersey 08901 105 Forrest Street Metuchen, New Jersey 08817

Contractor's office which will receive payment, supervise and administer the contract:

1130 Somerset Street  
New Brunswick, New Jersey 08901"

2. Subparagraph K.2, subparagraph a., DELETE in its entirety and SUBSTITUTE the following:

"Name: John C. Hunter  
Organization: USA CORADCOM  
Procurement Directorate  
Attn: DRDCO-PC-D(HUN)  
Fort Monmouth, New Jersey 07703  
Telephone No.: (201) 532-1716/3306  
Autovon No.: 992-1716/3306"

VI

PART IV, SECTION M is amended as follows:

DD Form 1423 Data Requirements, pages 51 through 56 revised - copies attached.

VII

The consideration for this extension in delivery is the additional tasks required to fabricate CLIN 0001AD items.



Contract No. DAAB07-76-C-0040  
Modification No. P00004  
Laser Diode Laboratories, Inc.  
Page No. 9 of 9

VIII

PCO responsibility for this contract has changed as follows:

FROM: Stephen L. Thacher  
Major, Signal Corps  
DRSEL-PC-C-CS-2 (THA)  
Phone (201) 532-3506

TO: Joseph E. Feeney  
Contracting Officer  
United States of America  
Phone (201) 532-1716

IX

Inclusion of the above changes shall be at no additional cost to the Government. All other terms and conditions of this contract remain unchanged and in effect.

Initiating Activity: CORADCOM/CENCOMS  
Prev Allot No.: 2162035 6627510 P5297 2510 S28043  
JCH/gms

APPENDIX C

DISTRIBUTION LIST

RCA Laboratories  
David Sarnoff Research Center  
Princeton, NJ 08540  
ATTN: Dr. M. Ettenberg

Rockwell International  
1049 Camino Dos Rios  
PO Box 1085  
Thousand Oaks, CA 91360  
ATTN: Dr. P.D. Dapkus

TRC  
Technology Research Center  
2525 East El Segundo Blvd  
El Segundo, CA 90245  
ATTN: H.D. Law

Varian  
Central Research Laboratories  
611 Hansen Way  
Palo Alto, CA 94303  
ATTN: Dr. R. L. Bell

Commander  
EPADCOM, NV & EO Laboratory  
ATTN: DELNV-1 (Mr. M. Skeldon)  
Fort Belvoir, VA 22060  
(5 Copies)  
Commander  
Naval Ocean Systems Center  
ATTN: Dr. H. Weider (Code 922)  
San Diego, CA 92152

Lasertron, Inc.  
8 Alfred Circle  
Bedford, MA 01730  
ATTN: Dr. J.L. Mason

Reliability Analysis Center  
ATTN: RBRAC (Mr. I. Krulac)  
Griffiss AFB, NY 13441

Commander, Rome Air Development Center  
ATTN: RADC/DCCT (Mr. P. Sierak)  
Griffiss AFB, NY 13441

Tri-Tac Office  
ATTN: TT-DA (Mr. C. Arnold)  
Fort Monmouth, NJ 07703

Advisory Group on Electron Devices  
ATTN: Secy, Working Group D(Lasers)  
201 Varick Street  
New York, NY 10014

Commander  
US Army Satellite Communications Agency  
Fort Monmouth, NJ 07703  
ATTN: DRCPM-SC-3

Commander  
US Army Avionics Research and  
Development Activity  
ATTN: DAVAA-D  
Fort Monmouth, NJ 07703

Raytheon Company  
Communications Systems Directorate  
Equipment Division  
528 Boston Post Road  
Sudbury, MA 01776  
ATTN: Mr. T. Kelly

ITT Electro-Optical Products Div  
7635 Plantation Road  
Roanoke, VA 24019  
ATTN: Mr. R. McDevitt

Hughes Aircraft Corp  
Tucson Systems Engrg. Dept.  
PO Box 8  
Tucson, AZ 85734  
ATTN: Mr. D. Fox

General Optronics Corp  
3005 Hadley Road  
South Plainfield, NJ 07080  
ATTN: P.W. Hankin

Motorola, Inc.  
High Frequency and Optical Products Div  
5005 East McDowell Road  
Phoenix, AZ 85008  
ATTN: J.C. Herman

The Plessey Company, LTD  
Allen Clark Research Center  
Caswell, Towcester  
Northants, England **NN12 8EQ**  
ATTN: R. Davis

Commander  
Naval Ocean Systems Center  
Code 4400  
San Diego, CA 92152  
Attn: Mr. R. Lebuska

Commander  
Naval Ocean Systems Center  
Attn: Library  
San Diego, CA 92152

Harris Government Comm Systems Div.  
P.O. Box 37  
Melbourne, FL 32901  
Attn: Mr. R. Tainter

ITT Defense Communications Division  
492 River Road  
Nutley, NJ 07110  
Attn: Dr. P. Stevens

GTE Products Corp  
Communications System Division  
189 F Street  
Needham Heights, MA 02194

Commander  
Naval Avionics Facility  
Code D831  
Indianapolis, IN 46218  
Attn: Mr. R. Katz

Mitre Corp.  
P.O. Box 208  
Bedford, MA 01730  
Attn: Mr. R. Hazel

National Bureau of Standards  
Electromagnetic Tech Div  
Boulder, CO 80303  
Attn: Dr. G. Day

Defense Logistics Agency  
Attn: DESC-EMI (Mr. A. Hudson)  
Dayton, OH 45444

Commander  
Air Force Avionics Laboratory  
Attn: AFAL/AAD-2 (Mr. K. Trumble)  
Wright-Patterson AFB, OH 45433

CDR, US Army Signals Warfare Lab  
Attn: DELSW-OG  
Arlington Hall Station  
Arlington, VA 22212

CDR, US Army Signals Warfare Lab  
Attn: DELSW-AN  
Arlington Hall Station  
Arlington, VA 22212

Commander  
US Army Logistics Center  
Attn: ATCL-NE  
Fort Lee, VA 22001

Commander  
US Army Training & Doctrine Command  
Attn: ATCD-TEC  
Fort Monroe, VA 23651

Commander  
US Army Training & Doctrine Command  
Attn: ATCD-TM  
Fort Monroe, VA 23651

NASA Scientific & Tech Info Facility  
Baltimore/Washington Intl Airport  
P.O. Box E757  
Baltimore, MD 21240

Commander  
ERADCOM  
Fort Monmouth, NJ 07703  
Attn: DELMT-D

Commander  
ERADCOM  
Fort Monmouth, NJ 07703  
Attn: DELSD-LS

Commander  
CECOM  
Fort Monmouth, NJ 07703  
Attn: DRSEL-COM-D

CDR, US Army Research Office  
Attn: DPRO-IP  
P.O. Box 12211  
Research Triangle Park, NC 27709

Commander  
CECOM  
Fort Monmouth, NJ 07703  
Attn: DRSEL-SEI

Director  
N.S. Army Material Systems Analysis Actr.  
Attn: DRMSY-MP  
Aberdeen Proving Ground, MD 21005

Commander  
CECOM  
Fort Monmouth, NJ 07703  
ATTN: DRSEL-COM-RM-1 (Mr. L. Coryell)  
(8 copies)

Advisory Group in Electron Devices  
201 Varick Street, 9th Floor  
New York, NY 10014

DISTRIBUTION LIST

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 Fort George G. Meade, MD 20755

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 Reston, VA 22090

Defense Communications Agency  
 Technical Library Center  
 Code 205 (P.A. Tolovi)  
 Washington, DC 20305

Office of Naval Research  
 Code 427  
 Arlington, VA 22217

GIDEP Engineering & Support Dept.  
 TE Section  
 P.O. Box 398  
 Norco, CA 91760

CDR, MICOM  
 Redstone Scientific Info Center  
 Attn: Chief, Document Section  
 Redstone Arsenal, AL 35809

Commander  
 HQ Fort Huachuca  
 Attn: Technical Reference Div  
 Fort Huachuca, AZ 85613

Commander  
 US Army Electronic Proving Ground  
 Attn: STEEP-MT  
 Fort Huachuca, AZ 85613

Commander  
 USASA Test & Evaluation Center  
 Attn: IAO-COR-T  
 Fort Huachuca, AZ 85613

Director  
 Naval Research Laboratory  
 Attn: Code 2627  
 Washington, DC 20375

Command, Control & Communications Div.  
 Development Center  
 Marine Corps Development & Educ Comd  
 Quantico, VA 22134

Naval Telecommunications Command  
 Technical Library, Code 911  
 4401 Massachusetts Avenue, NW  
 Washington, DC 20390

Rome Air Development Center  
 Attn: Documents Library (TILD)  
 Griffiss AFB, N.Y. 13441

HQDA (DAMP-ARP/DR. F.D. Vanderamo)  
 Washington, DC 20310

Director  
 US Army Human Engineering Lab  
 Aberdeen Proving Ground, MD 21005

CDR, AVREDCOM  
 Attn: DRFAV-E  
 P.O. Box 209  
 St. Louis, MO 63166

Director  
 Joint Com Office (TRI-TAC)  
 Attn: TP-AD (Tech Docu Cen)  
 Fort Monmouth, NJ 07703

Dir., US Army Air Mobility R&D Lab  
 Attn: T. Gossett, Bldg. 207-5  
 NASA Ames Research Center  
 Moffett Field, CA 94035

HQDA (DAMI-TNE)  
 Washington, DC 20310

Deputy for Science & Technology  
 Office, Asst Sec Army (ASD)  
 Washington, DC 20310

Commander, DARCOM  
 Attn: DRTEE  
 5001 Eisenhower Avenue  
 Alexandria, VA 22303

END

DATE  
FILMED

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DTIC